



**HAL**  
open science

# Reactions at surfaces. Plasma Reactivity and Nanoparticles. Insights using Molecular Dynamics simulations

Pascal Brault

► **To cite this version:**

Pascal Brault. Reactions at surfaces. Plasma Reactivity and Nanoparticles. Insights using Molecular Dynamics simulations. Master. Germany. 2021. hal-03572683

**HAL Id: hal-03572683**

**<https://hal.science/hal-03572683>**

Submitted on 14 Feb 2022

**HAL** is a multi-disciplinary open access archive for the deposit and dissemination of scientific research documents, whether they are published or not. The documents may come from teaching and research institutions in France or abroad, or from public or private research centers.

L'archive ouverte pluridisciplinaire **HAL**, est destinée au dépôt et à la diffusion de documents scientifiques de niveau recherche, publiés ou non, émanant des établissements d'enseignement et de recherche français ou étrangers, des laboratoires publics ou privés.



# Reactions at surfaces

## Plasma Reactivity and Nanoparticles

### Insights using Molecular Dynamics simulations

**Pascal Brault**

*GREMI, UMR7344 CNRS Université d'Orléans,  
Orléans, France*

[pascal.brault@univ-orleans.fr](mailto:pascal.brault@univ-orleans.fr)

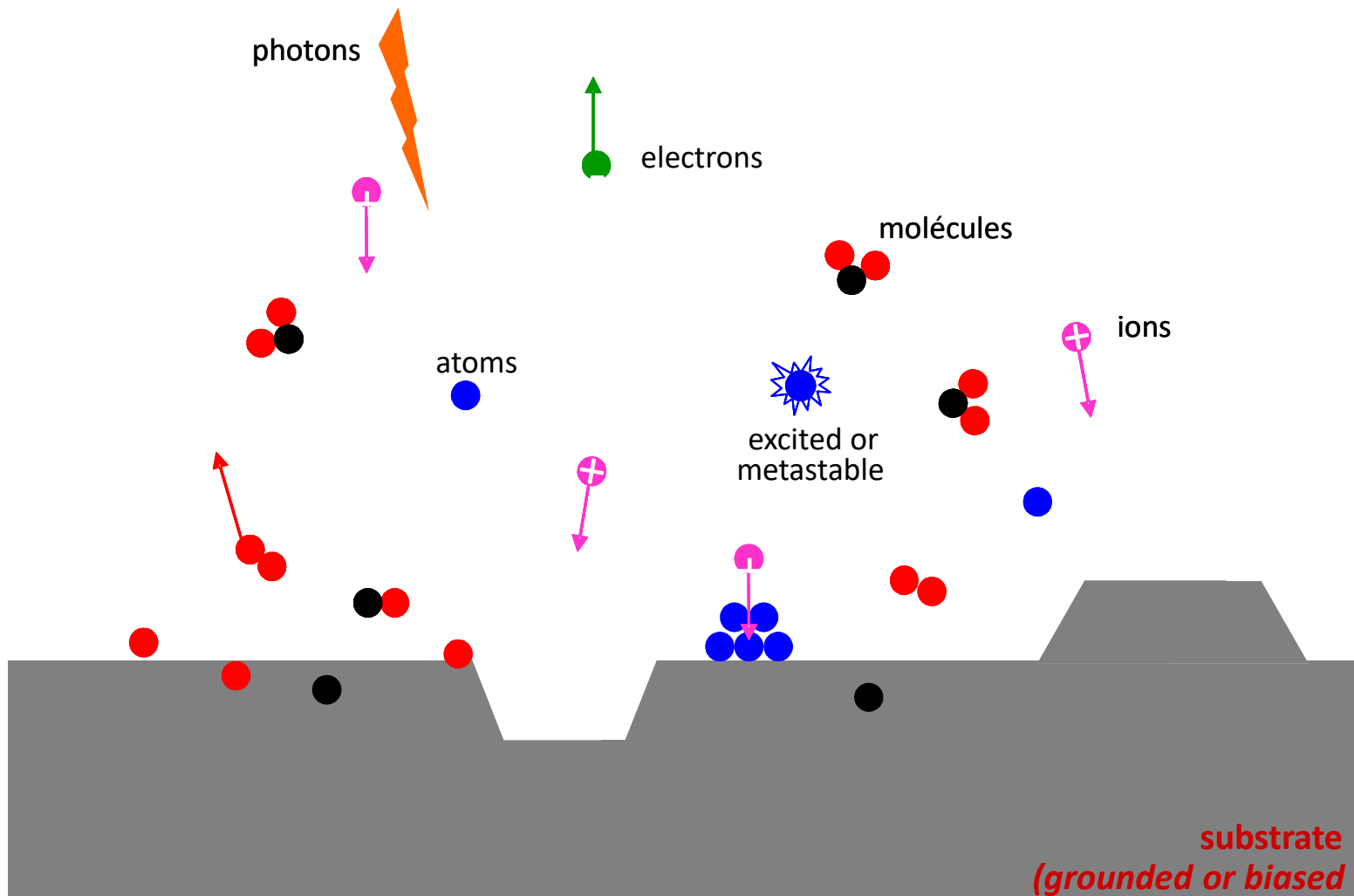
<http://www.univ-orleans.fr/gremi/pascal-brault>



# Reactions at surfaces



Which reaction pathways ?  
How to identify them ?



# Which species?

## Electrons

:  $E = 1 \text{ eV} - 6 \text{ eV} \rightarrow \text{keV} \rightarrow \text{MeV} \rightarrow \text{GeV}$   
plasmas materials  $\rightarrow$  e- beams  $\rightarrow$  Tokamaks  $\rightarrow$  CERN  
treatments

## Photons

: plasmas – photochemistry – laser treatments

## Atoms

:  $1 - 20 \text{ eV}$  :  $\text{d}\acute{\text{e}}\text{p}\acute{\text{o}}\text{sition}$  – etching – surface treatments  
(fundamental or metastable states)

## Molecules & clusters

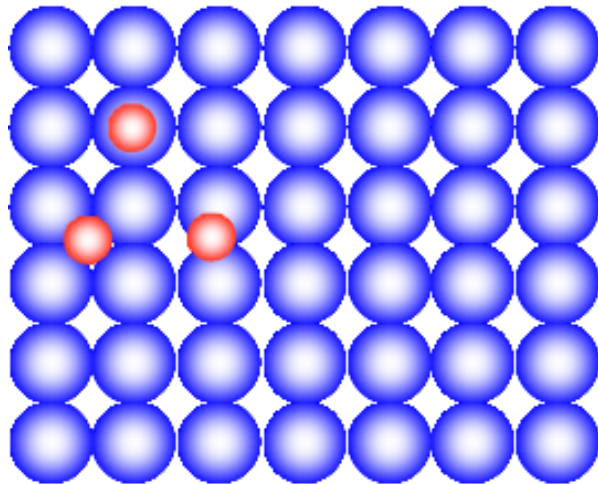
:  $1 - 20 \text{ eV}$  :  $\text{r}\acute{\text{e}}\text{a}^{\text{c}}\text{t}\text{i}\text{v}\acute{\text{e}}\text{t}\acute{\text{e}}$  -  $\text{d}\acute{\text{e}}\text{p}\acute{\text{o}}\text{t}\text{s}$  – gravure – traitements de surface  
(fundamental ou electronicv – vibra<sup>l</sup> – rota<sup>l</sup> excit ed states)

## Ions

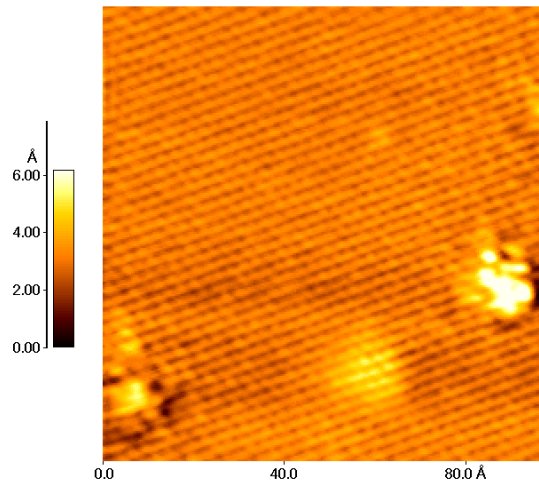
:  $1 \text{ eV} - 1 \text{ keV} \rightarrow 10 \text{ keV} - 10 \text{ MeV}$   
plasmas & ion beams implantations  
materials Tokamaks (fusion devices)

# Which Surfaces ?

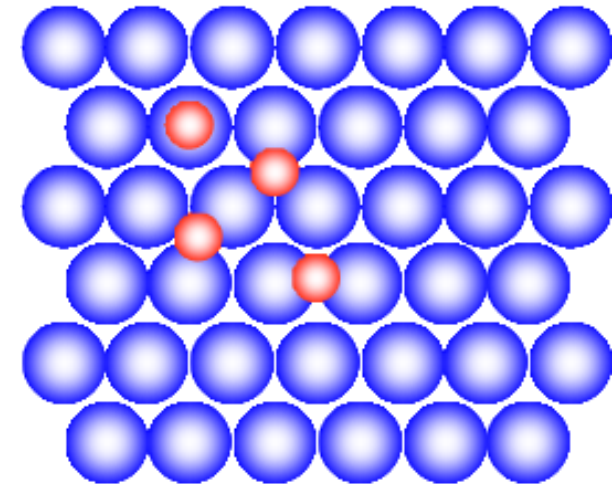
## Ordered



fcc (100)

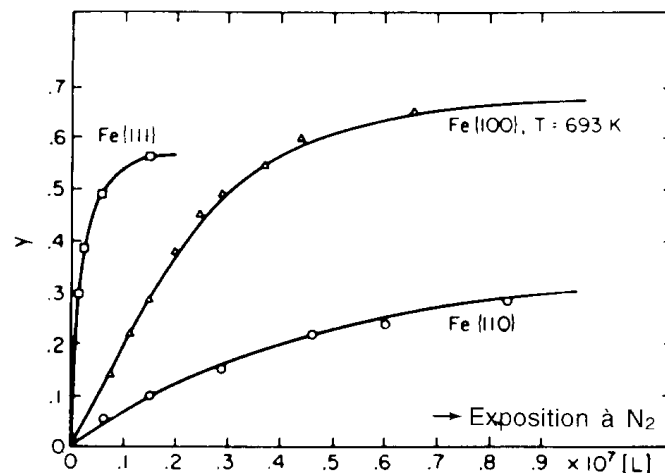


C(0001)



fcc (111)

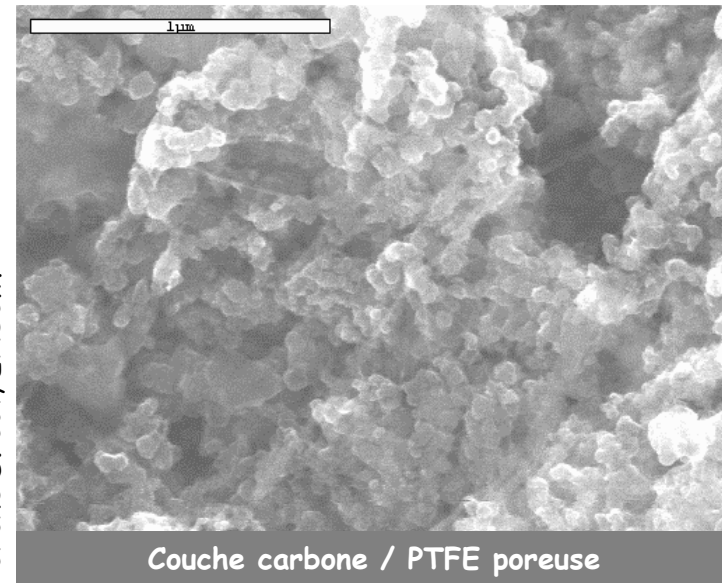
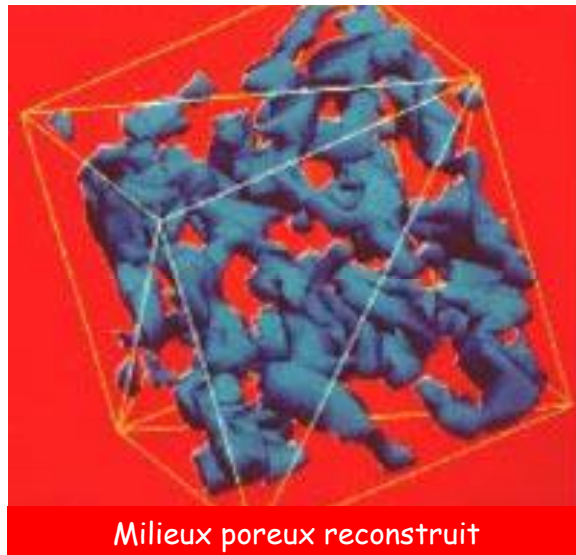
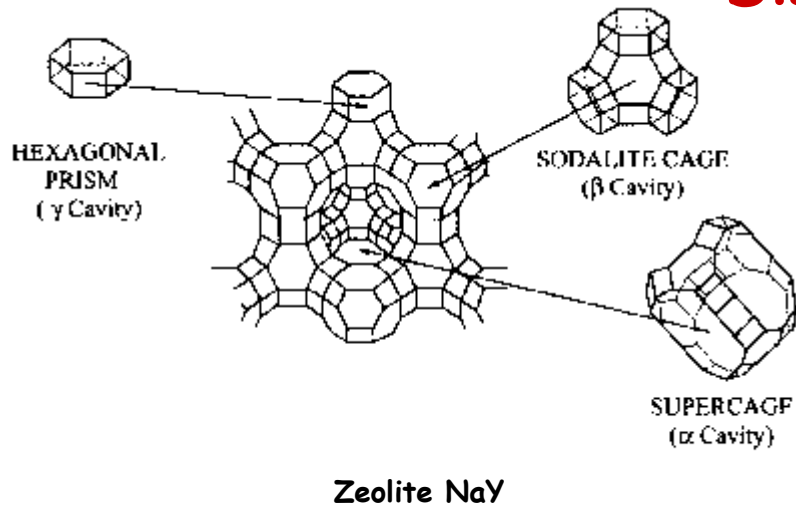
**Surface structure  $\Rightarrow$  reaction sites  $\Rightarrow$  Reactivity**



**Figure 7.16.** Variations de la concentration superficielle relative,  $y$ , en azote atomique en fonction de l'exposition à N<sub>2</sub> [33]. 1 L (Langmuir) =  $1,333 \cdot 10^{-4}$  Pa · s ( $10^6$  torr · s).

# Which surfaces ?

Complex ordered  
Disordered

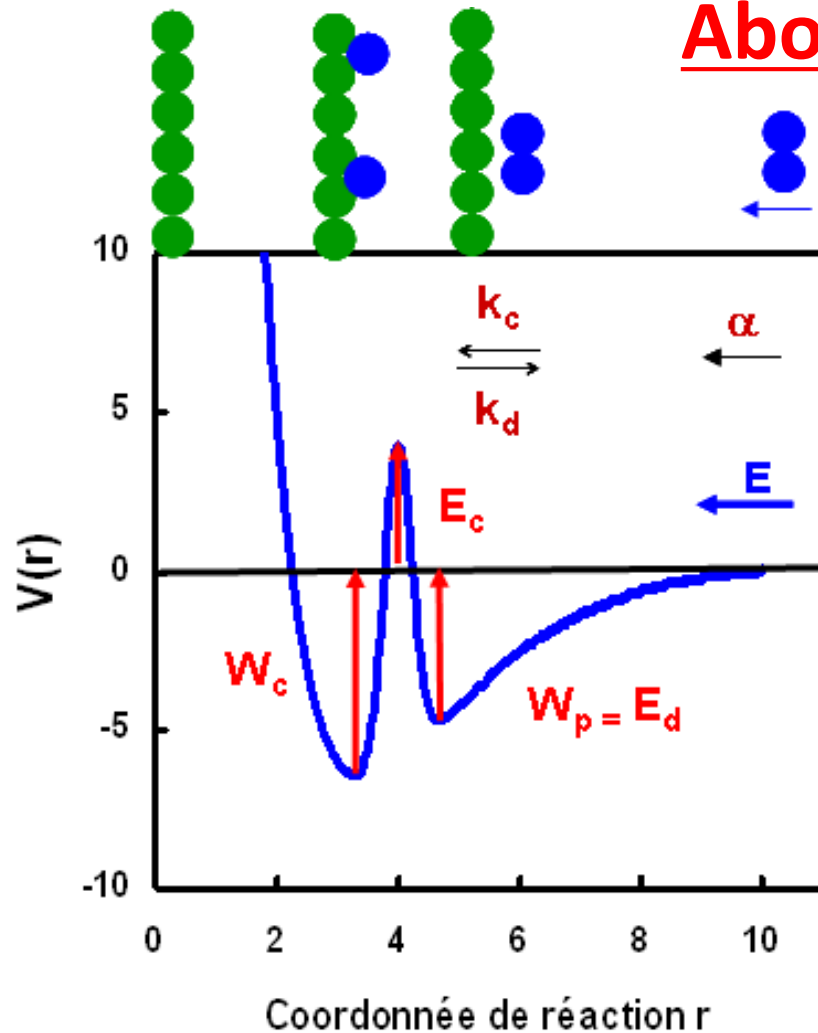


# Adsorption

## Surface mechanism quick picture

- ✓ Transport to surface (Boundary layer at high pressure)
- ✓ Sticking
- ✓ Reactants diffusion at surface
- ✓ Adsorption of one or many reactants at surface
- ✓ Reactions at surface
- ✓ Product desorption from surface
- ✓ Transport outwards surface (Boundary layer at HP)

# About Sticking



Sticking coefficient  $S_{0p}$   
(physisorption)  
 $E < 1.5 - 2 E_c$

$$S_0 = \alpha \frac{k_c}{k_c + k_d}$$

$$k_d = v_d \exp\left(-\frac{E_d}{kT_s}\right)$$

$$k_c = v_c \exp\left(-\frac{E_c + E_d}{kT_s}\right)$$

$$S_0 = \frac{\alpha}{1 + \left(\frac{v_d}{v_c}\right) \exp\left(\frac{E_c}{kT_s}\right)}$$

$W_c$  : Chemisorption well  
 $W_p$  : Physisorption well  
 $E_c$  : Barrier to chemisorption  
 $E_d$  : Desorption energy

$k_c$  : Chemisorption rate  
 $k_d$  : Desorption rate  
 $\alpha$  : Physisorption probability  
 $T_s$  : Surface temperature



# About sticking (more complicated)

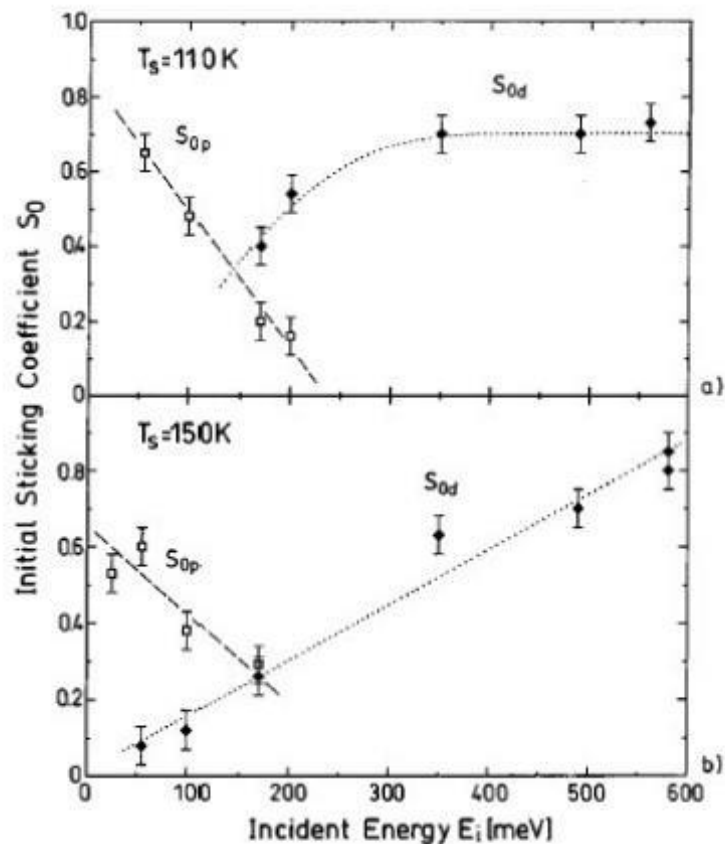


FIG. 6. The initial sticking coefficient  $S_0$  of  $O_2$  on Rh(111) as a function of the incident beam energy  $E_i$  for an angle of incidence of  $\theta_i = 0^\circ$  and two surface temperatures (a)  $T_s = 110$  K and (b)  $T_s = 150$  K. The filled symbols ( $\blacklozenge$ ) indicate  $S_{0d}$  and the open symbols ( $\square$ ) indicate  $S_{0p}$ . The error bars have been estimated from the  $S(t)$  curves similar to those in Fig. 4. The curves are shown to guide the eye.

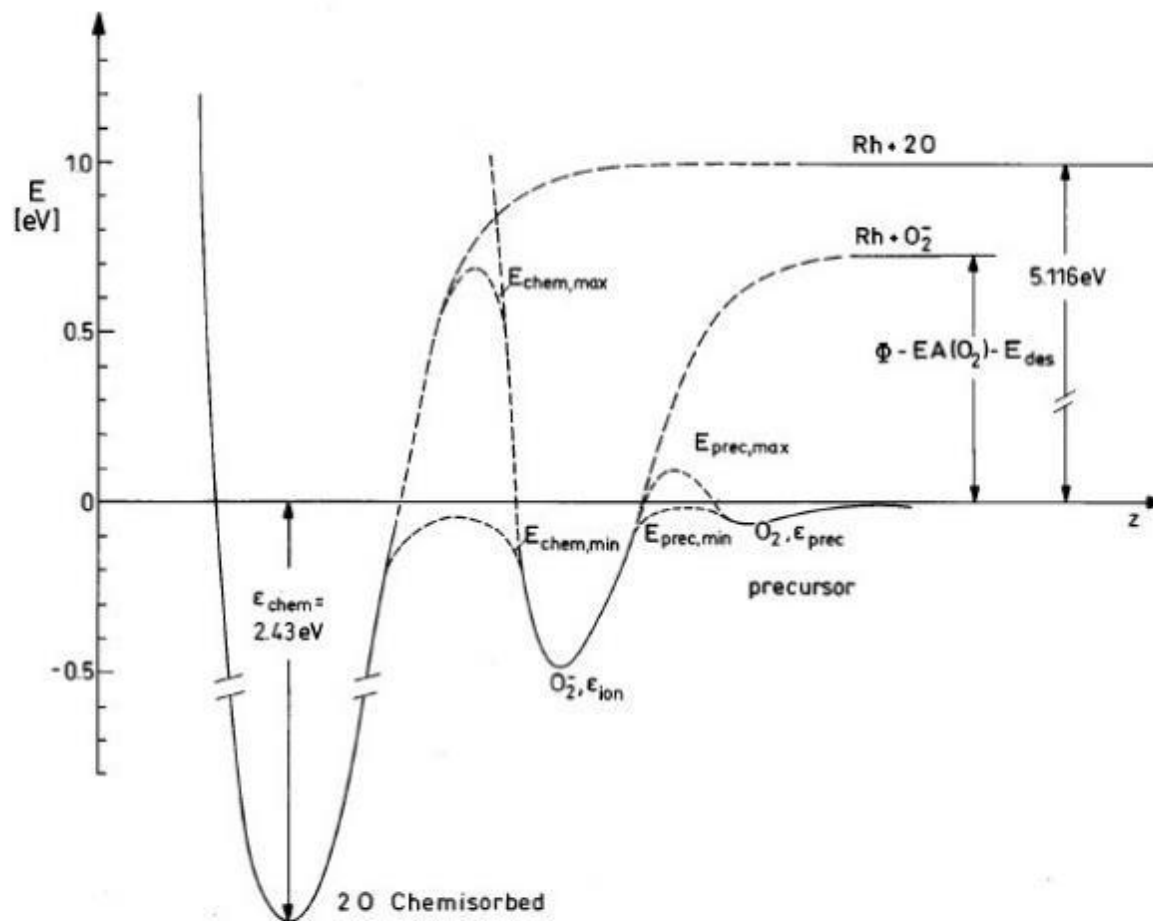


FIG. 7. Schematic diagram of a one-dimensional potential energy surface for the oxygen adsorption on Rh(111) based on the model proposed for  $O_2$  on (111) Ref. 16.  $E_{prec}$  and  $E_{chem}$  represent the barrier heights for trapping in the precursor state and for direct dissociative chemisorption, respectively. The fictive maximum and minimum values of the barriers are indicated.  $\epsilon_{prec}$ ,  $\epsilon_{ion}$ , and  $\epsilon_{chem}$  are the well depths of the precursor, ion-resonance, and associative chemisorbed states. The dissociation energy, binding energy  $\epsilon_{chem}$ , and the electron affinity of molecular oxygen on Rh(111) are taken from the literature (Refs. 23 and 27).

Sticking coefficient  $\rightarrow$  Interaction potential

# Electrons et photons

## Electrons

Electrons low energy repelled by negatively biased sheath.

Electrons high not concerned by reactivity

Main effect → attachment on adsorbed atom/molecule

insulating surfaces : polymères, oxides, ...: a bit brittle

maximum transferred energy during elastic collision:

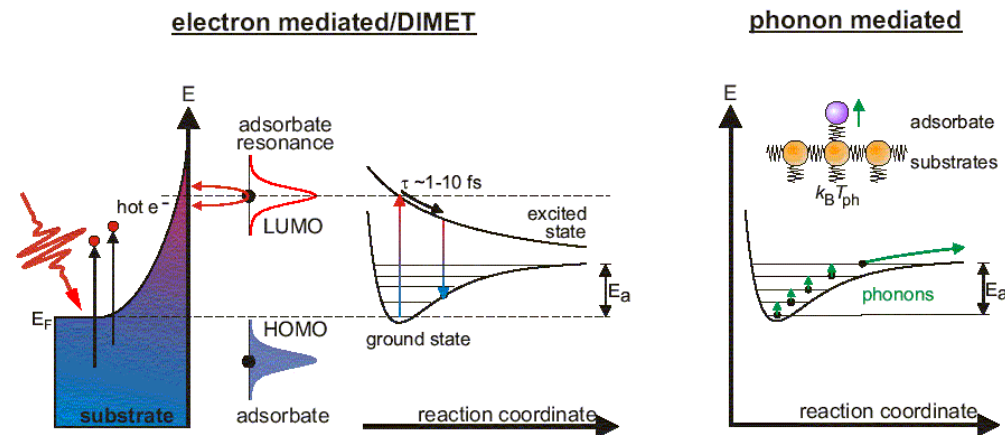
$$\Delta E_{\max} \approx 4 \frac{m_{e^-}}{M} E_{e^-} \ll E_{e^-}$$

Atom displacement => for having 10eV transferred =>  $E_{e^-} = 100\text{keV}$

## Photons

Substrate coupling

Weak direct effects on adsorbed species

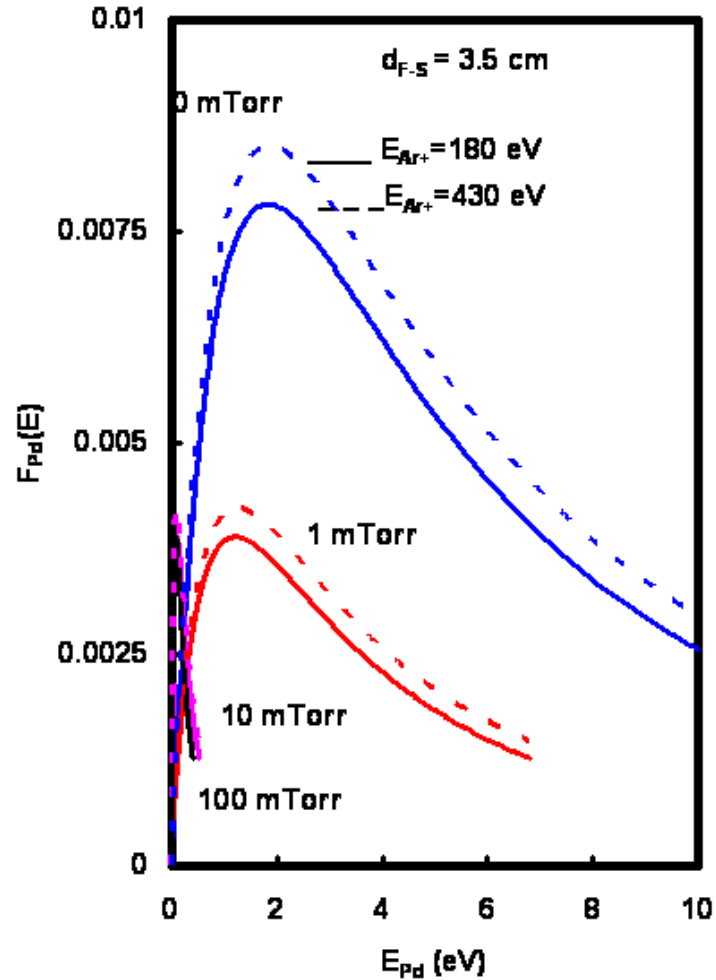


# Atom-Surface: initial conditions

## Atom sources:

vapor at  $T_g$  (gas or evaporation : dist. MB),  
 molecular beam ( $E_c \approx 0.01 - 10 \text{ eV} + T_g$ )  
 ou sputtered matter

- ion : Thompson distribution
- laser : ?



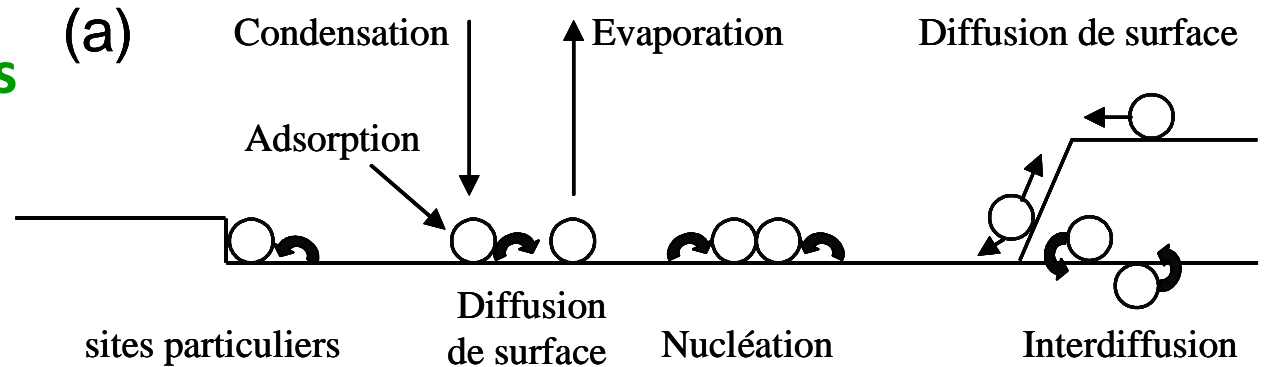
$$f(E) \propto \frac{1 - \left( \frac{E_{coh} + E}{\Lambda E_{Ar^+}} \right)^{\frac{1}{2}}}{E^2 \left( 1 + \frac{E_{coh}}{E} \right)^3}$$

Pressure effect on distribution :

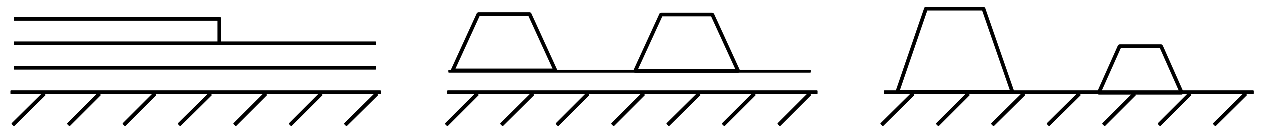
$P \nearrow f(E) \rightarrow \text{MB}, \forall f(E) \text{ et donc } \langle E \rangle \searrow$

# Atom-Surface : Growth

## Atom – Surface interactions



## Growth mode

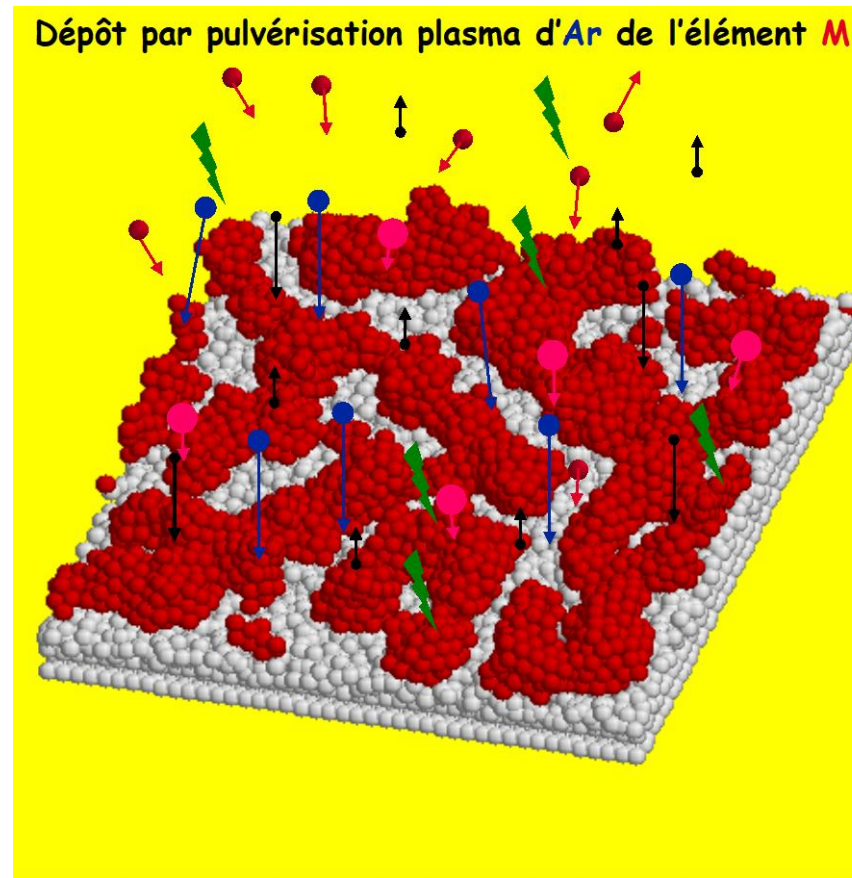
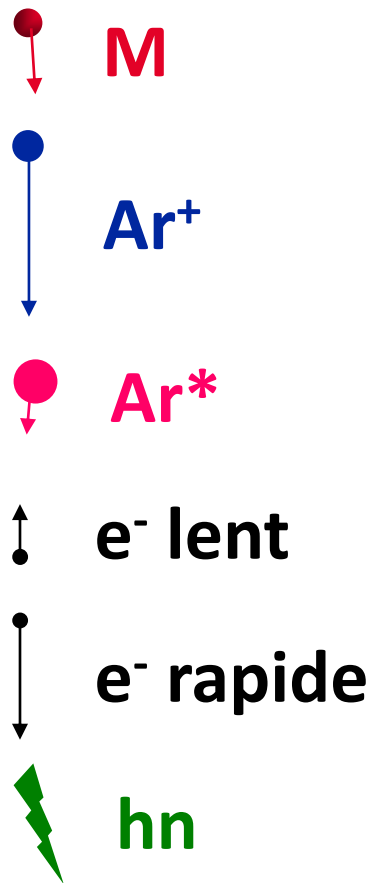


$$\frac{E_{coh}}{3/4} \frac{3/4}{b^{3/4}} \text{®}$$

(a) Schéma simplifié des processus de nucléation-croissance en surface et des trois modes de croissance principaux

(b) Franck van der Merve (c) Stranski-Krastanov (d) Volmer-Weber

# Atom-Surface et growth



Growth (deposition rate, morphology, structure)

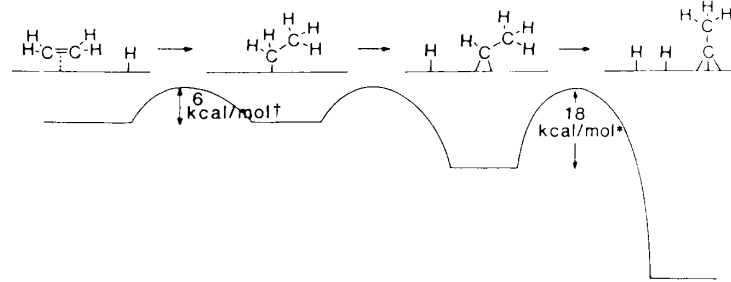
Depends on:

- Flux et energy of atoms, substrate  $T^\circ$  , gas  $T^\circ$  ,
- Substrate composition, vapor composition (ion, metastable,  $e^-$ )

# Molécule – Surface : Réactivité

$E_i, v_i, J_i, Ee_i, \theta_i$

Conversion de l'éthylène en éthylidyne ( $CCH_3$ )



$E_f^1, v_f^1, J_f^1, Ee_f^1, \theta_f^1$   
 $E_f^2, v_f^2, J_f^2, Ee_f^2, \theta_f^2$

Fragmentation de l'éthylidyne en vinylidène ( $CCH_2$ ) et acétylure ( $CCH$ )

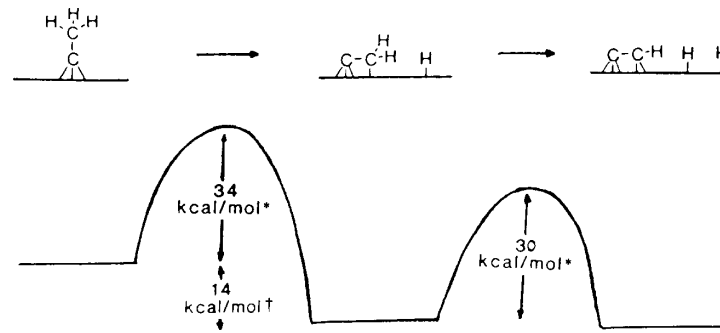
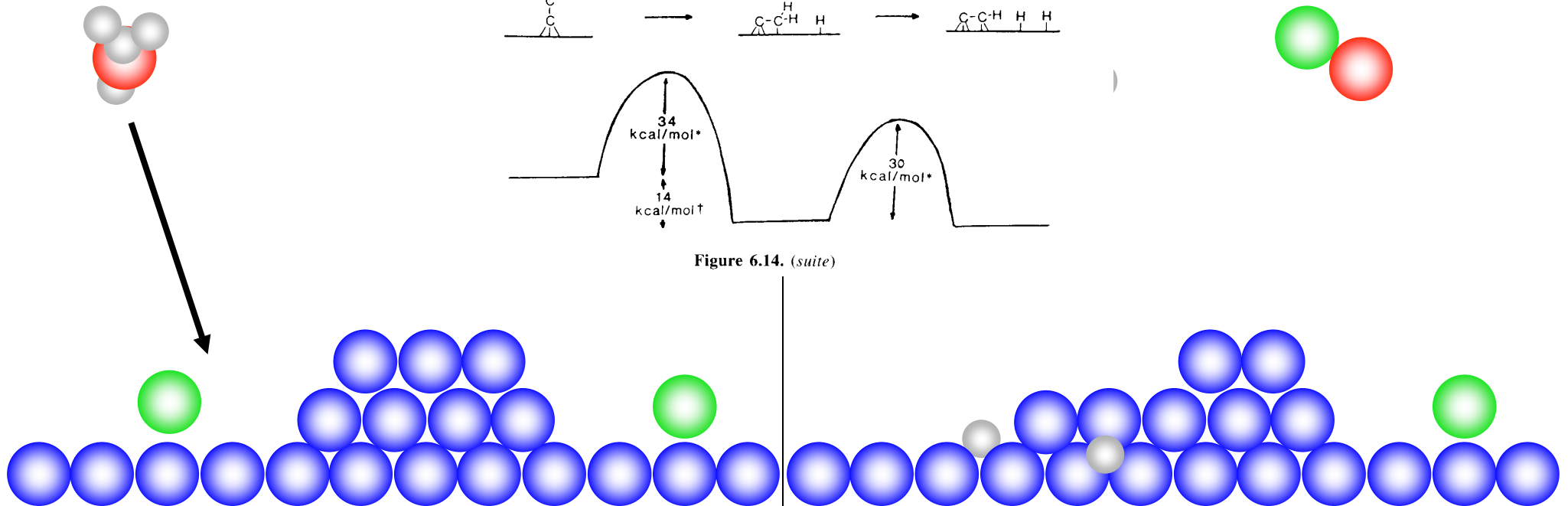


Figure 6.14. (suite)



# Interactions Faisceau moléculaire - Surface Approche moléculaire

## Features

$E_c, \theta, v, J$  variables

$dv/v = 1-15\%$



Analysis of the various reaction channels

Interaction potential surface probe

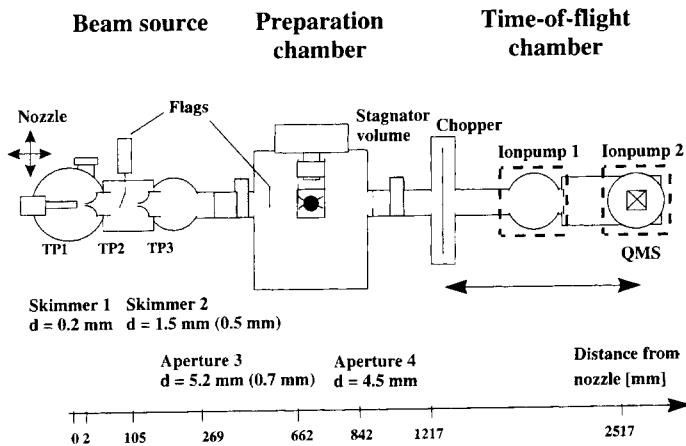


Fig. 6. The beam source and TOF system.

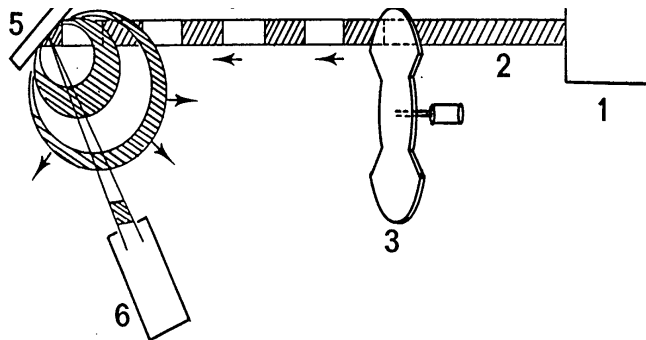


Fig. 5: Schematic drawing of a molecular beam experiment. (1) molecular beam source, (2) molecular beam, (3) modulator, (4) pulsed beam, (5) sample, (6) detector.

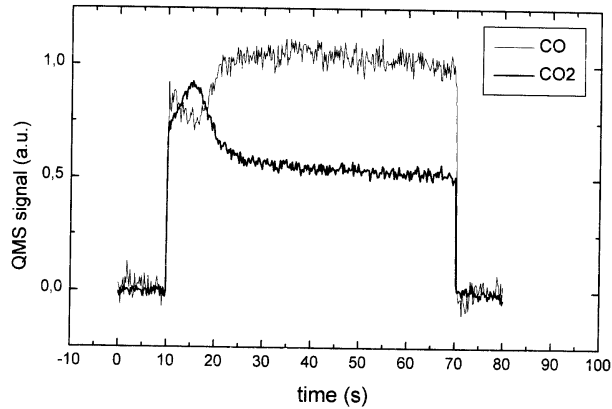


Fig. 42. Molecular beam study of the CO oxidation on a Pd/MgO(100) model catalyst. A CO<sub>2</sub> product pulse (heavy line) and the associated pulse of unreacted CO (light line) are displayed.  $T = 556 \text{ K}$ ,  $n = 7.2 \times 10^{11} \text{ cm}^{-2} \text{ s}^{-1}$ ,  $D = 5.0 \text{ nm}$  (from L. Piccolo, C.R. Henry, unpublished).

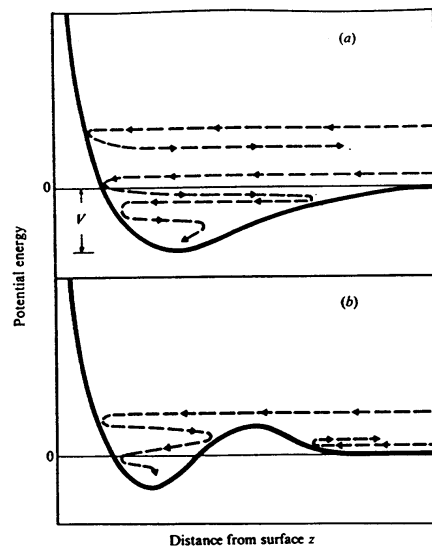


Fig. 4: Schematic representation (after A. Zangwill, 'Physics at surfaces' Cambridge University Press, 1992) of the (1D) interaction potential between a gas molecule and a metal surface as a function of the separation distance ( $z$ ). Curve (a) corresponds to a molecular adsorption (e.g. CO/Pd) and curve (b) corresponds to a dissociative adsorption (e.g. O<sub>2</sub>/Pd).

## Measure

## Variable

## Probe

**Dissociation**

$E_c$

$v$

$J$

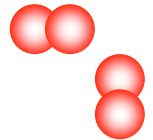
$\theta$

- Barrier position(x,y)

- Rotational corrugation

- Transition state

- Surface corrugation



**vibrational excitation**

$E_c$

$v$

**rotational excitation**

$E_c$

$J$

**diffraction**

$E_c$

- Surface corrugation

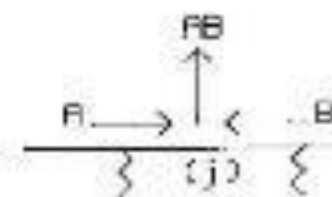
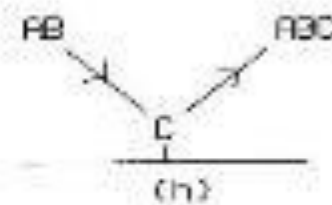
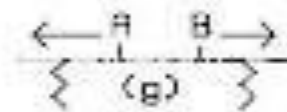
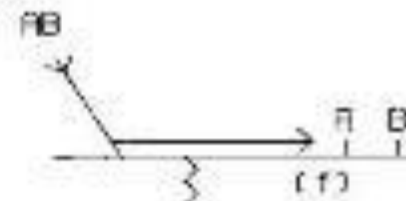
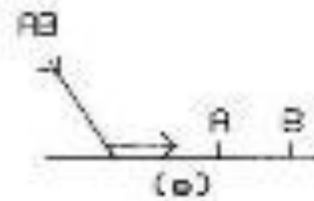
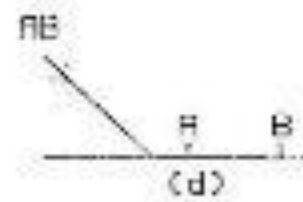
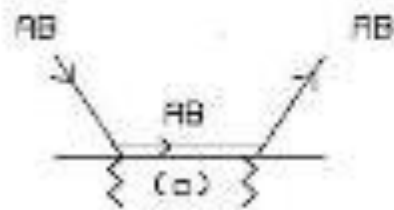
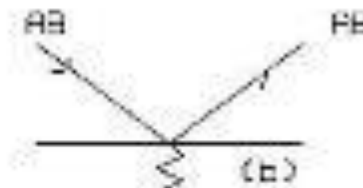
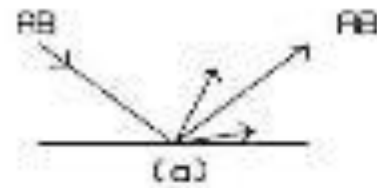
- Barrier height  $E_b(x,y)$

**-Potential surface curvature**

**- Rotational corrugation**



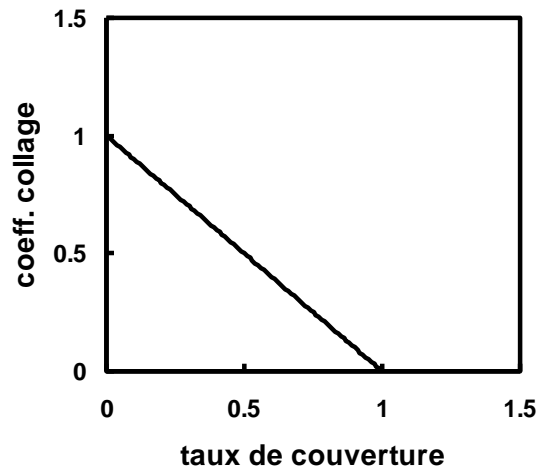
# Adsorption/reaction mechanisms



# Sticking coefficient evolution

Direct adsorption

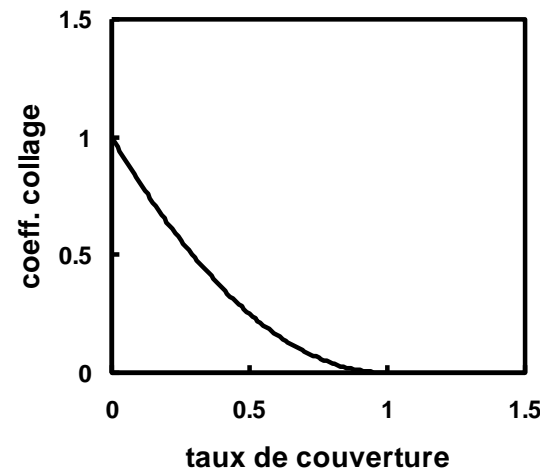
$$S = S_0(1-\theta)$$



Dissociative

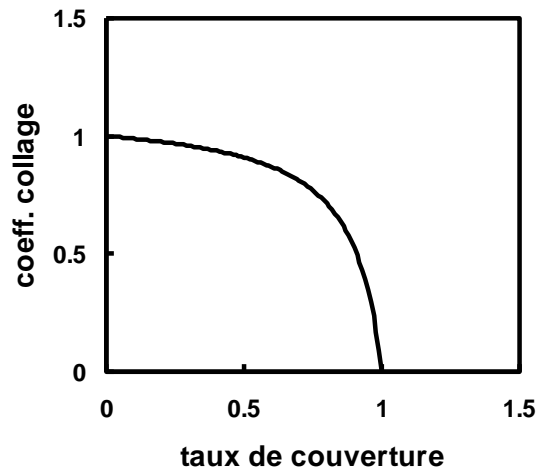
adsorption

$$S = S_0(1-\theta)^2$$

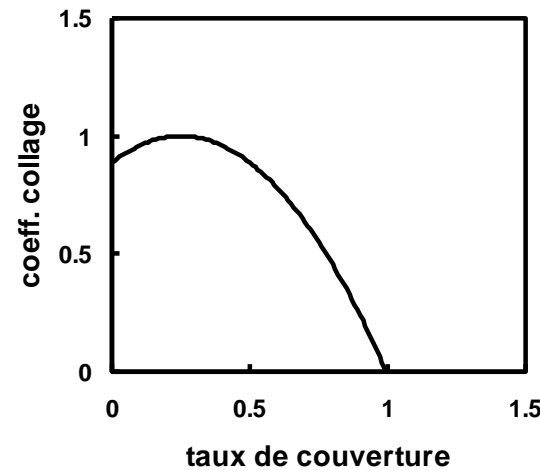


Adsorption  
via precursor

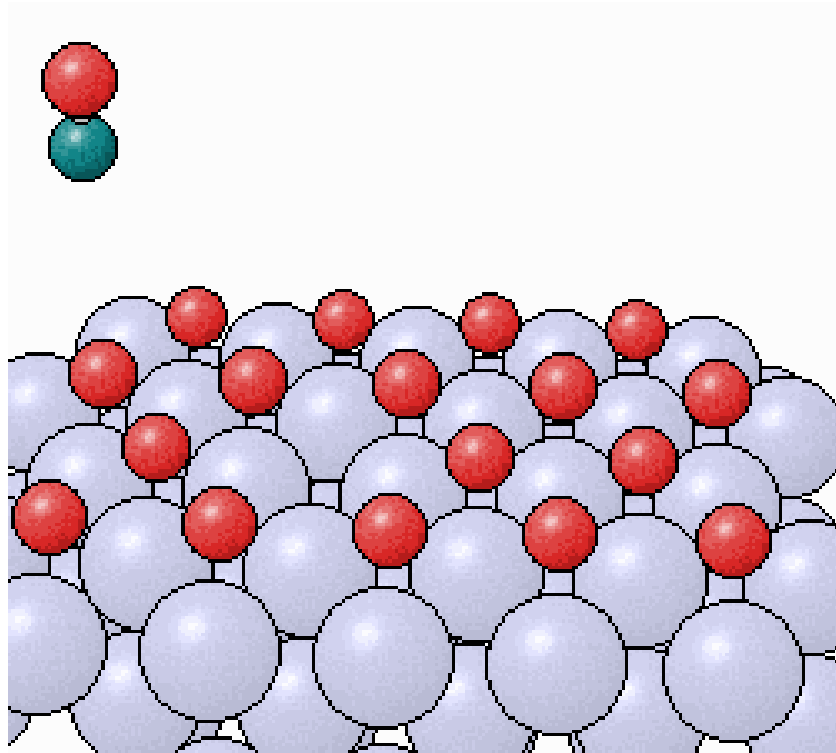
$$S = S_0 \frac{(1+K)(1-\theta)}{1+K(1-\theta)}$$



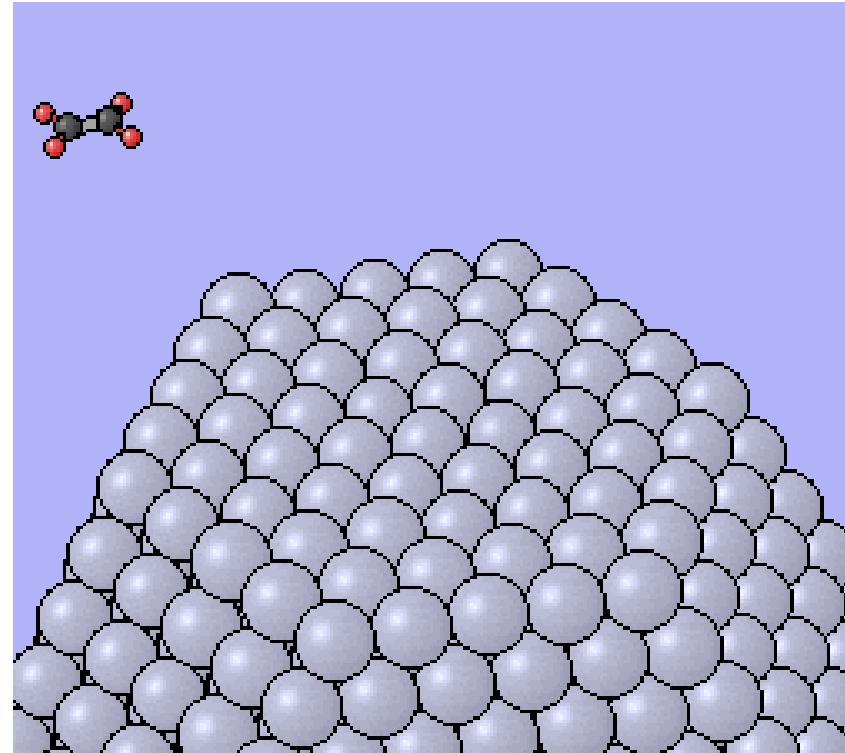
Adsorption  
via surface  
cluster



## Video clips



CO oxidation on Ru(111)



Ethylen dehydrogenation on Ni(111)

# High pressure special case

✓ adsorption increases  
(more exactly nucleation site density increases )  
When incoming flux increase (pressure)



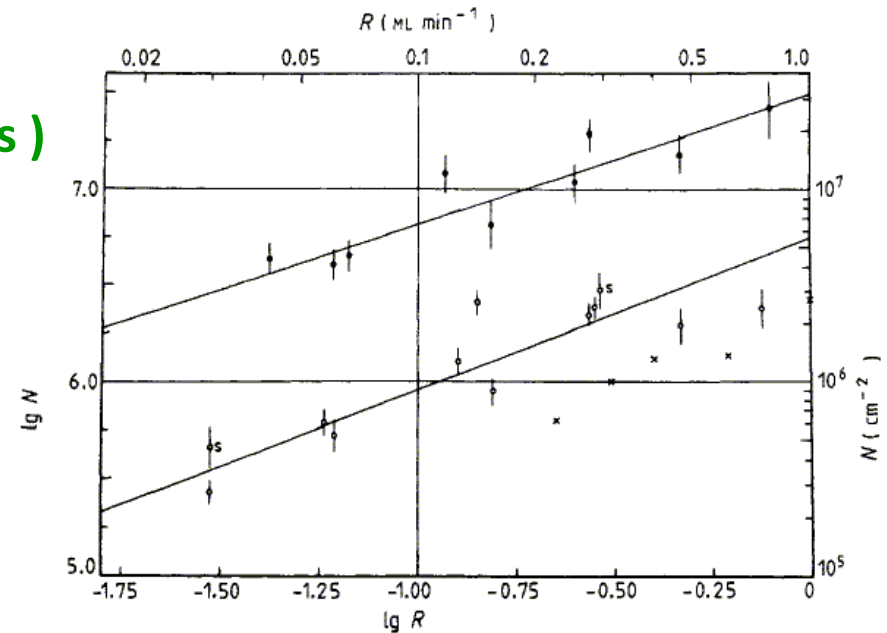
∃ Boundary layer  
⇒ Limiting mechanisms  
Reaction / transport in BL



Turbulence effect ?

✓ How to observe reactions in HP

→ Optical methods and close field microscopies (STM/AFM)



**Figure 19.** Rate dependence  $N_x(R)$  for Ag/W(110) at  $T_s = 300$  (●) and  $500^\circ\text{C}$  (○) (from Spiller *et al* 1983). Crosses are from Akhter *et al* (1980) nominally at  $500^\circ\text{C}$ , but possibly at higher  $T_s$ , and points marked s are on noticeably stepped surfaces. (Note  $N_x$  in  $\text{m}^{-2}$ , not  $\text{cm}^{-2}$ .)

# HIGH PRESSURE HIGH TEMPERATURE SFG + STM

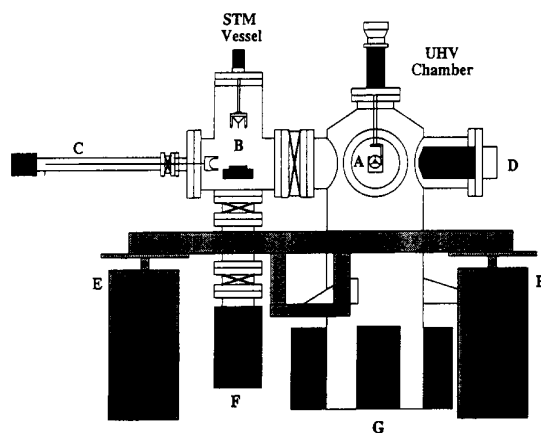


Fig. 1. STM in a high pressure reactor with a UHV surface characterization chamber attached.

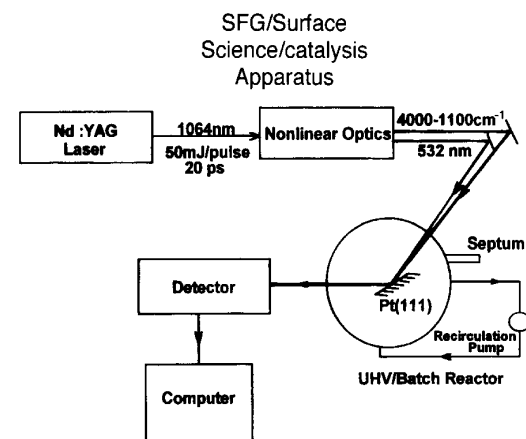
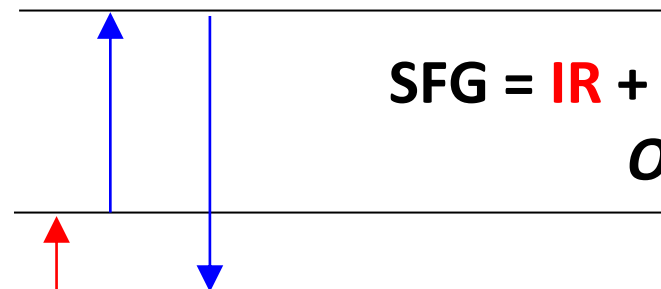


Fig. 2. The UHV/batch reactor apparatus coupled to an Nd:YAG laser for in-situ SFG studies.



**SFG = IR + Raman anti-Stokes (UV-Vis)**  
*Only sensitive to surface*

# Some pioneering outstanding results

## *In Situ* High Pressure STM Adsorbate-induced surface reconstructions Pt(110) under atmospheric pressures

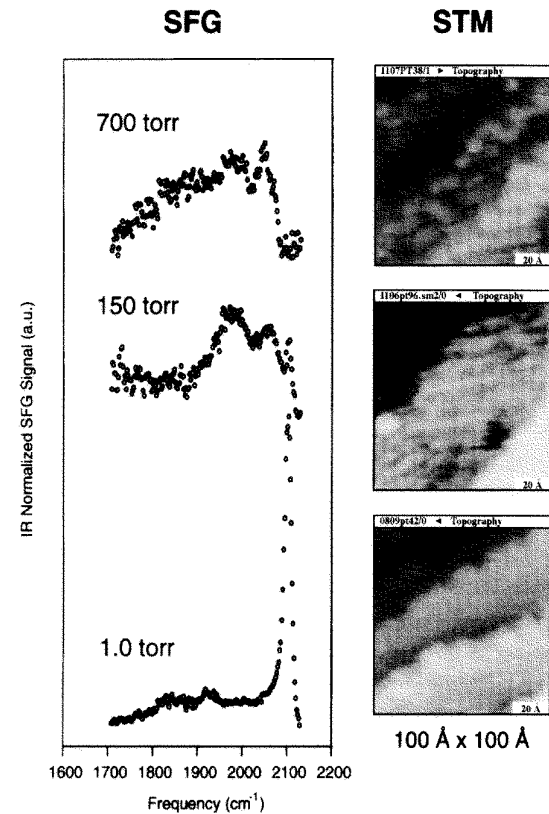
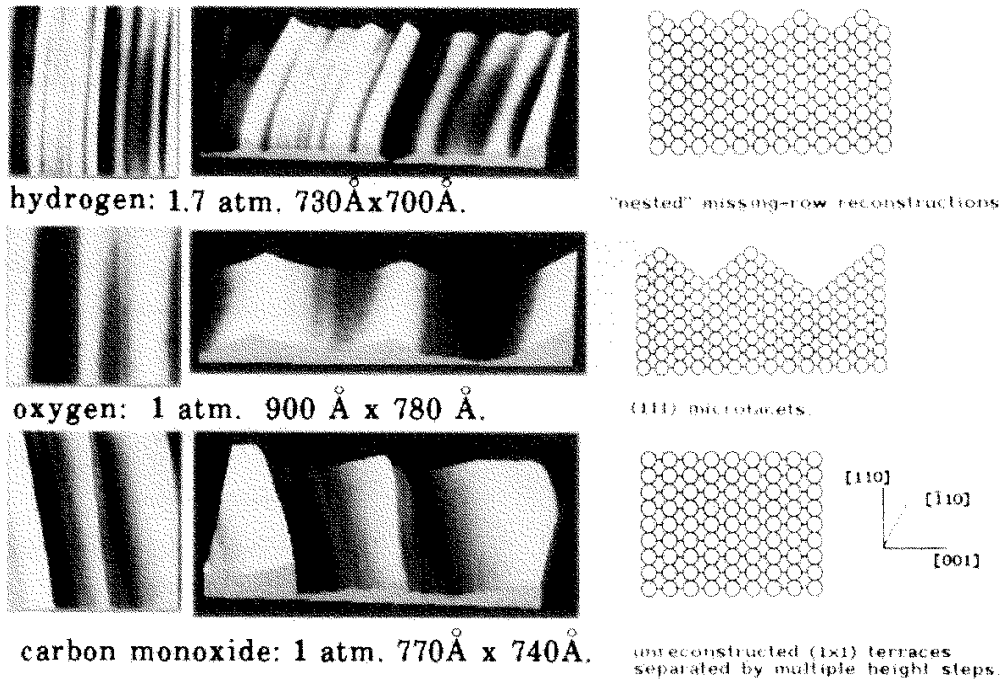


Fig. 7. Scanning tunneling microscope pictures of carbon monoxide over the Pt(111) crystal face at three different pressures: 1.0, 100, and 500 torr.

Ethylene Hydrogenation  
on Pt(111) with 100 Torr H<sub>2</sub>  
35 Torr C<sub>2</sub>H<sub>4</sub> at 295 K

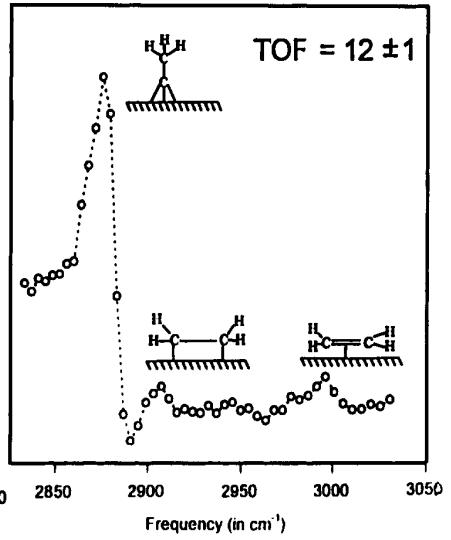
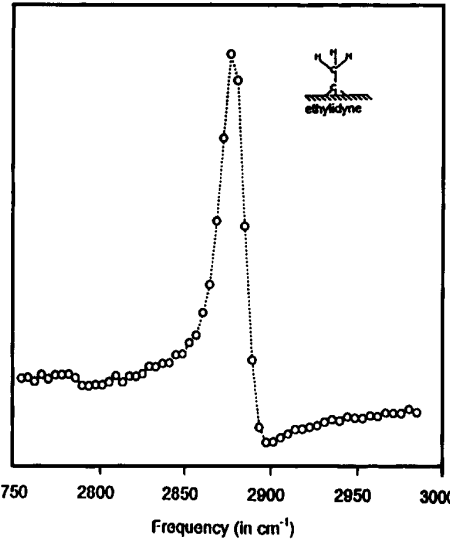
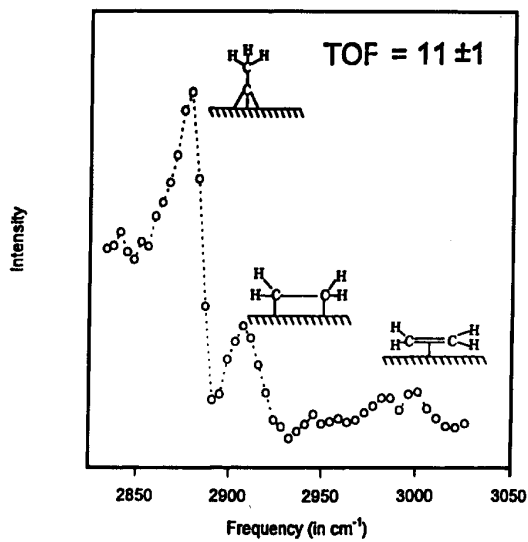


Fig. 8. (a) SFG spectrum of the Pt(111) surface during ethylene hydrogenation with 100 torr H<sub>2</sub>, 35 torr C<sub>2</sub>H<sub>4</sub>, 615 torr He at 295 K. (b) The vibrational spectrum of the same system after the evacuation of the reaction cell. (c) SFG spectrum under the same conditions as (a), but on a surface which was pre-covered in UHV with 0.52 monolayers (ML) of ethynidyne.

Pressure Dependence of SFG  
Spectra of CO on Pt(111) at 295 K

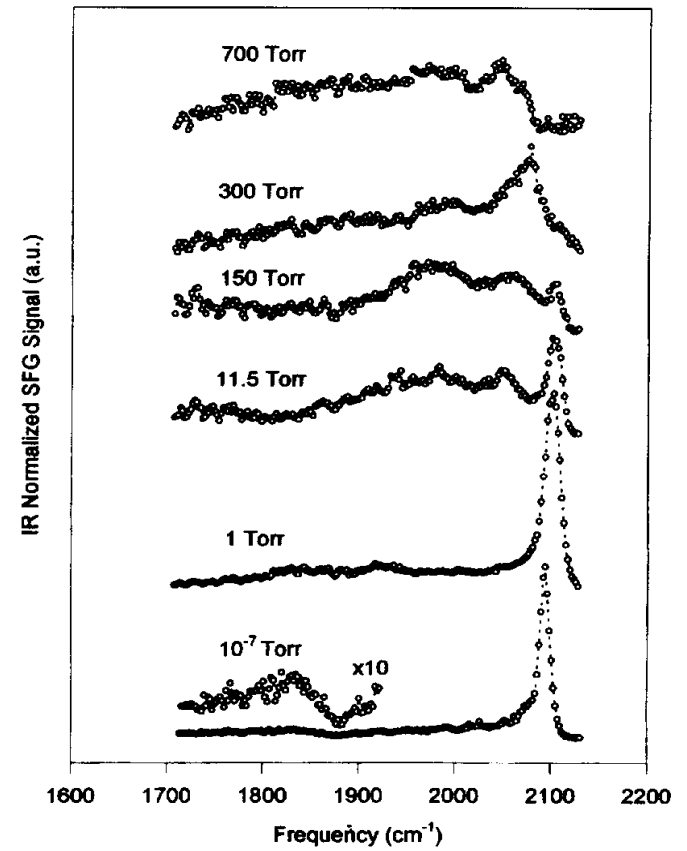


Fig. 6. Pressure dependence of SFG spectra for CO on Pt(111) at 295 K. The spectra change indicates that new surface species appeared at high pressures.

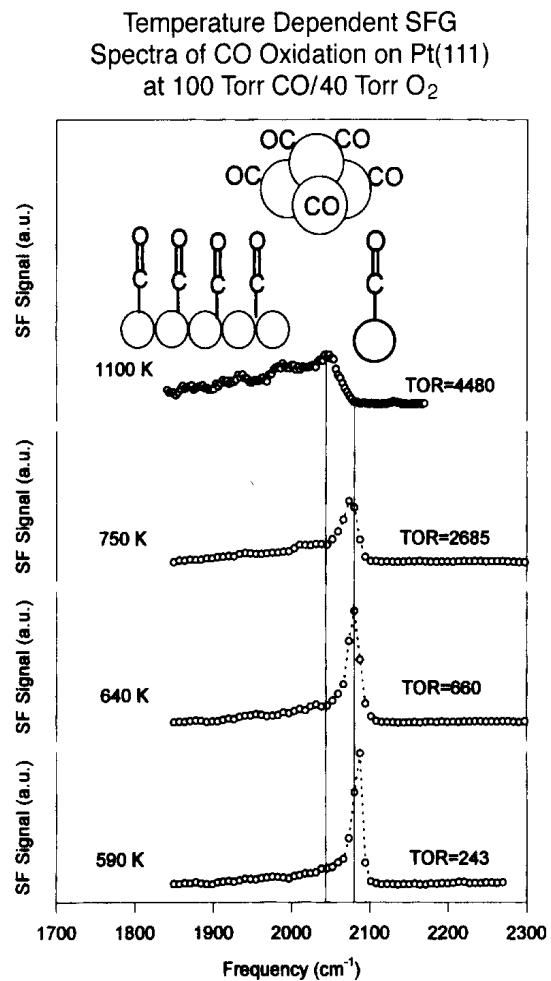
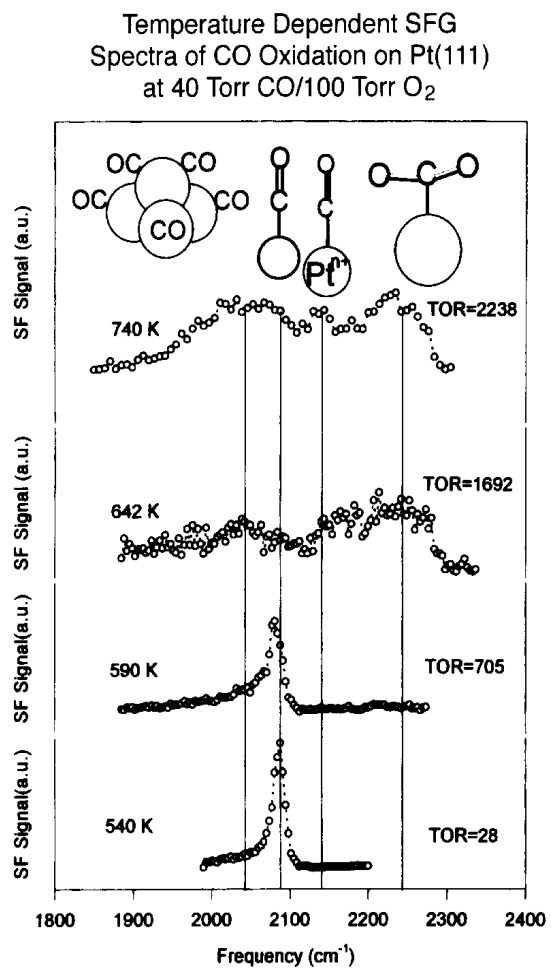


Fig. 11. (a) Temperature dependence of SFG spectra of high pressure CO oxidation over Pt(111) at 100 torr O<sub>2</sub> and 40 torr CO. The temperature and turnover rate are also shown. (b) Temperature dependence of SFG spectra of high pressure CO oxidation over Pt(111) at 100 torr CO and 40 torr O<sub>2</sub>. The temperature and turnover rate are also shown.



# ABSORPTION X : ...EXAFS

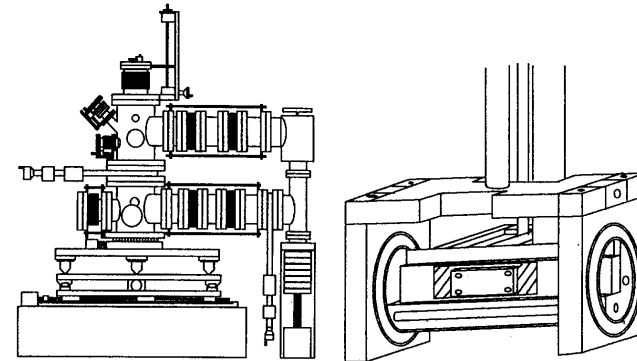
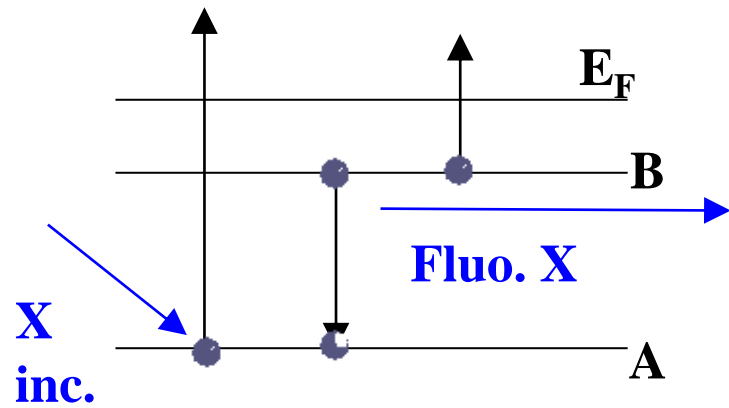


Figure 5. In-situ polarized total-reflection fluorescence XAFS system; (a) the chamber and (b) the sample holder.

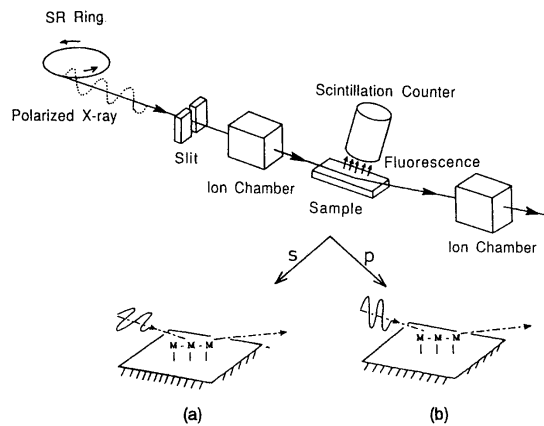


Figure 4. Polarized total-reflection fluorescence XAFS; (a) s-polarization and (b) p-polarization.

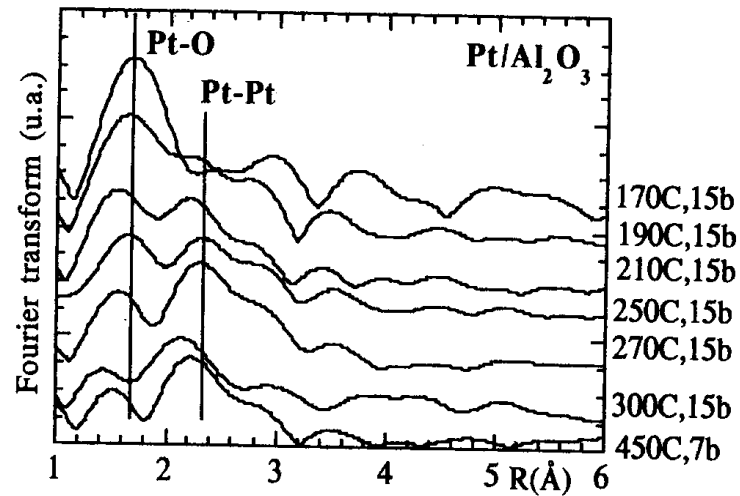


Figure 15 : Evolution of the Fourier transform at the platinum  $L_{III}$  edge during the reduction process.

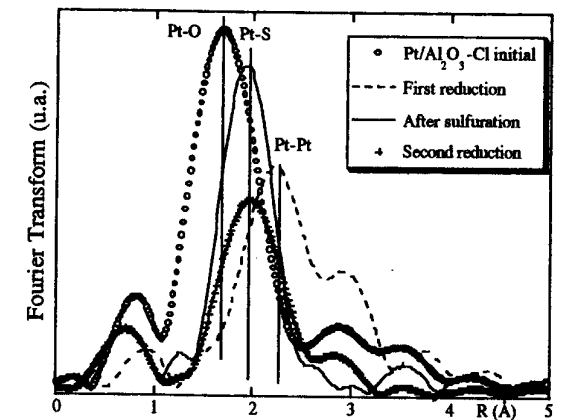


Figure 10 : Moduli of the Fourier transform of the monometallic Pt/alumina.

# ion-surface interactions and surface modifications

## kinematics :

Binary collision: Energy transfer  $\Delta E$  ( $E < \text{few } 10 \text{ keV}$ )

$$\Delta E_{\text{max}} \approx 4 \frac{m_g m_s}{(m_g + m_s)^2} E_g$$

$\Rightarrow$  atom displacements  $E < 10 \text{ eV}$

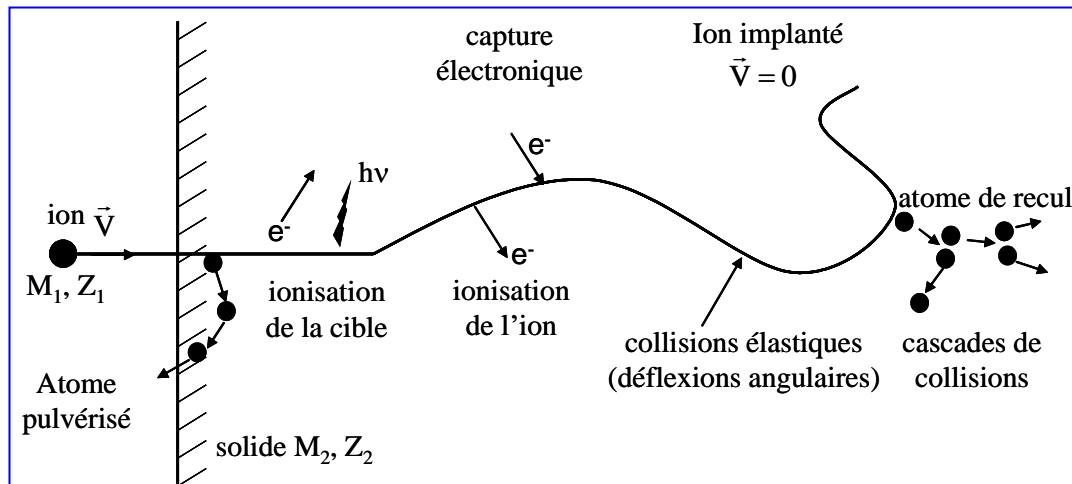
$\Rightarrow$  Sputtering  $10 \text{ eV} < E < 100 \text{ keV}$

Sputtering threshold:  $\approx 25 - 50 \text{ eV}$

Sputtering rate =  $f(E)$

$\Rightarrow$  implantation

$E > 100 \text{ keV}$



# Atom displacement(s) $E < 20 \text{ eV}$

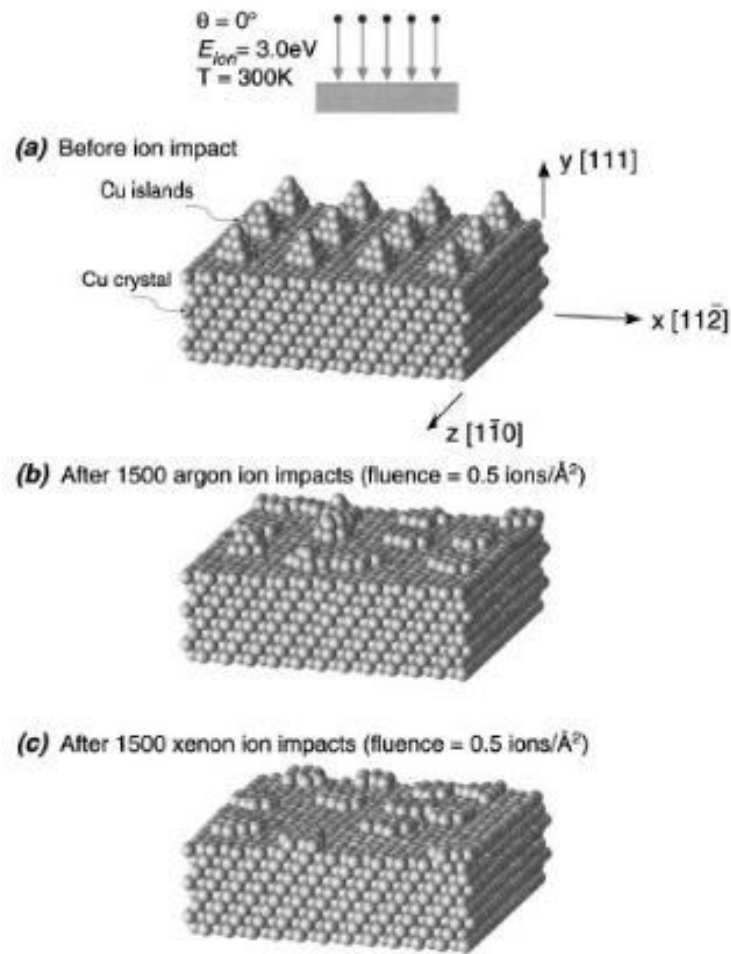


FIG. 1. Evolution of copper islands on copper surface during 3 eV ion impacts.

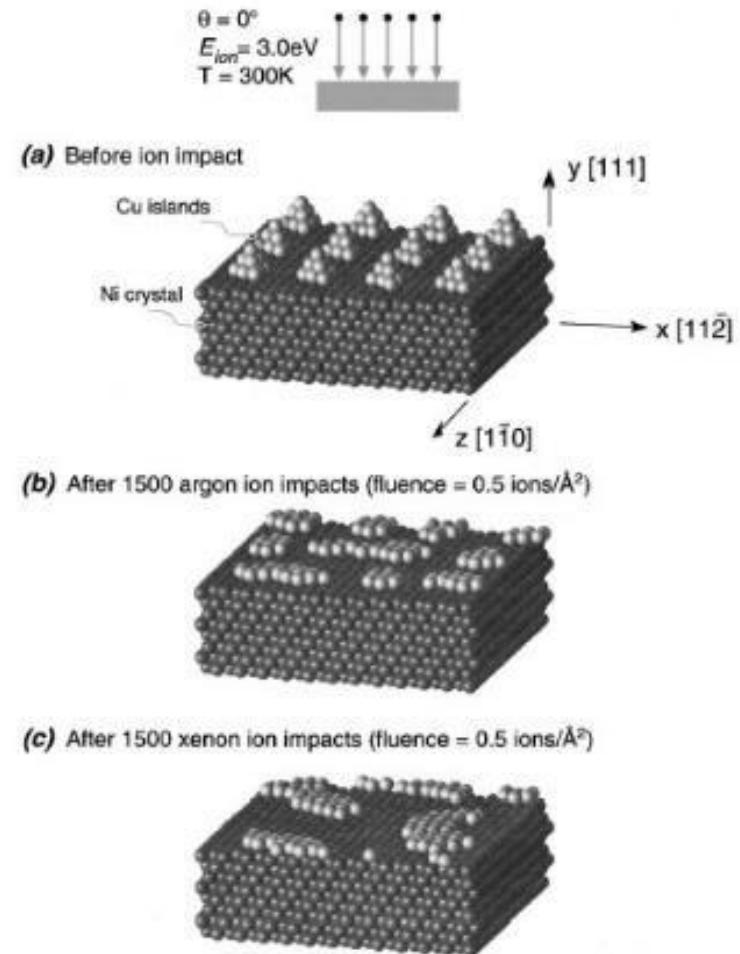


FIG. 2. Evolution of copper islands on nickel surface during 3 eV ion impacts.

# Sputtering

Sputtering rate:

$$Y(E) = 0.042 \frac{Q(Z_2)\alpha^*(M_2/M_1)}{U_s} \frac{S_n(E)}{1 + \Gamma k_e \epsilon^{0.3}} \times \left[ 1 - \sqrt{\frac{E_{th}}{E}} \right]^s$$

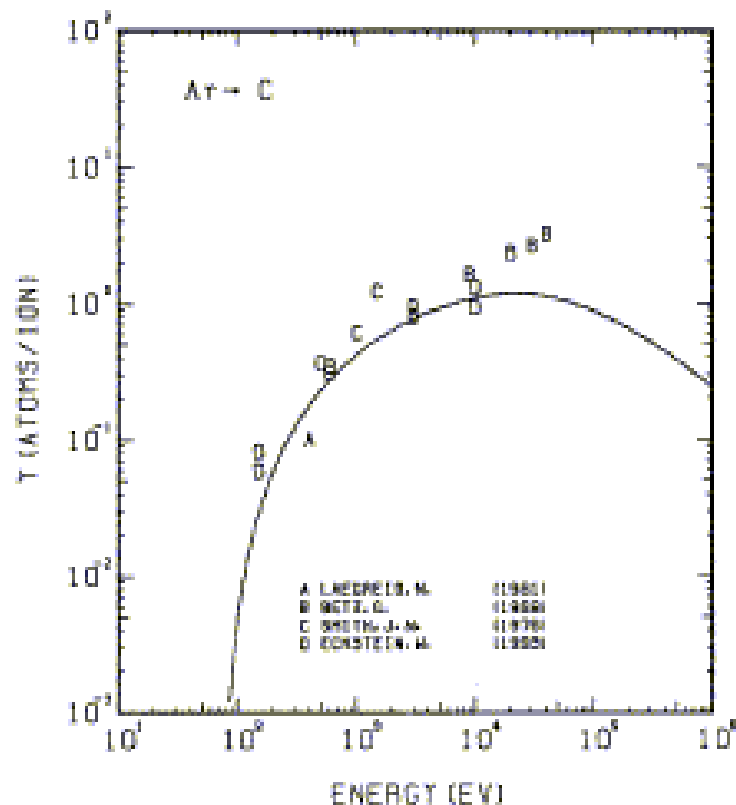


FIG. 21 ENERGY DEPENDENCE OF THE SPUTTERING YIELD OF C WITH AR<sup>+</sup>. A= 0.30, Q= 1.70, U<sub>s</sub>= 7.37ev, s= 2.50, W= 0.25U<sub>s</sub>. EXPERIMENTAL DATA FOR DIFFERENT KINDS OF GRAPHITE ARE INCLUDED.

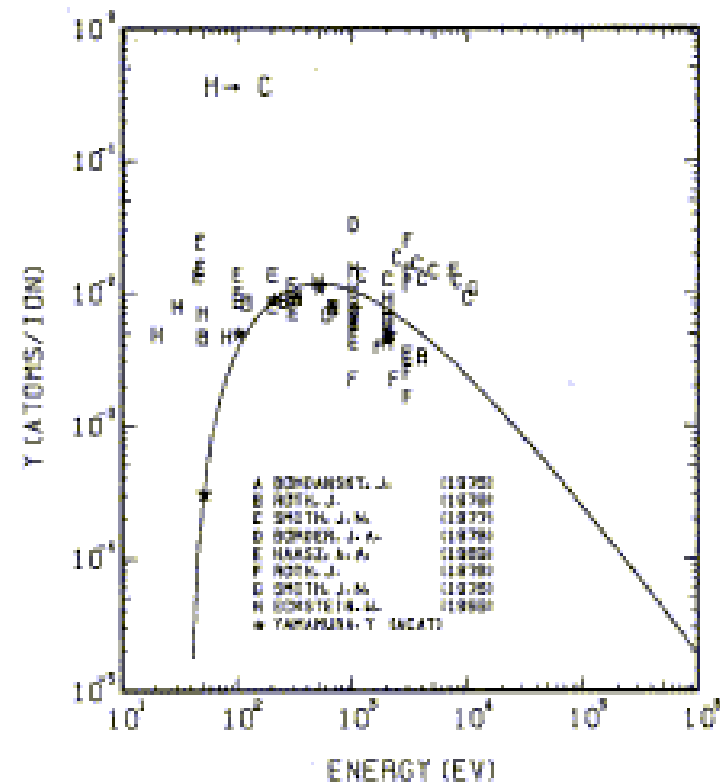
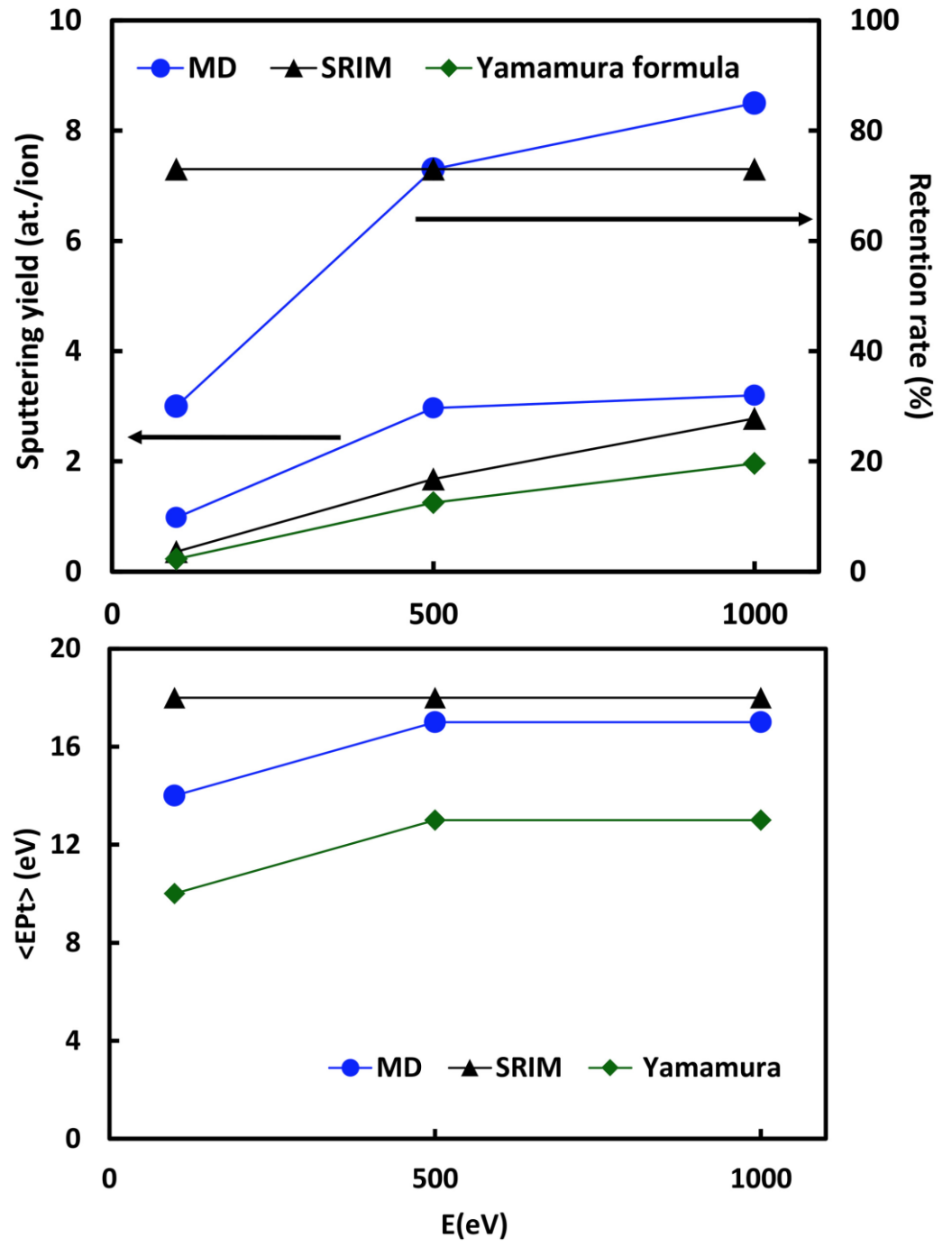
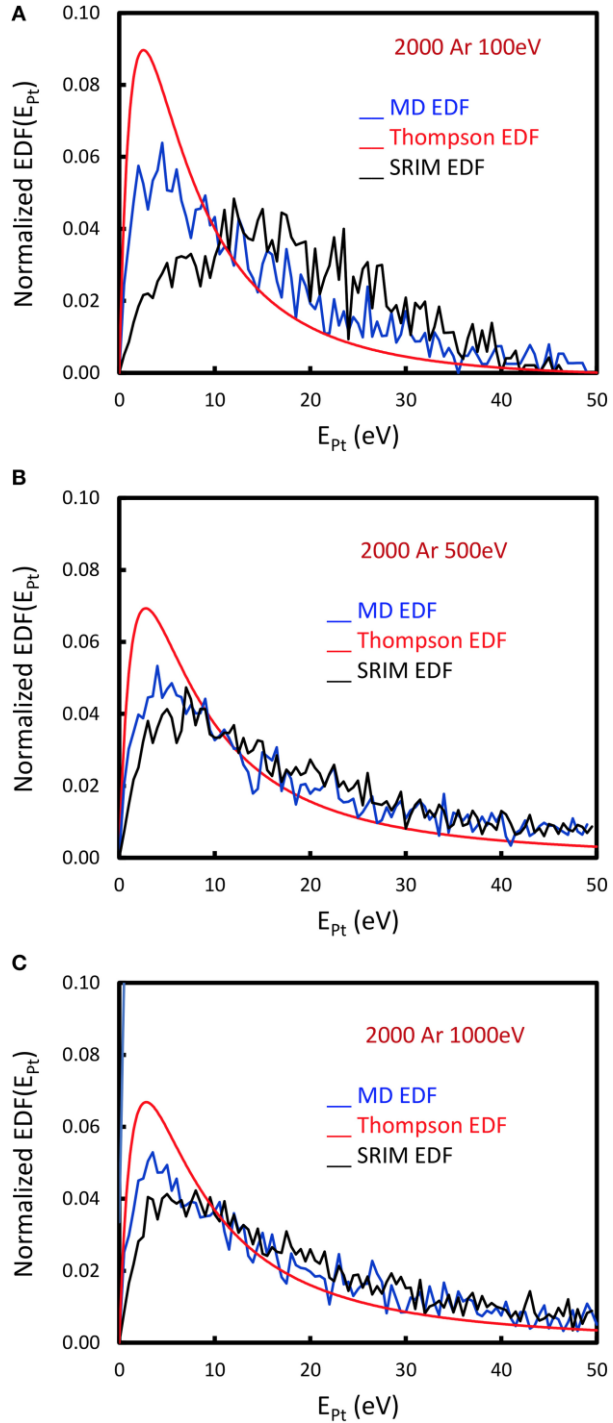


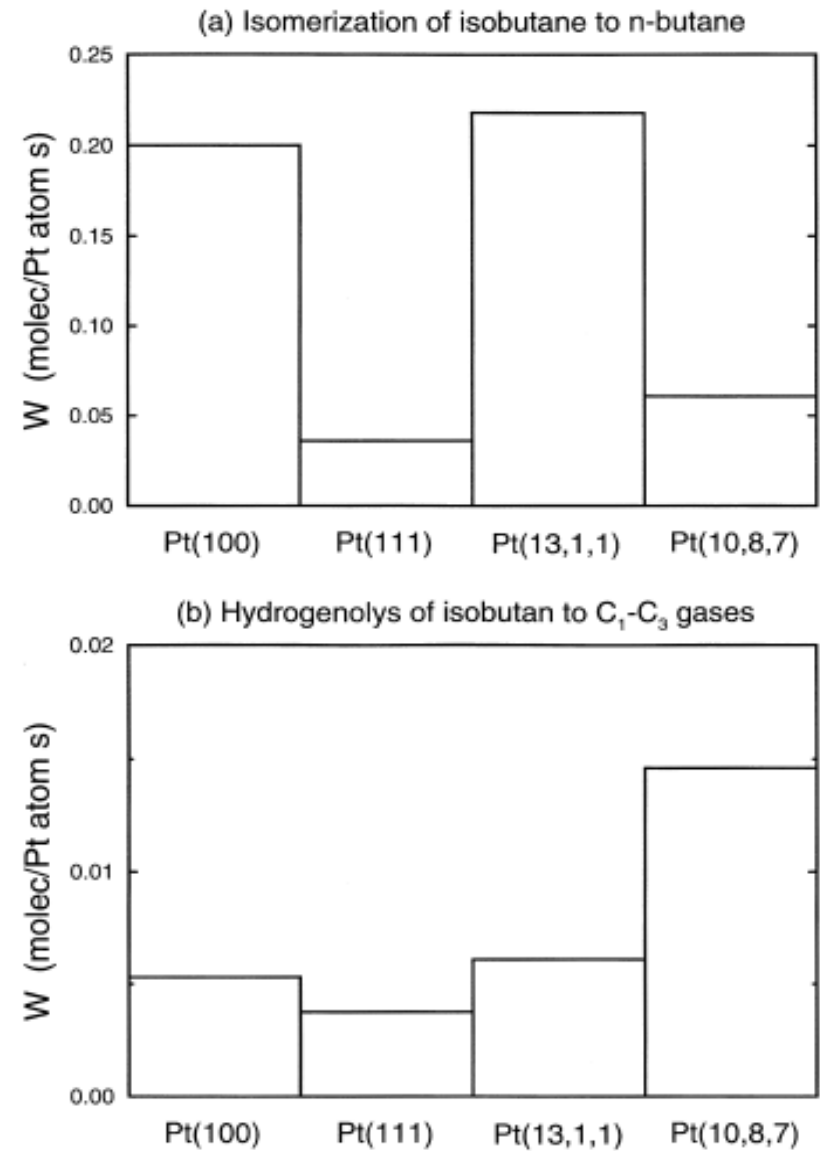
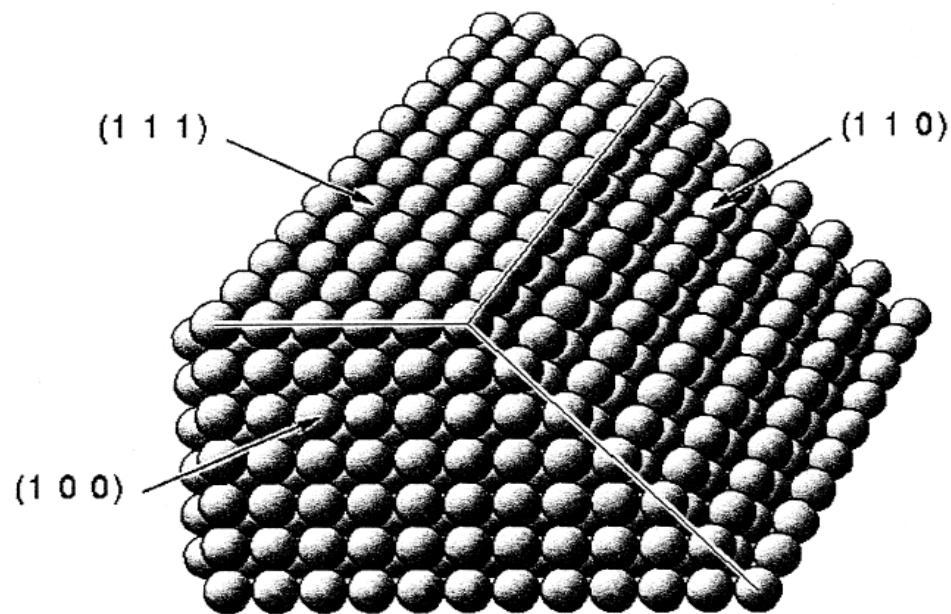
FIG. 15 ENERGY DEPENDENCE OF THE SPUTTERING YIELD OF C WITH H<sup>+</sup>. A= 11.91, Q= 1.70, U<sub>s</sub>= 7.37ev, s= 2.50, W= 0.25U<sub>s</sub>. EXPERIMENTAL DATA FOR DIFFERENT KINDS OF GRAPHITE ARE INCLUDED. THE CHEMICAL EROSION IS FOUND EVEN AT ROOM TEMPERATURE.

# Comparison of different methods for calculating sputtering yields and sputtered atom energy distributions.



Brault P et al(2016) Molecular Dynamics Simulations of Platinum Plasma Sputtering: A Comparative Case Study. *Front. Phys.* 4:20. doi: 10.3389/fphy.2016.00020

# Structure effects on reactivity



# NANO OBJECTS

## Morphologies

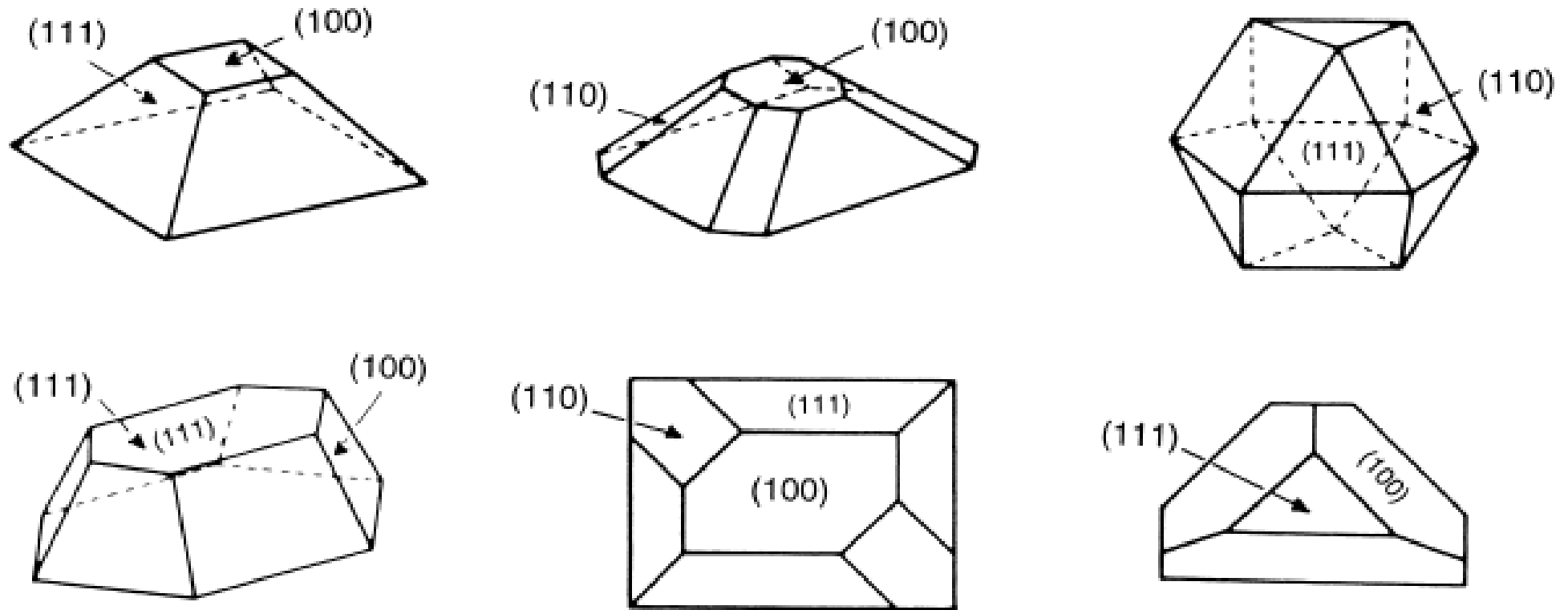


Fig. 18. Typical shapes of supported crystalline 3–20 nm metal particles. (Redrawn from [49].)

➔ Many combinations of corner, faces, ridges

## Size effects

Recall : dispersion ( $\equiv$  # surface atoms ( $N_s$ ) / #total atom ( $N_t$ ))

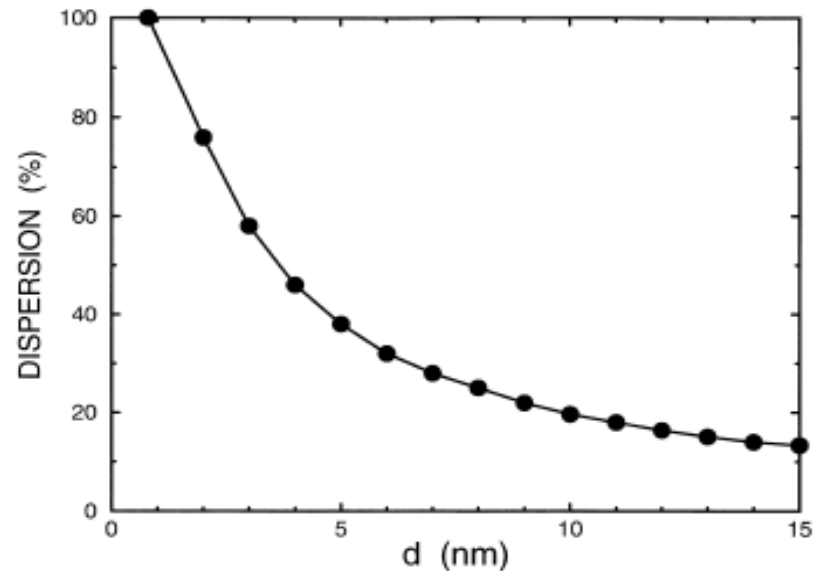


Fig. 1. Dispersion as a function of the Pt particle size. The calculations are based on the sphere and cubo-octahedron models. The size of the data points characterizes the difference of the results for the two models. (Redrawn from [16].)

Example for a sphere with radius  $r$ :

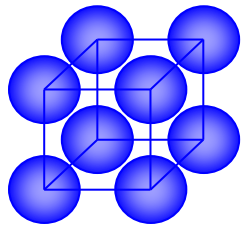
$$V = \frac{4}{3}\pi r^3; \quad N_T = \rho_V V = \frac{4\pi}{3}\rho_V r^3$$

$$S = 4\pi r^2; \quad \rho_S = \rho_V^{2/3}; \quad N_S = \rho_S S = 4\pi\rho_V^{2/3} r^2$$

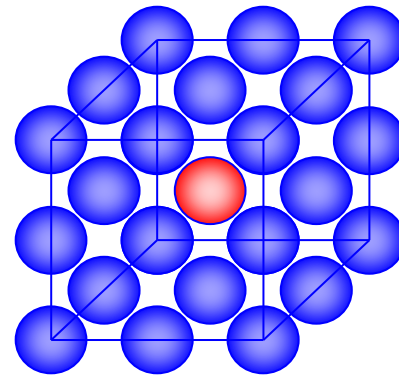
$$\text{et donc : } D = \frac{N_S}{N_T} = \frac{3}{\rho_V^{1/3} r}$$



## Example



Nano-cube with 8 atoms  
All are surface atoms



Nano-cube with 27 atoms  
26 are surface atoms, only one is  
bulk atom: red one

*Q: for a  $4 \times 4 \times 4 = 64$  atoms cube, how many surface atoms are there ?*

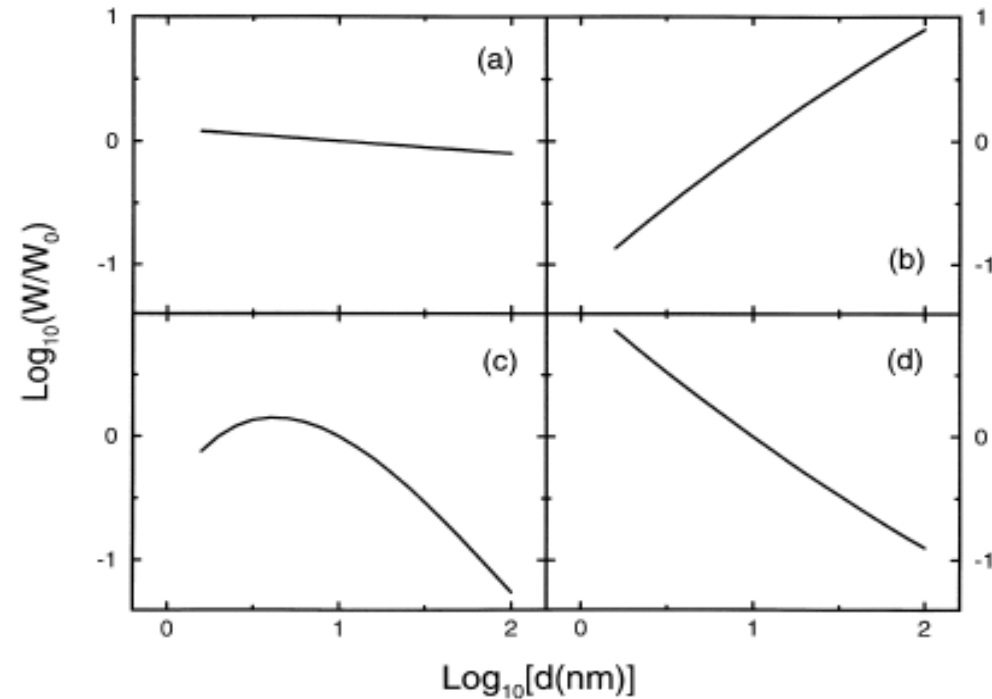
Top + Bottom  $\rightarrow 2 \times 16 = 32$  atoms

Front and rear, it remains  $\rightarrow 2 \times 8 = 8$  atoms

Left and right, it remains  $\rightarrow 2 \times 4 = 8$  atoms

So there are 56 surface atoms in a 4x4x4 cube

## reaction rate vs size



- a) Reaction rate is not sensitive to size (rare)
- b) Reaction rate is increasing  
*structure effects (faces, defects).*
- c) Reaction rate has a maximum  
*electronic size effects at intermediate sizes 3-4 nm*
- d) Reaction rate decreases  
*Small sizes are favored*

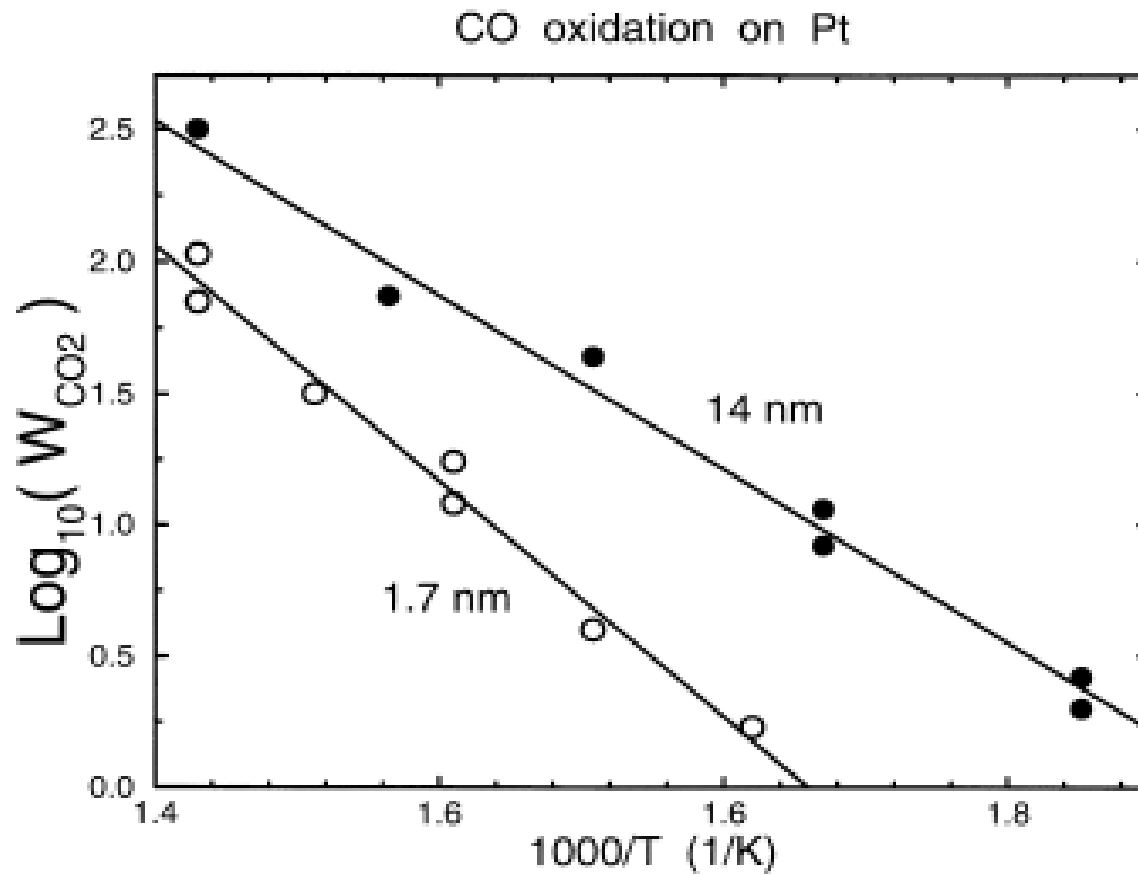


Fig. 3. Rate of CO oxidation,  $W_{CO_2}$  ( $CO_2$  molecules/site s), on  $Pt/\alpha-Al_2O_3$  for 14 and 1.7 nm catalyst particles at  $P_{CO} = P_{O_2} = 10$  Torr. (Redrawn from [21].)

$$W_{1.7\text{ nm}} < W_{14\text{ nm}} \text{ car } E_{CO}(1.7\text{ nm}) > E_{CO}(14\text{ nm})$$

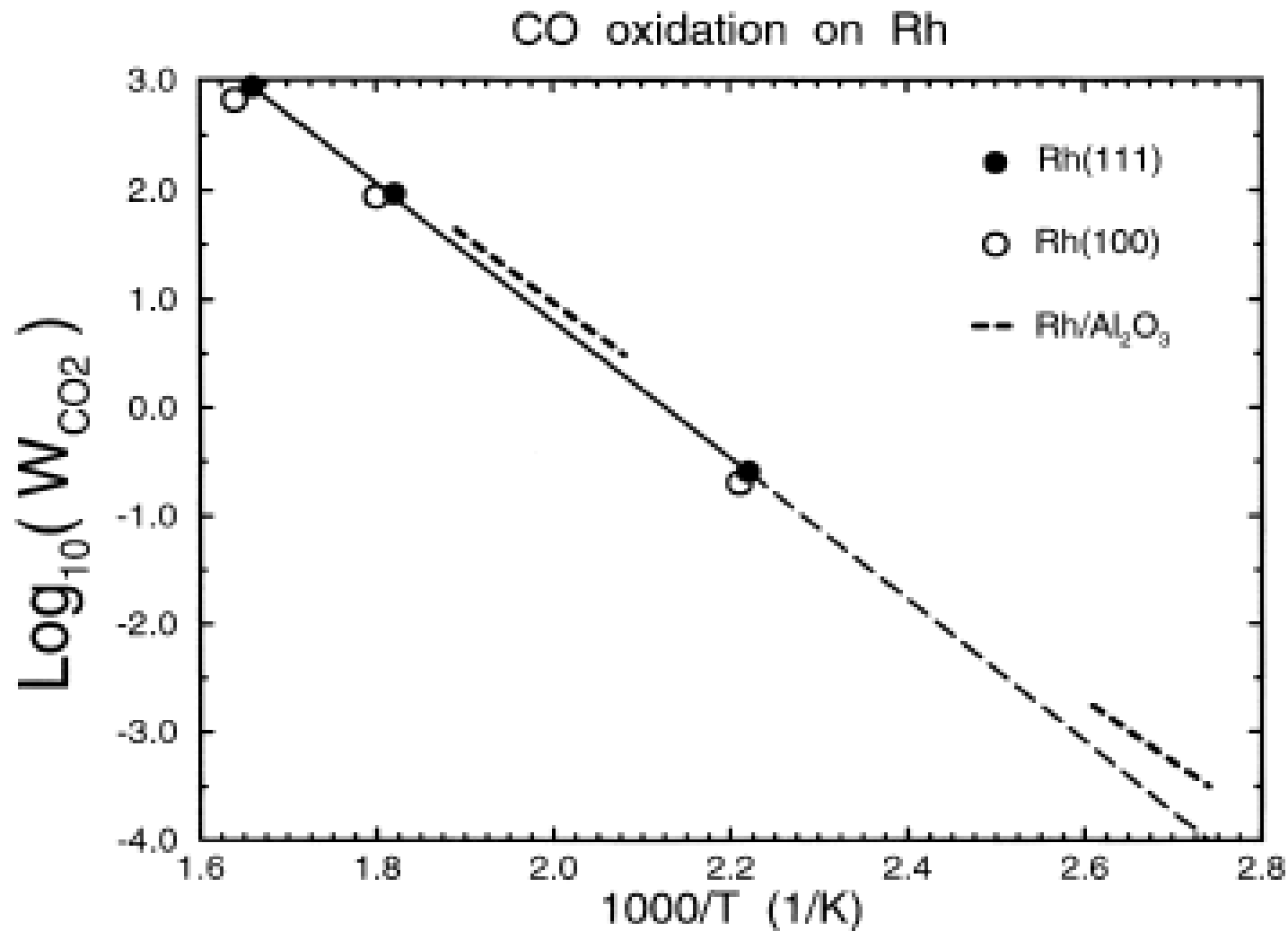


Fig. 4. Rate of CO oxidation,  $W_{\text{CO}_2}$  (CO<sub>2</sub> molecules/site s), on Rh (1 1 1), Rh (1 0 0), and Rh/Al<sub>2</sub>O<sub>3</sub> at  $P_{\text{CO}} = P_{\text{O}_2} = 8$  Torr. The supported Rh catalyst (with dispersion of 12%) was prepared by impregnation of alumina beads. (Redrawn from [22].)

→ Uninsensitive to structure/size

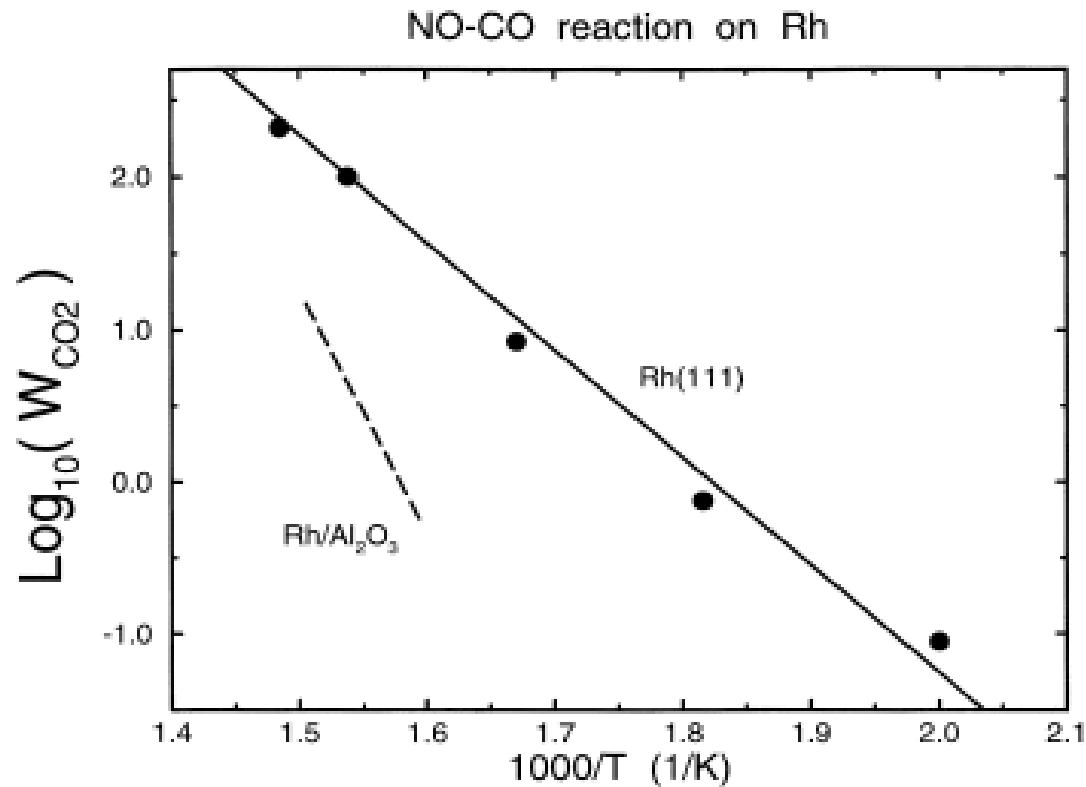


Fig. 5. Rate of CO<sub>2</sub> production,  $W_{CO_2}$  (CO<sub>2</sub> molecules/site s), during the NO-CO oxidation on Rh (1 1 1) and Rh/Al<sub>2</sub>O<sub>3</sub> at  $P_{CO} = P_{O_2} = 8$  Torr. The supported Rh catalyst (with dispersion\* of 12%) was prepared by impregnating alumina beads. (Redrawn from [22].)

NO+CO → CO<sub>2</sub> + 1/2N<sub>2</sub> on Rh is very sensitive to structure

$$D = 12\% \Rightarrow r = \frac{3}{D\rho_V^{1/3}} = 6nm \text{ pour Rh}; \rho_V(Rh) = 7.2310^{22} \text{ at.cm}^{-3}$$

## Size effects and temperature

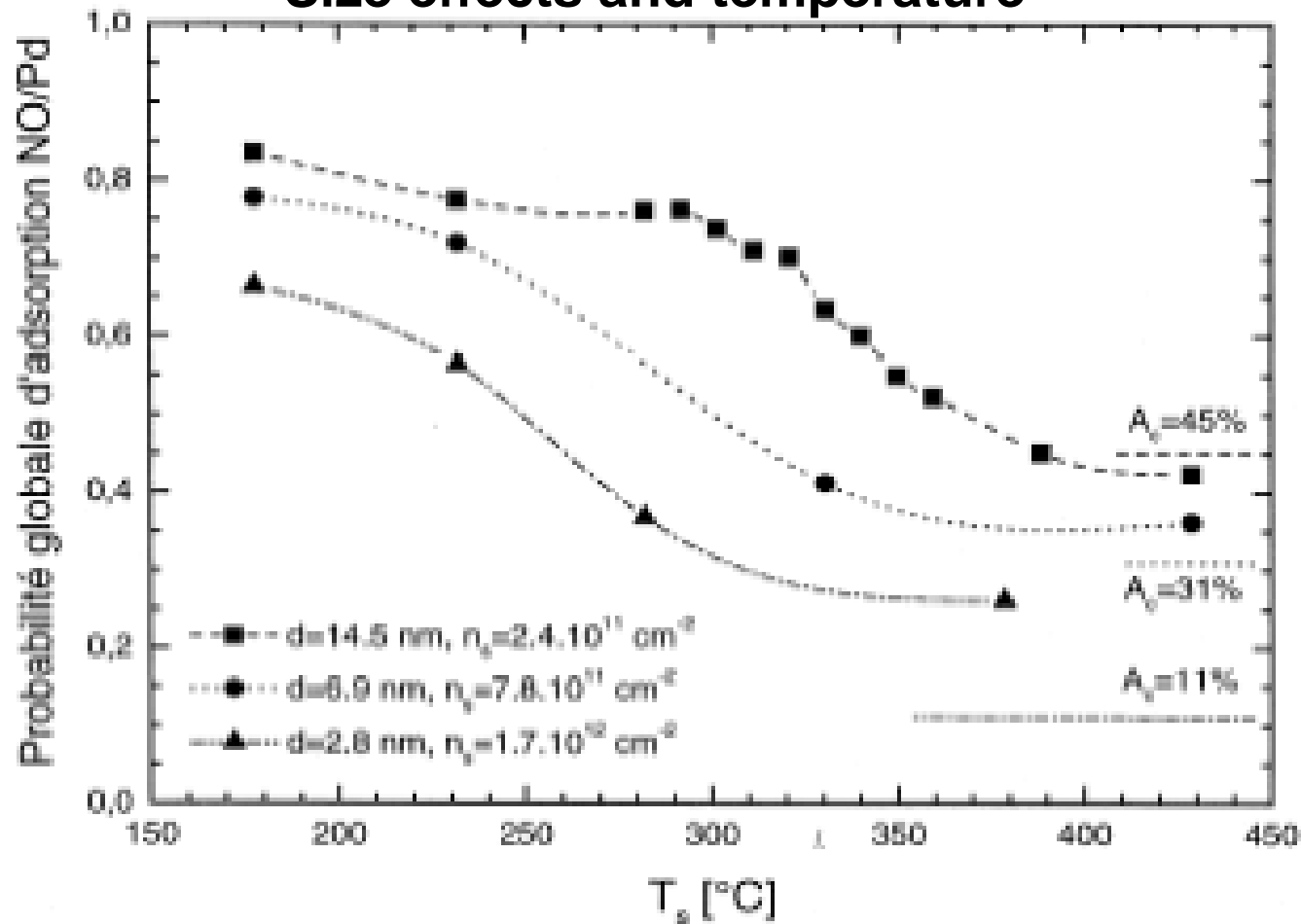


Figure 2.12 : Probabilité globale d'adsorption  $\alpha_g$  de NO sur Pd en fonction de la température pour trois types de catalyseurs. Pour chaque type, les points expérimentaux sont reliés par une fonction spline et la valeur  $A_g$  de la fraction d'air couverte par le Pd est représentée par un trait de style (tirets, pointillés ou tirets-pointillés) identique au style de la fonction spline. L'erreur sur les valeurs absolues de  $\alpha_g$  est estimée à 10% du fait de l'approximation (1.19) conduisant à l'expression (1.20) du paragraphe 1.3.2.1, utilisée dans le calcul de  $\alpha_g$ .

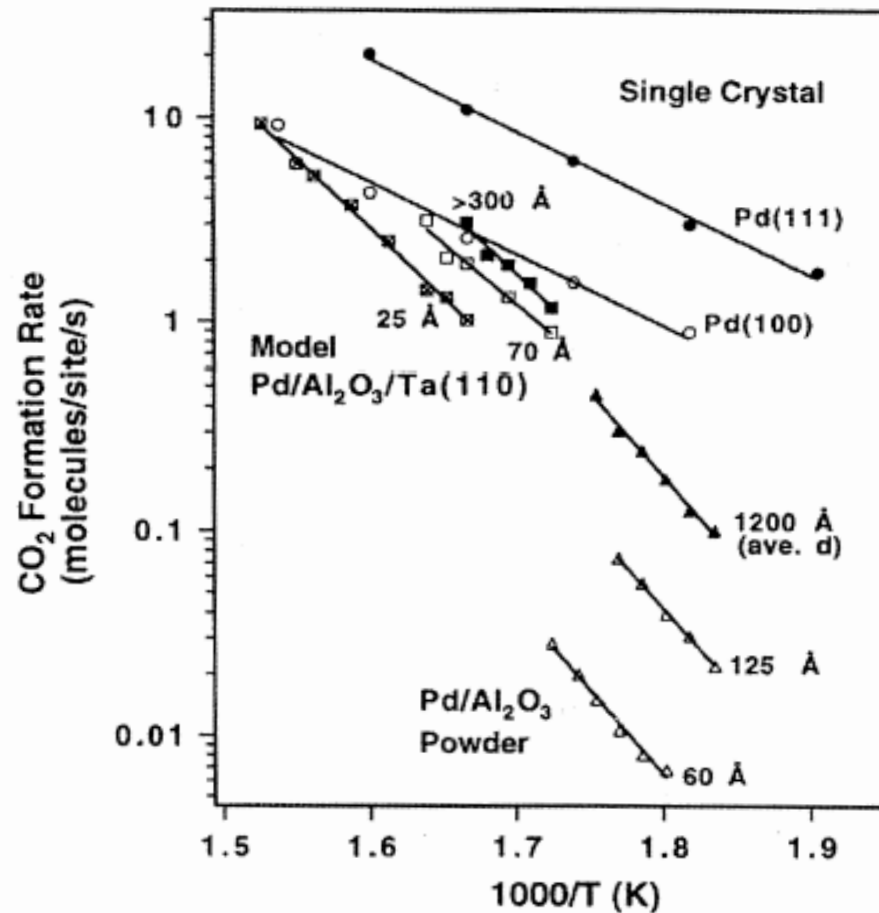


figure 3.1 : *Turnover number* de production de CO<sub>2</sub> en fonction de l'inverse de la température (diagramme d'Arrhénius) pour différents types de catalyseurs (réf. [34] p.237).

$W(\text{CO}_2)$  increases on single crystals with increasing size



## NO sur agrégats de Pd déposés sur MgO

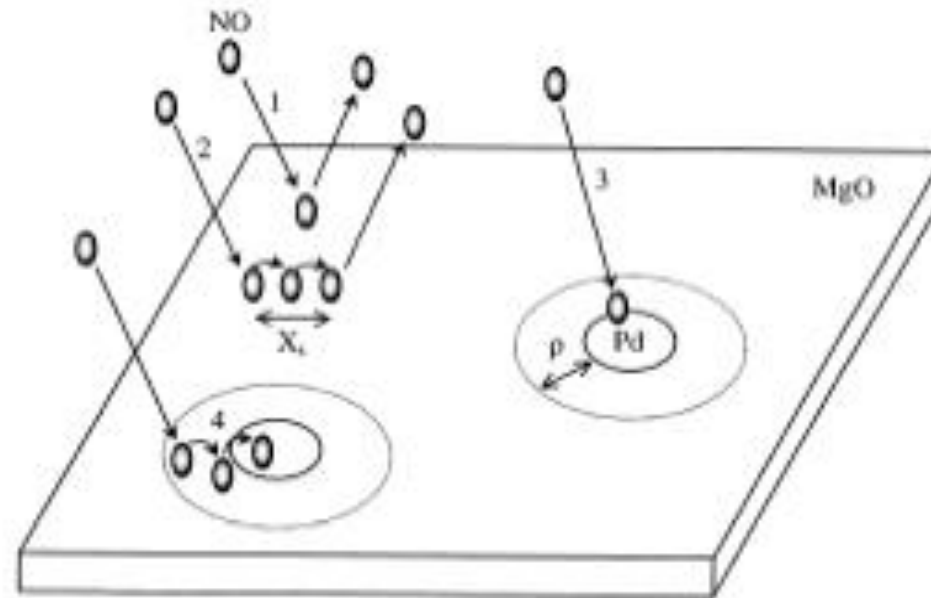
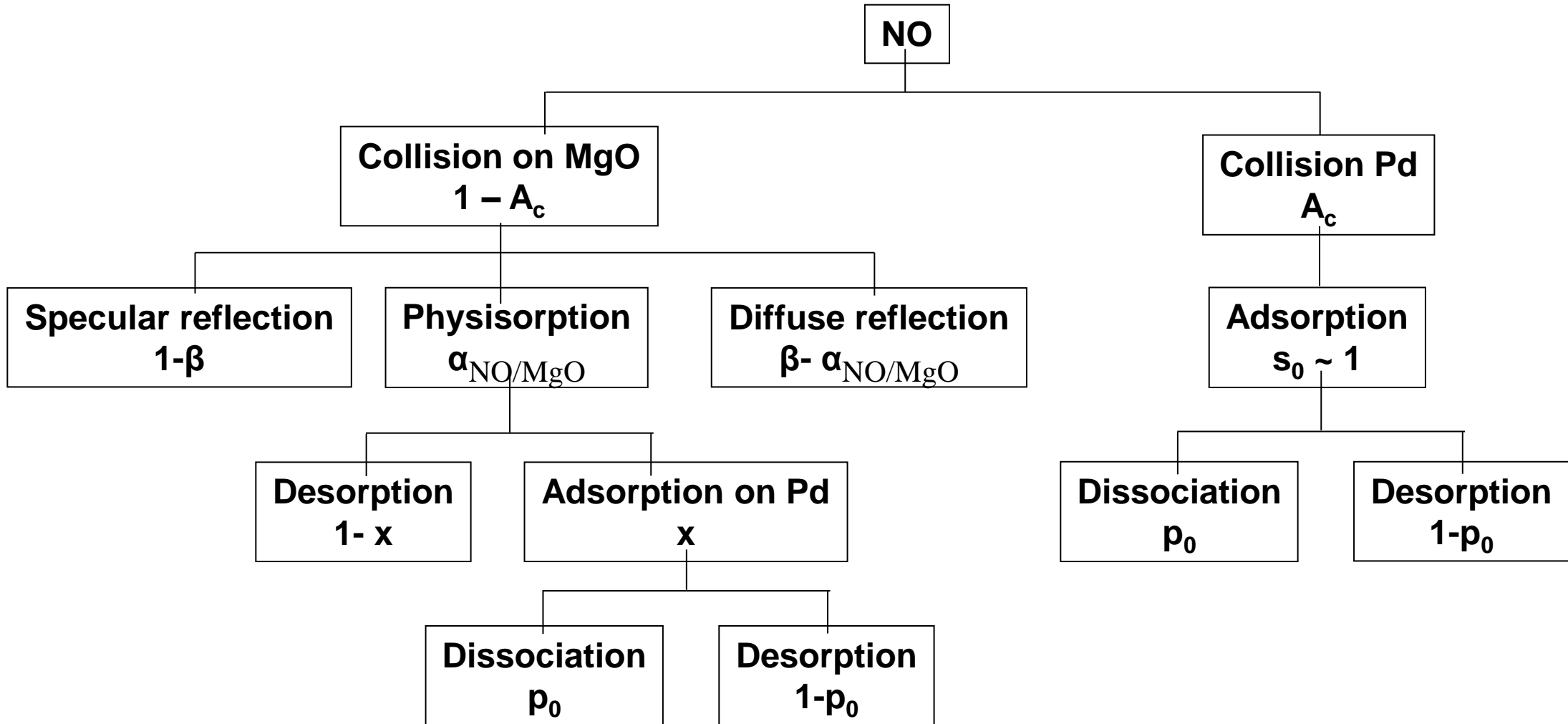


figure 2.13: Représentation schématique des étapes élémentaires de l'interaction NO/Pd/MgO précédant la chimisorption: (1) réflexion (spéculaire ou diffuse), (2) adsorption et diffusion sur le support (libre parcours moyen  $X_s$ ), (3) adsorption sur les agrégats par impact direct, (4) adsorption sur les agrégats par capture de molécules diffusant sur le support, à l'intérieur d'une zone de capture de largeur  $\rho$ . NB : Bien sûr, la réflexion peut aussi survenir à l'intérieur d'une zone de capture.

Square lattice of Pd half-spheres with radius  $R$ , surrounded by a fictitious capture area (width  $\rho = mfp$  of NO on MgO). When NO is landing on the capture area, it belongs to the cluster

$$P = P_{\text{direct}}(\text{cluster}) + P_{\text{NO/MgO}} n_s [\pi(R + \rho)^2 - \pi R^2]$$

# Steps of the interaction of NO on Pd/MgO



⇒ NO on Pd total probability of adsorption  $P = A_c + (1 - A_c)\alpha_{\text{NO/MgO}}x$

## Morphology effects

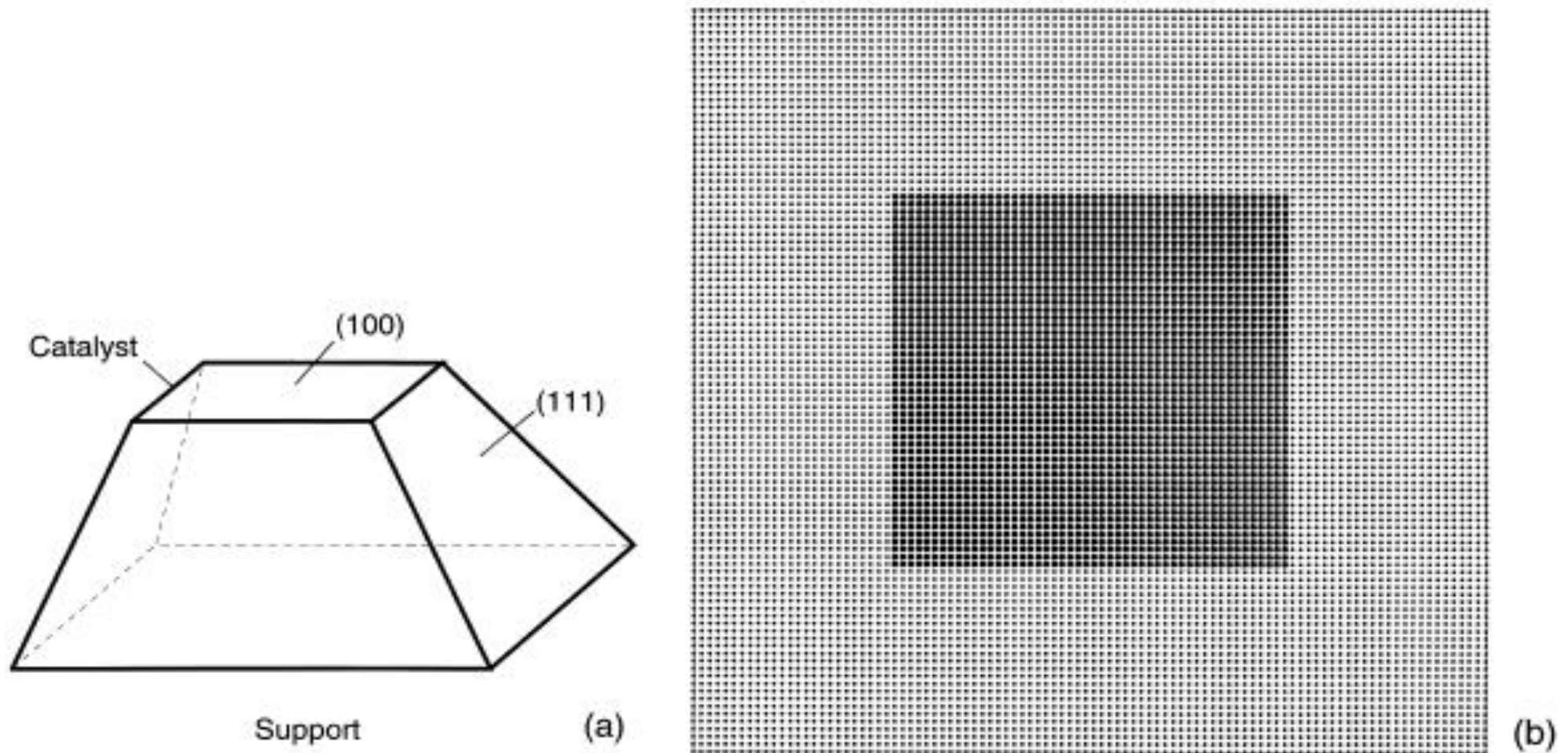


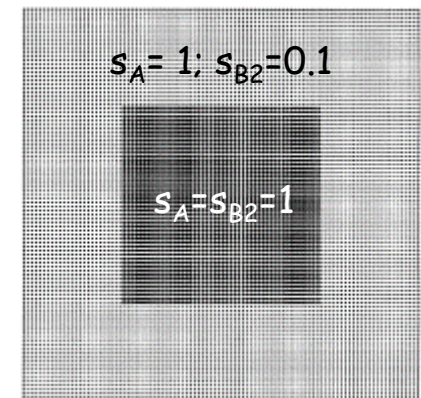
Fig. 23. (a) Typical shape of a supported metal particle. (b) 2D  $100 \times 100$  lattice mimicking a particle shown on panel (a). The central  $50 \times 50$  part of the lattice (large filled circles) represents the top (001) facet. The periphery (small circles) models the side (111) facets. (From [77].)

# Algorithm

**Step 1:** The arriving molecule is chosen to be A with the probability  $p$  and  $B_2$  with the probability  $1 - p$ .

**Step 2:** If the arriving molecule is  $B_2$ , two adjacent sites are selected at random. If either site is occupied, the trial ends [corresponding to direct second-order adsorption (no precursor states)]. Otherwise,  $B_2$  dissociates and adsorbs on the chosen sites with unit probability, if both sites belong to the central part of the lattice, or with the probability  $s_{B_2}^p$  if at least one of the sites is located on the periphery of the lattice.

**Step 3:** If the arriving molecule is A, a site (site 1) on the lattice is selected at random. If that site is occupied, the trial ends (no precursor states). Otherwise, A adsorbs. The subsequent reaction of A does not occur with a B particle adjacent to site 1, but somewhere else on the lattice. The reason is that A diffusion is even more rapid than the reaction step. We also need to take into account that the A-binding energies and the LH<sup>\*</sup>-reaction rate constants for the central part and the periphery of the lattice might be different. For these reasons, the A consumption is executed via a few substeps.



## Algorithm (Cont'd)

**Step 3.1:** Taking into account that diffusion of an A particle is very rapid, we realize the canonical distribution for this particle on all the available sites (i.e., on the sites which are free of B particles). In our case, this distribution depends the binding-energy difference,  $\Delta E$  ( $\Delta E > 0$ ), between the central and peripheral sites. Practically, the canonical distribution is imitated by choosing at random another site, i.e., site 2 (after site 1 was chosen and provided site 1 was empty). If this site 2 is vacant, the A particle originally landing on site 1 is placed on site 2 with the probability  $q_p$  if site 2 is located on the periphery, and with the probability  $q_c$  if it belongs to the central part of the lattice [the parameters  $q_c$  and  $q_p$  are chosen so that one of them is equal to unity and the other is lower than or equal to unity; thus, the lower value of  $q$ , i.e.,  $q_{\min} = \min(q_c, q_p)$ , and  $\Delta E$  are interconnected as  $q_{\min} = \exp(-\Delta E/T)$ ].

If an attempt of replacement from site 1 to site 2 is not successful [i.e., site 2 is occupied or a generated random number (from 0 to 1) is higher than  $q_c$  or  $q_p$ , respectively], a new site (site 3) is chosen for another attempt of replacement, etc., until a successful replacement occurs.

**Step 3.2:** After successful replacement, the A particle tries to react. An adjacent site to, where A was placed in (step 3.1) is randomly selected, and if this site is occupied by a B particle this A–B pair is removed from the lattice (i.e., AB leaves the surface) with the probability  $r_p$ , if either reactant is located on the periphery, and with the probability  $r_c$ , if both reactants are adsorbed on the central part of the lattice (the parameters  $r_c$  and  $r_p$  are chosen so that one of them is equal to unity and the other is lower than or equal to unity). If the reaction trial is realized, we return to (step 1) above. Otherwise, steps 3.1 and then 3.2 are repeated again until a successful reaction event occurs.

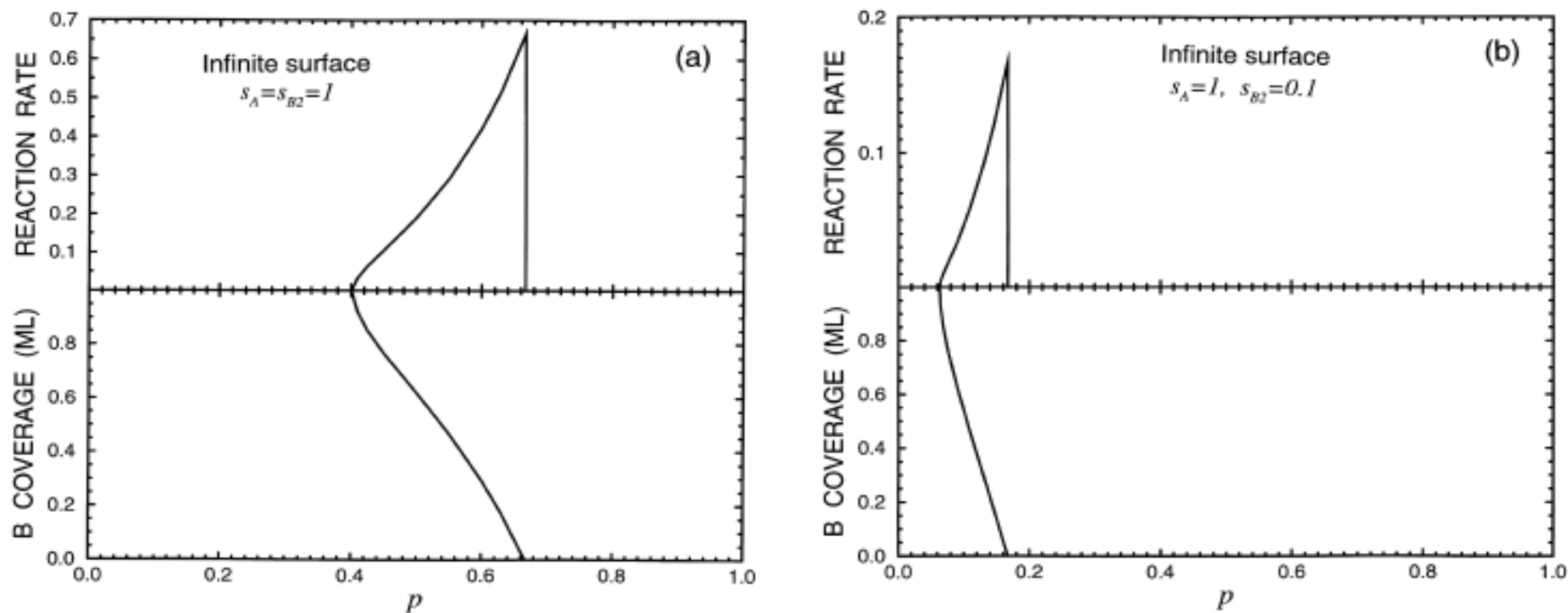


Fig. 24. Reaction rate (A molecule/site MCS) and B coverage for rapid  $2A + B_2 \rightarrow 2AB$  reaction with irreversible A and  $B_2$  adsorption, rapidly-diffusing A particles and immobile B particles. The catalyst surface is infinite. (a) Results for the case when the A and  $B_2$  sticking coefficients are equal,  $s_A = s_{B_2} = 1$ . (b) As (a) but for  $s_A = 1$  and  $s_{B_2} = 0.1$ . (From [77].)

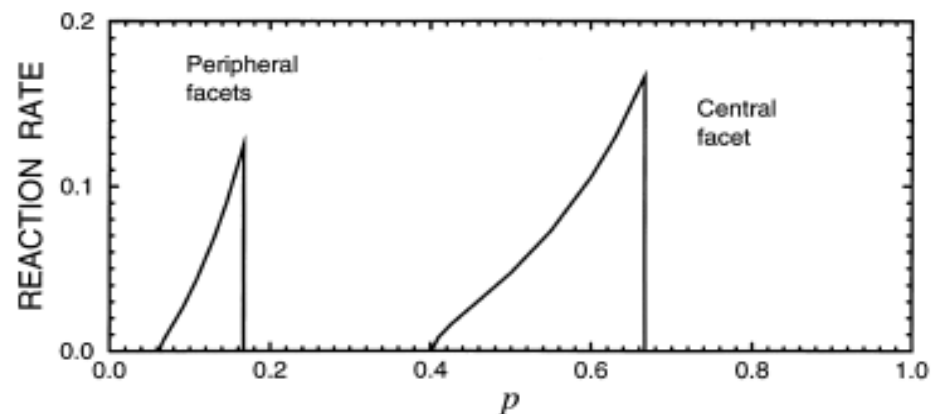


Fig. 25. Superposition of the reaction rates shown in Figs. 24a and b. (From [77].)

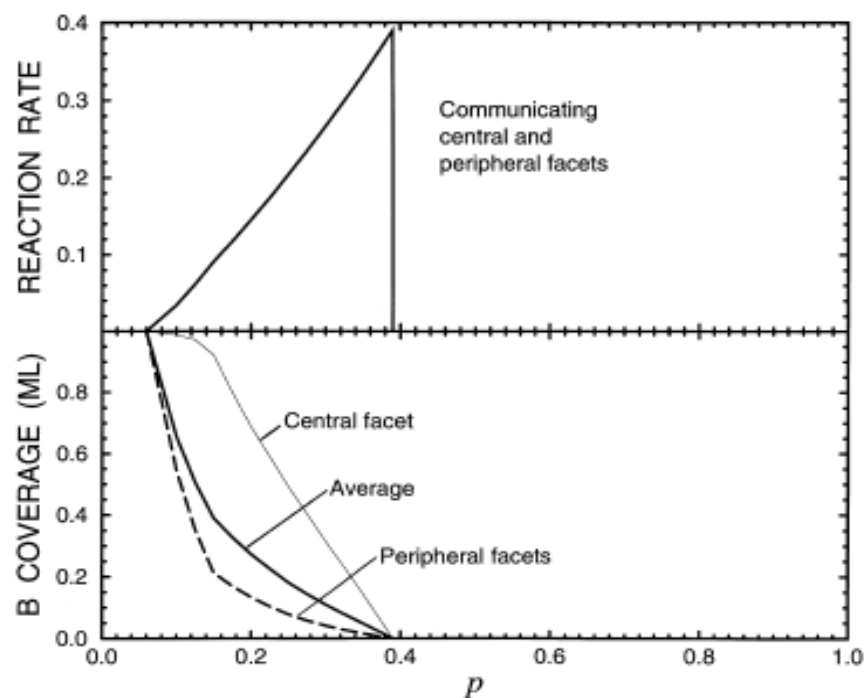


Fig. 26. Reaction rate (A molecule/site MCS) and B coverages for rapid  $2A + B_2 \rightarrow 2AB$  reaction occurring on the finite lattice (Fig. 23b) mimicking a supported catalyst. The thick solid line (on panel (b)) shows the average coverage, the thin solid line corresponds to the coverage of the central facet of the nanoparticle, and the dashed line exhibits the coverage of sites on the peripheral facets. The parameters employed are as follows:  $s_A = 1$ ,  $s_{B_2}^c = 1$ ,  $s_{B_2}^p = 0.1$ ,  $q_c = q_p = 1$ , and  $r_c = r_p = 1$ .

## Example of kinetics

$2A + B_2 \rightarrow 2AB$  reaction  $\theta_{A,B}$  = coverage rate of A, B

$$\frac{d\theta_A}{dt} = k_A^a P_A (1 - \theta_A - \theta_B) - k_A^d \theta_A - k_T \theta_A \theta_B,$$

$$\frac{d\theta_B}{dt} = k_{B_2}^a P_{B_2} (1 - \theta_A - \theta_B)^2 - k_T \theta_A \theta_B,$$

**Case (1)**  $\theta_B \gg \theta_A$  and  $\theta \simeq \theta_B$ , where  $\theta = \theta_A + \theta_B$ ,

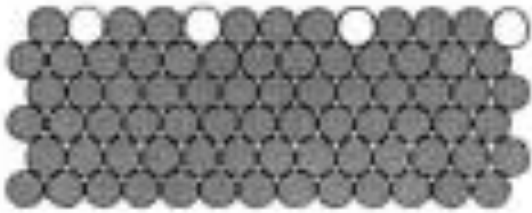
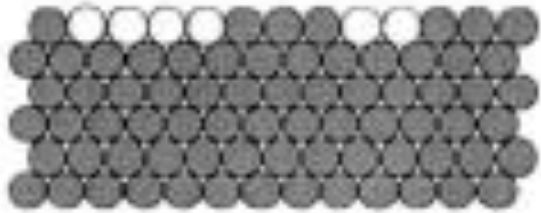
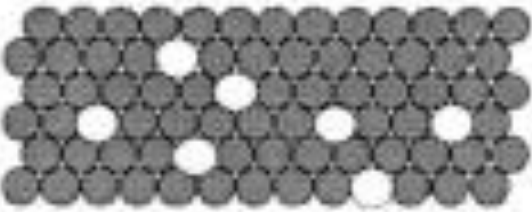
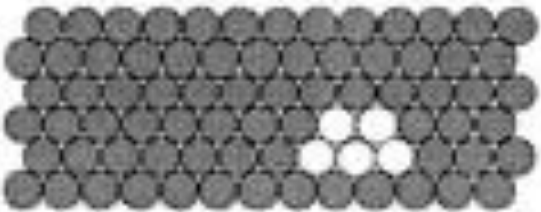
$$\frac{d\theta}{dt} = k_{B_2}^a P_{B_2} (1 - \theta)^2 - k_A^a P_A (1 - \theta).$$

**Case (2)**  $P_A/P_{B_2}$  is sufficiently large and  $\theta \simeq \theta_A$

$$\frac{d\theta}{dt} = k_A^a P_A (1 - \theta) - k_A^d \theta - k_{B_2}^a P_{B_2} (1 - \theta)^2.$$



## Alloy effects

		Mixing	
		$e_{\text{mix}} > 0$ alloy formation	$e_{\text{mix}} < 0$ phase separation
Segregation	$e_{\text{segr}} < 0$ adsorbate atoms stay at the surface		
	$e_{\text{segr}} > 0$ adsorbate atoms migrate into the bulk		

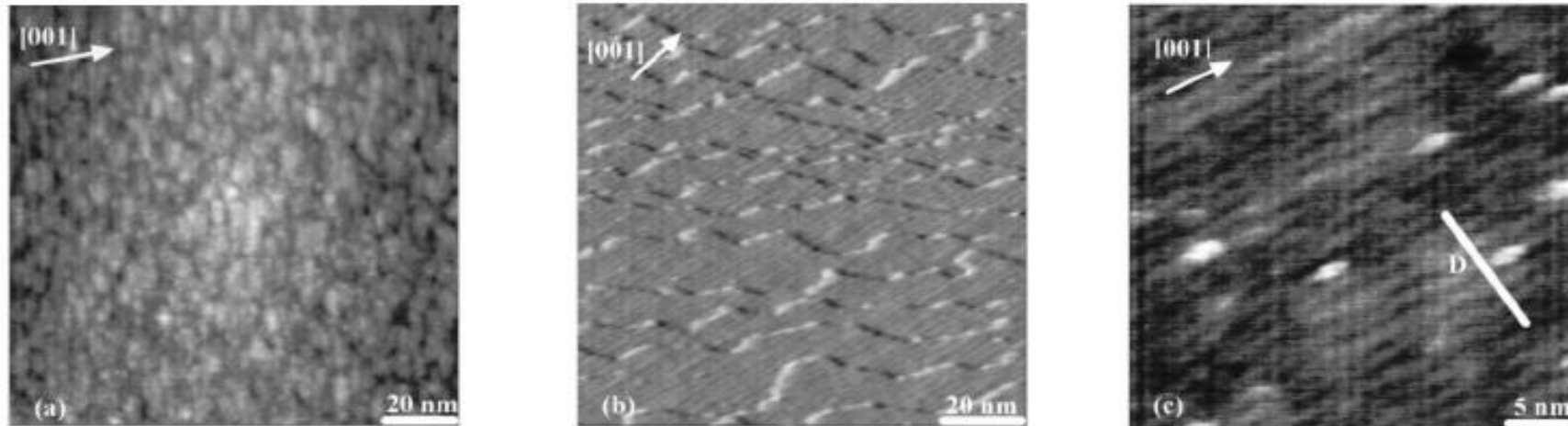
## Alloy effects

### Mixing

### Segregation

	$e_{mix} > 0$ alloy formation	$e_{mix} < 0$ phase separation
$e_{segr} < 0$ adsorbate atoms stay at the surface	Co*, Ru, Rh, Pd, Ag, Pt, Au / Fe Rh, Pd, Ag, Pt, Au / Co Cu*, Rh, Pd, Ag, Pt, Au / Ni Pd, Ag, (Pt), Au / Cu Fe*, Co*, Ni*, Pt, Au / Ru (Fe*), Ni*, Pt, [Au] / Rh Au / Pd	Ni, Cu / Fe ([Fe]), [Ni], Cu / Co Cu*, Rh, Pd, Ag / Ru Cu, Pd, Ag / Rh Ag* / Pd Ag*, Au / Pt
$e_{segr} > 0$ adsorbate atoms migrate into the bulk	Ru / Co Fe*, [Co*], Ru / Ni Ni* / Cu (Co*) / Rh Fe*, Co*, Ni*, (Cu*) / Pd Co*, Ni*, Cu*, Rh*, Pd*, Pt*, (Au) / Ag Fe*, Co*, Ni*, Cu*, Ru*, Rh*, ([Pd*]) / Pt Fe*, Co*, Ni*, Cu*, Rh*, Pd*, (Ag*), Pt* / Au	Fe*, Co*, Ru, [Rh] / Cu Ru* / Rh Ru, Rh*, [Pt*] / Pd Fe*, Ru* / Ag Ru* / Au

## Alloys effects



**3 ML Pd/Ni(110) : (a) as deposited (b, c) after annealing at 250° C  
Nanostructuration issu de la relaxation des contraintes.**

Catalytic activity for the 1,3-butadiene hydrogenation reaction<sup>a</sup> of pure Ni(110), pure Pd(110) and Pd/Ni(110) [as-deposited at room temperature (RT) and after further heating at  $\approx 200\text{--}250^\circ\text{C}$ ] deposits [4]

	Catalyst									
	Ni(110)	0.25 ML RT	0.25 ML heated	0.5 ML RT	0.5 ML heated	1 ML RT	1 ML heated	4 ML RT	4 ML heated	Pd(110)
Activity ( $\times 10^{15} \text{ cm}^2 \text{ s}^{-1}$ )	0.35	1.1	2.2	7.4	69	8.4	46	42	142	4.3

<sup>a</sup> Results are given for a hydrogen pressure of 20 Torr and a hydrogen/butadiene ratio of 5.

## CO adsorbed on Co/Cu(111) STM picture

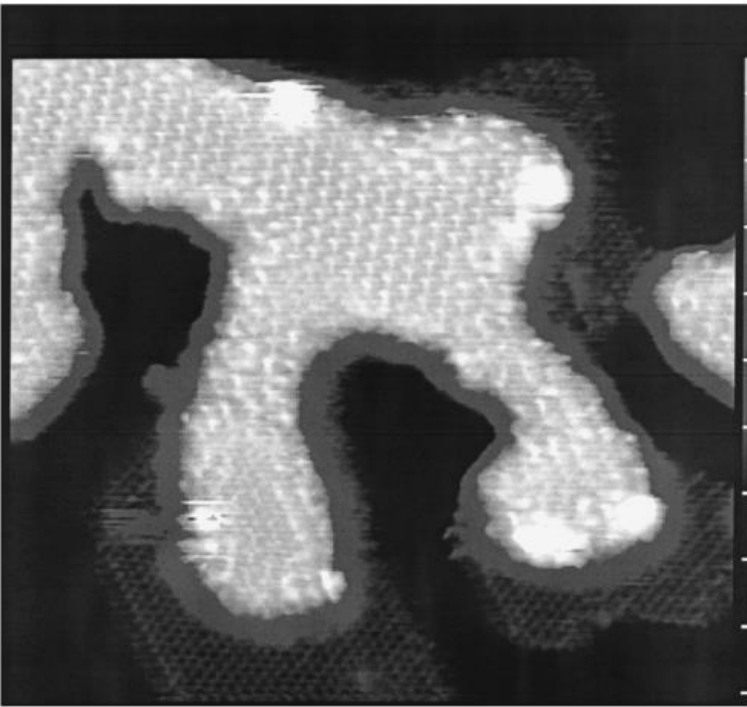
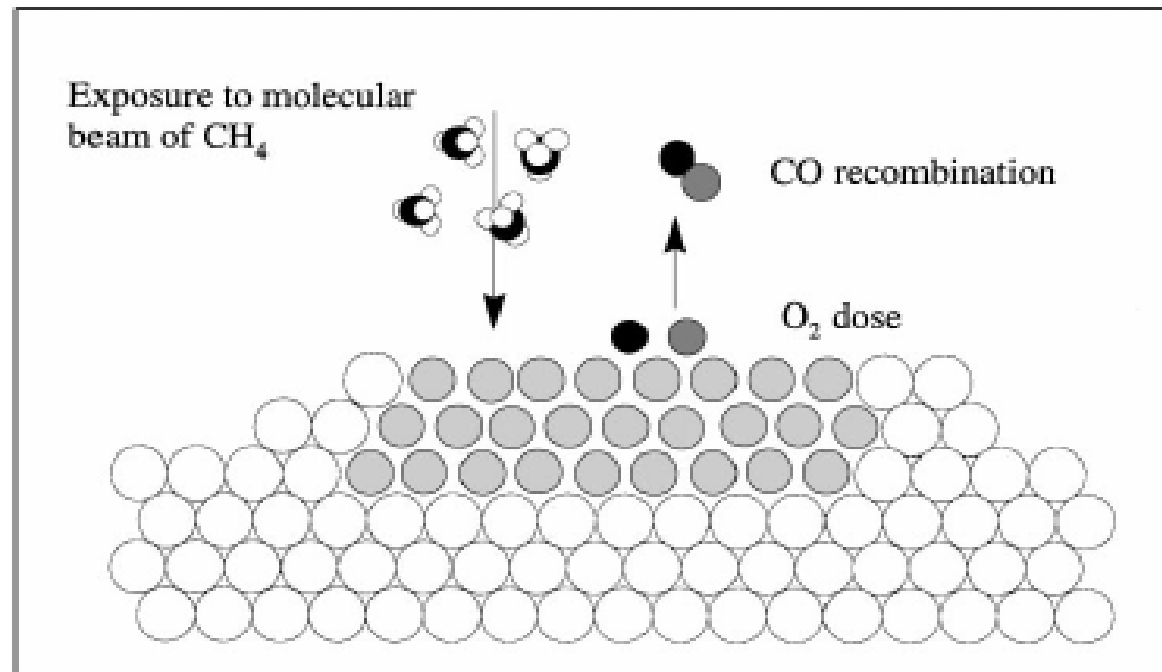


Fig. 42. STM picture of CO adsorbed on Co/Cu(111). The Co was deposited at 150 K and then CO was dosed. The scanning took place at room temperature so that CO only was bonded to Co sites. The image, covering  $140 \text{ \AA} \times 160 \text{ \AA}$ , is from Ref. [177].



## Adsorbed CO on Co/Cu(111)

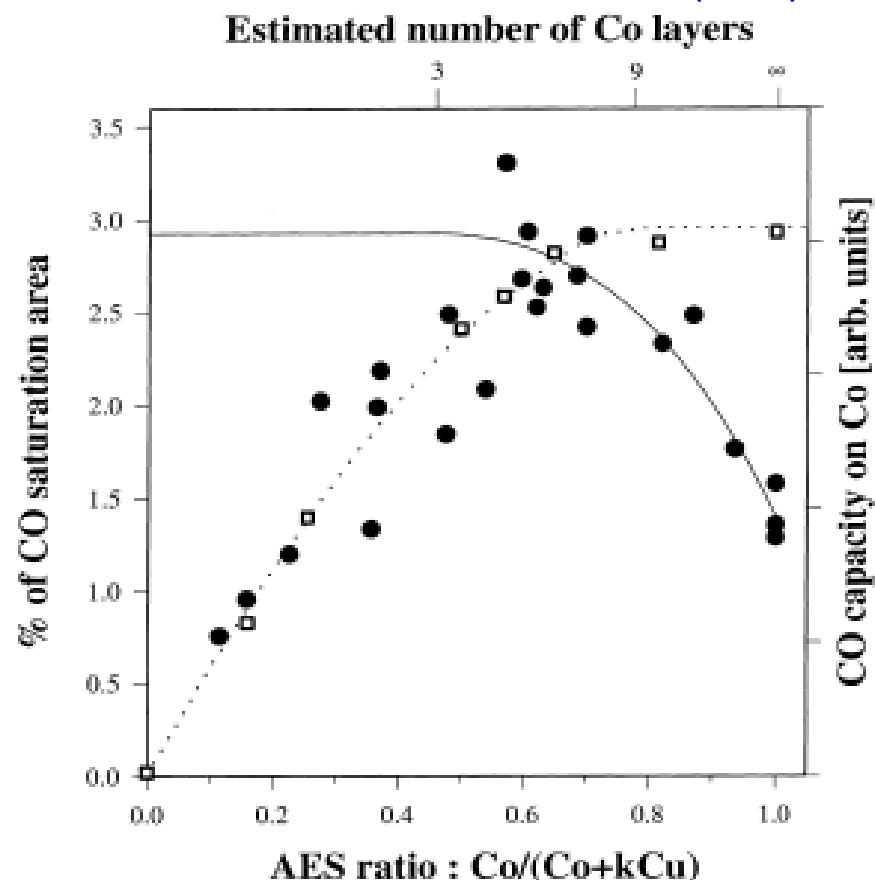
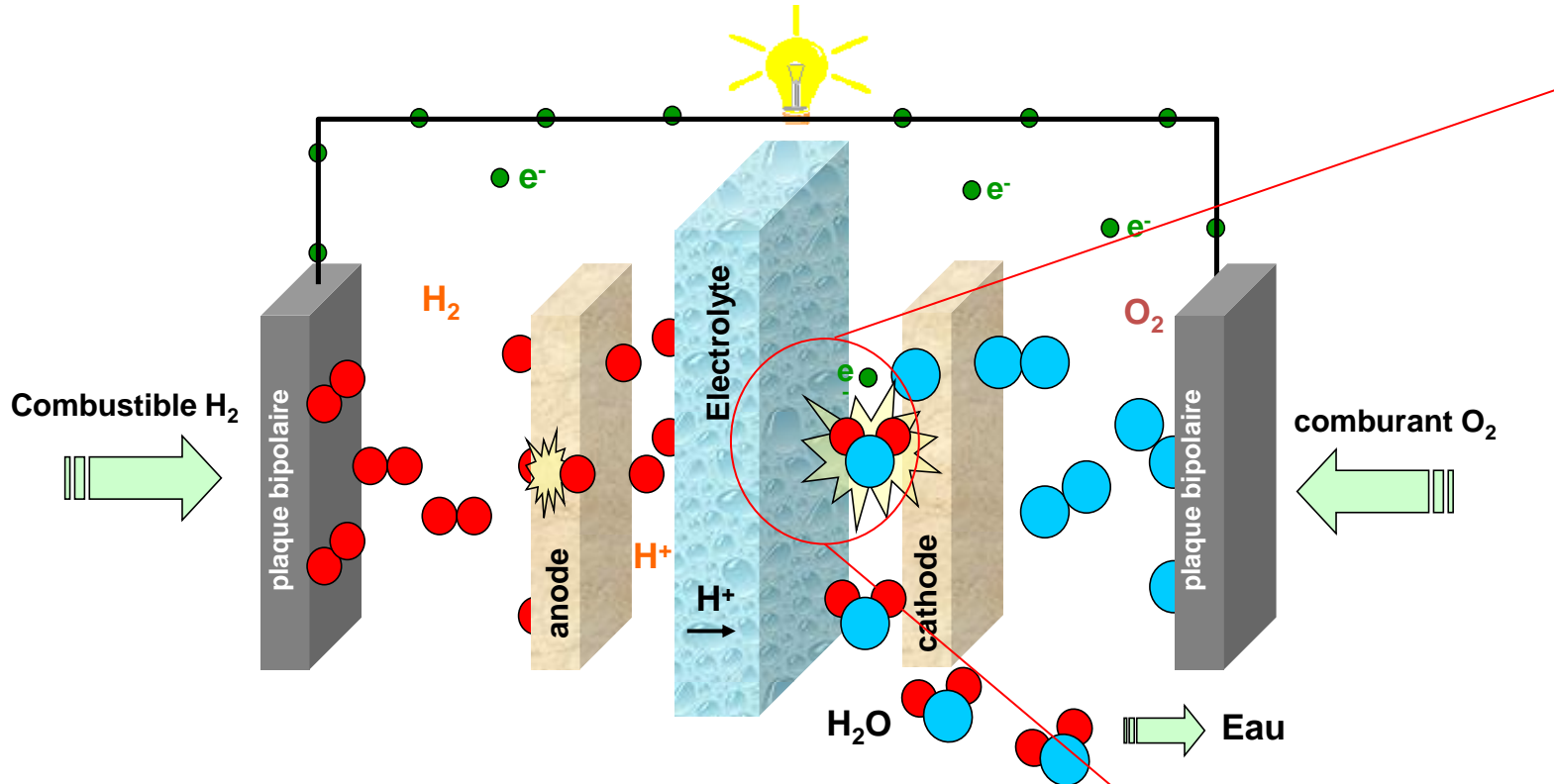
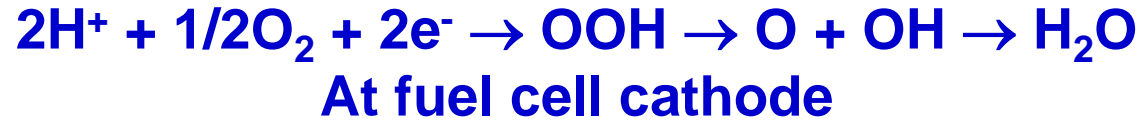


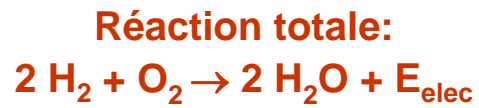
Fig. 41. Measurement of the dissociation probability of  $\text{CH}_4$  on Co/Cu(111). The dissociation probability (solid circle) is shown as the area of the recombination peak of carbon and oxygen in percent of CO saturation as a function of the Co amount. The value of the Co amount is the ratio of Auger line heights for Co divided by a weighted sum of Co and Cu. A value of 1.0 corresponds to an infinite number of Co layers. Also shown in this figure with open squares and the dotted line is the CO TPD area from Co indicating the number of Co sites available on the surface. Finally, the solid line indicates the reactivity per surface Co atom towards  $\text{CH}_4$ . The behavior of this line is further discussed in the text. From Auger measurements, the number of Co layers corresponding to the AES ratio has been indicated for 3, 9 and an infinite number of Co layers.

# Alloys effects

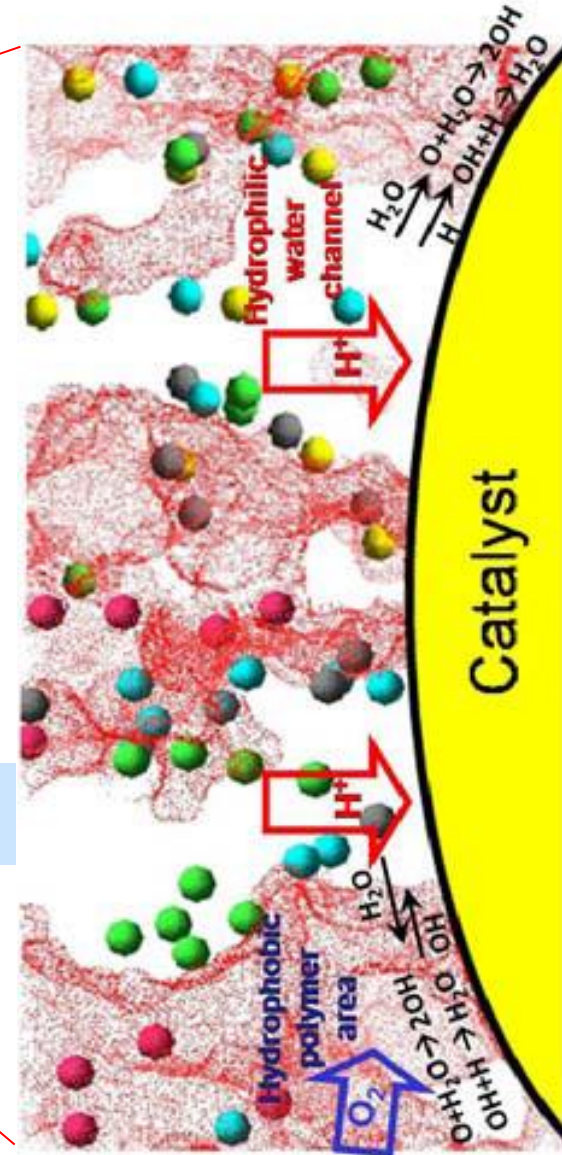


Réaction anodique  
 $\text{H}_2 \rightleftharpoons 2\text{H}^+ + 2\text{e}^-$

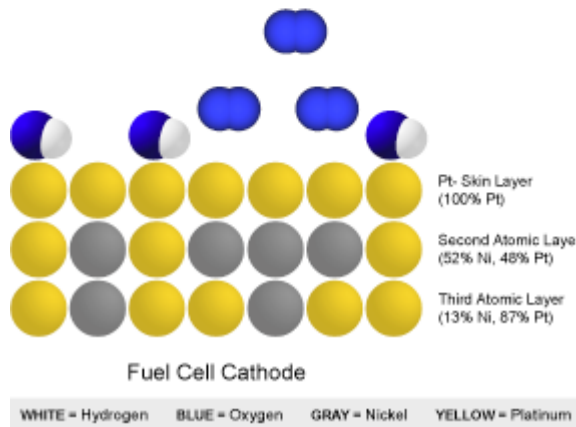
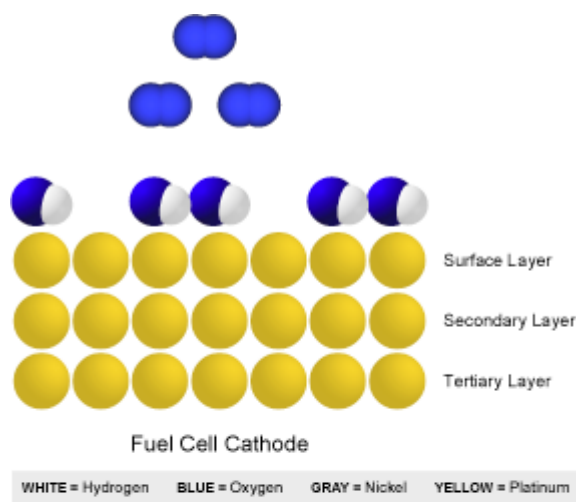
Réaction cathodique  
 $\text{O}_2 + 4\text{H}^+ + 4\text{e}^- \rightleftharpoons 2\text{H}_2\text{O}$



+ 40-50% de l'énergie est produite sous forme de chaleur



# Alloy effects

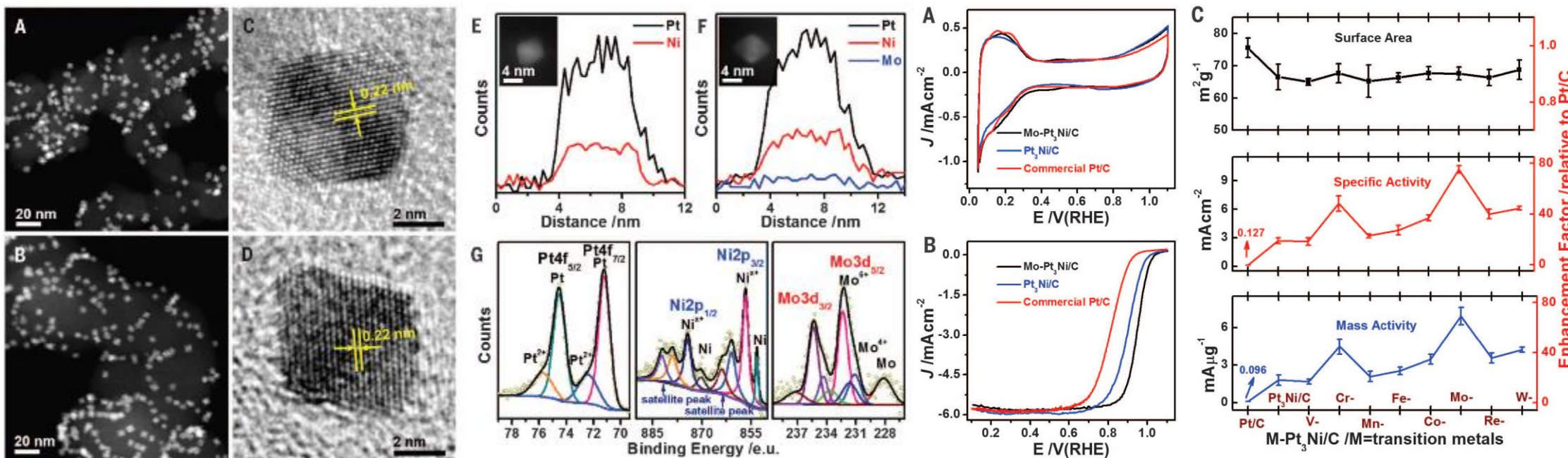


**TOP. Pt(111).**  $\text{OH}^-$  bonds tightly to platinum surface atoms, leaving less room for  $\text{O}_2$  to adsorb onto Pt active sites. Since hydroxide blocking species do not have an active role in reduction of oxygen molecules, their presence substantially hinders the rate of cathodic reaction.

**BOTTOM.  $\text{Pt}_3\text{Ni}(111)$ .** With Ni in the subsurface layers, the topmost Pt atoms (Pt-skin) have a modified electronic structure, which alters different adsorption properties of Pt. Consequently, interaction between  $\text{OH}^-$  ions and Pt-skin is weaker compared to the pure Pt catalysts, and surface is less covered by blocking species, leaving more Pt sites active for adsorption of  $\text{O}_2$ . The overall effect generates an increase in specific activity for cathodic reaction: 10 times more active than the Pt(111) surface and 90 times more active than state-of-the-art Pt/C catalysts currently used in fuel cells.

Surface Morphology	(111)	(100)	(110)
Specific Activity: $i_k$ [ $\text{mA}/\text{cm}^2$ ] 0.1M $\text{HClO}_4$ at 0.9 V versus RHE			
	$ \Delta d_{(111)}  = 0.34 \text{ eV}$	$ \Delta d_{(100)}  = 0.24 \text{ eV}$	$ \Delta d_{(110)}  = 0.16 \text{ eV}$
	$\text{Pt}_3\text{Ni}(111)$ $\text{Pt}(111)$	$\text{Pt}_3\text{Ni}(100)$ $\text{Pt}(100)$	$\text{Pt}_3\text{Ni}(110)$ $\text{Pt}(110)$
d-band center [eV]	-3.10    -2.76	-3.14    -2.90	-2.70    -2.54

# Alloys effects







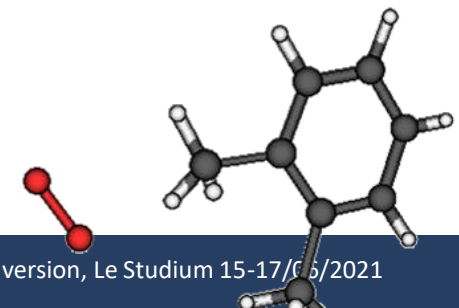
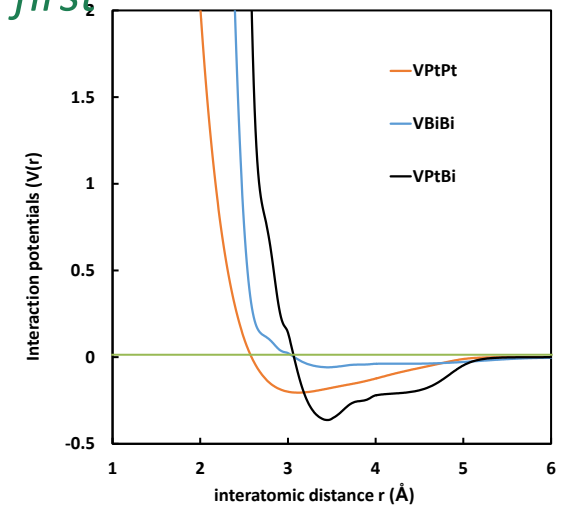
# Practical Molecular Dynamics simulation

- ✓ Calculate all trajectories of a set of atoms, molecules, ...  
via the Newton equation of motion  
→ Suitable for processes at nanoscale (up to  $10^9$  atoms)
- ✓ A rigorous approach requires the use of robust interaction potentials  
If necessary running DFT, i.e. electronic calculations → *ab-initio* or *first-principles* MD and/or Machine Learning methods
- ✓ and initial conditions (positions, velocities) preferably matching experimental conditions  
→ appropriate velocity distribution functions can be derived from experimental conditions.
- ✓ Proper energy dissipation:
  - Energy release during deposition, bond formation/breaking
  - Annealing
  - via friction term(s), thermostat(s)

$$\vec{F}_i = m_i \vec{a}_i = m_i \frac{d\vec{v}_i}{dt} = m_i \frac{d^2 \vec{r}_i}{dt^2}$$

and

$$\vec{F}_i = -\vec{\nabla}_{\vec{r}_i} U(\vec{r}_1, \vec{r}_2, \vec{r}_3, \dots, \vec{r}_N)$$





# Practical Molecular Dynamics simulation

## Relevance/significance of MD Simulations

### Flux :

Exp.  $1 \cdot 10^{15} \text{cm}^{-2} \text{s}^{-1} = 10 \text{ species} / \text{nm}^2 / \text{s}$  - MD  $1 \text{ specie} / 10 \times 10 \text{ nm}^2 / 2 \text{ ps}$

Prohibit long time diffusion, except if including specific strategies (fbMC, CVHD, hyperdynamics, ...)

### Pressure/simulation box size

Solid density : Pt  $65 \text{ nm}^{-3}$

Liquid density: water  $33 \text{ nm}^{-3}$

If box size is in the range  $10 \times 10 \times 10 \text{ nm}^3 \rightarrow 65 \text{ 000 Pt atoms}$  or  $33 \text{ 000 water molecules}$   
 $\rightarrow$  Statistical quantities (diffusion coeff, reaction rates, etc) can be directly calculated

Gas density :  $1 \text{ atm} = 2.4 \cdot 10^{-2} \text{ nm}^{-3}$

$\rightarrow$  Not enough species in box of size  $d$  at pressure  $P$

$\rightarrow$  Chemistry and reactivity in the gas phase require scaling law between simulation box and reactor sizes

**Solution:** relevant parameter = Collision number  $\propto P \cdot d \rightarrow \uparrow P \downarrow d$  should work.



# Practical Molecular Dynamics simulation

1/ recovering/scaling experimental conditions

Hypothesis : Collision number are the same in experiments and simulations so,  $P_{exp}d_{exp} = P_{sim}d_{sim}$  thus  $N_{sim} = \frac{P_{exp}}{k_B T_g} \cdot S_{sim} \cdot d_{exp}$  and if  $r_{cut}$  is the largest cutoff radius :  $d_{sim} > \frac{N_{sim}}{S_{sim}} \cdot r_{cut}^3$

Or equivalently  $\rho_{sim} = \frac{N_{sim}}{V_{sim}} < \frac{1}{r_{cut}^3}$

( $S_{sim}$ ,  $V_{sim}$  are the chosen smallest area, volume of the simulation box)

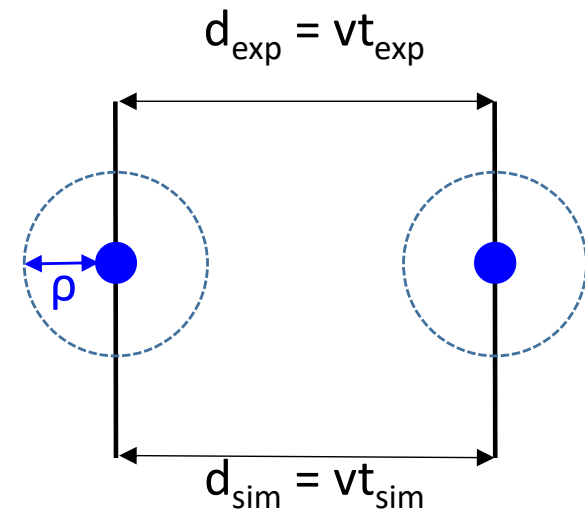
2/ Experimental time recovery

→ Velocities are same in experiments and simulations

$$v = \frac{d_{exp}}{t_{exp}} = \frac{d_{sim}}{t_{sim}}, \text{ when } d_{exp}, d_{sim} > 2\rho$$

$$\text{then, } t_{exp} = \frac{d_{exp}}{d_{sim}} \cdot t_{sim}, \text{ when } d_{exp}, d_{sim} > 2\rho$$

$$\text{or, } t_{exp} = t_{sim}, \text{ when } d_{exp}, d_{sim} \leq 2\rho$$





# Practical Molecular Dynamics simulation

## Thermal relaxation

- Choose a relevant specie release time: i.e. greater than thermalisation time
- Choose a relevant thermostat (region i.e. which should be thermostated) within this relevant time
- For interactions with surface, one can guess that only the substrate should be thermostated



# Practical Molecular Dynamics simulation

## Interaction potentials

New reactive and including electron interaction potentials (force fields) allow targeting multiscale MD simulations

### 2/ combine improved force fields

Plasma factor	Possible?	Example
electric field	yes	CNT growth
atoms and hyperthermal species	yes	Si-NW oxidation
radicals	yes	a-C:H growth
ions	yes	sputtering
electronically excited states	yes	etching
vibrationally excited states	yes / no (reaxFF)	/
photons	implicit	(polymer degradation)
electrons	Yes (eFF, e-reaxFF)	/

E. Neyts, P. Brault (Review article), *Molecular dynamics simulations for plasma surface interactions*, *Plasma Processes and Polymers* 14 (2017) 1600145



# Practical Molecular Dynamics simulation: Interactions potentials

Metals : Embedded Atom Method (EAM) (well suited for metal catalysts)

- ⇒ energy of a solid is a unique functional of the electron density.
- ⇒ uses the concept of electron (charge) density to describe metallic bonding:
- ⇒ each atom contributes through a spherical, exponentially-decaying field of electron charge, centered at its nucleus, to the overall charge density of the system.
- ⇒ Binding of atoms is modelled as embedding these atoms in this “pool” of charge, where the energy gained by embedding an atom at location  $r$  is some function of the local density.

⇒ The total energy thus writes:

$$E_{pot} = \sum_{i=1}^N E_i = \frac{1}{2} \sum_{i=1}^N \sum_{i,j,i \neq j} \phi_{ij}(r_{ij}) + \sum_{i=1}^N F_i(\rho_i) \quad \rho = \sum_{j,j \neq i} f_j(r_{ij}) \quad f(r) = \frac{f_e \exp\left[-\beta\left(\frac{r}{r_e} - 1\right)\right]}{1 + \left(\frac{r}{r_e} - \lambda\right)^{20}}$$

With pairwise function:

$$\phi(r) = \frac{A \exp\left[-\alpha\left(\frac{r}{r_e} - 1\right)\right]}{1 + \left(\frac{r}{r_e} - \kappa\right)^{20}} - \frac{B \exp\left[-\beta\left(\frac{r}{r_e} - 1\right)\right]}{1 + \left(\frac{r}{r_e} - \lambda\right)^{20}}$$

and mixing rule:

$$\phi^{ab}(r) = \frac{1}{2} \left[ \frac{f^b(r)}{f^a(r)} \phi^{aa}(r) + \frac{f^a(r)}{f^b(r)} \phi^{bb}(r) \right]$$

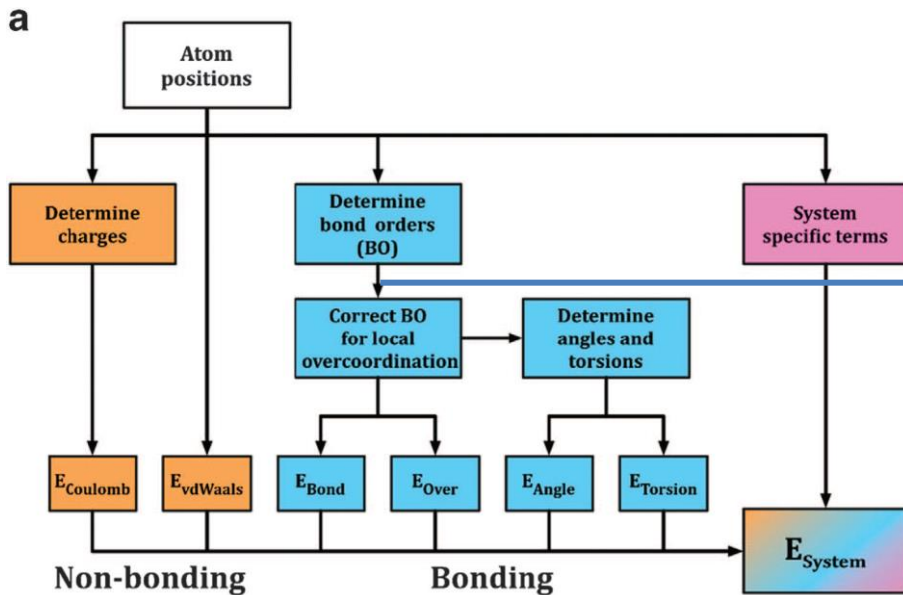
S.M. Foiles, M.I. Baskes Contributions of the embedded-atom method to materials science and engineering, MRS Bulletin, 37 (2012) 485-491.  
 X. W. Zhou et al, MDN-energy-increasing dislocations in vapor-deposited CoFe/NiFe multilayers, Phys. Rev. B 69 (2004) 144113



# Practical Molecular Dynamics simulation: Interactions potentials

ReaxFF allows for computationally efficient simulation of materials under realistic conditions, *i.e.* bond breaking and formation with accurate chemical energies. It also includes variable partial charges.

Due to the chemistry, ReaxFF has a complicated potential energy function:  $E_{\text{system}} = E_{\text{bond}} + E_{\text{over}} + E_{\text{angle}} + E_{\text{tors}} + E_{\text{vdWaals}} + E_{\text{Coulomb}} + E_{\text{Specific}}$



$$\begin{aligned}
 BO_{ij} &= BO_{ij}^{\sigma} + BO_{ij}^{\pi} + BO_{ij}^{\pi\pi} \\
 &= \exp \left[ p_{bo1} \left( \frac{r_{ij}}{r_o^{\sigma}} \right)^{p_{bo2}} \right] + \exp \left[ p_{bo3} \left( \frac{r_{ij}}{r_o^{\pi}} \right)^{p_{bo4}} \right] \\
 &\quad + \exp \left[ p_{bo5} \left( \frac{r_{ij}}{r_o^{\pi\pi}} \right)^{p_{bo6}} \right]
 \end{aligned}$$

Correct Bond Order  $\Rightarrow$  Correct description of reaction energy barriers

Overview of the ReaxFF total energy components

Parametrization using experimental known data and DFT calculations

TP Senftle et al, *The ReaxFF reactive force-field: development, applications and future directions*, npj Computational Materials 2, (2016) 15011

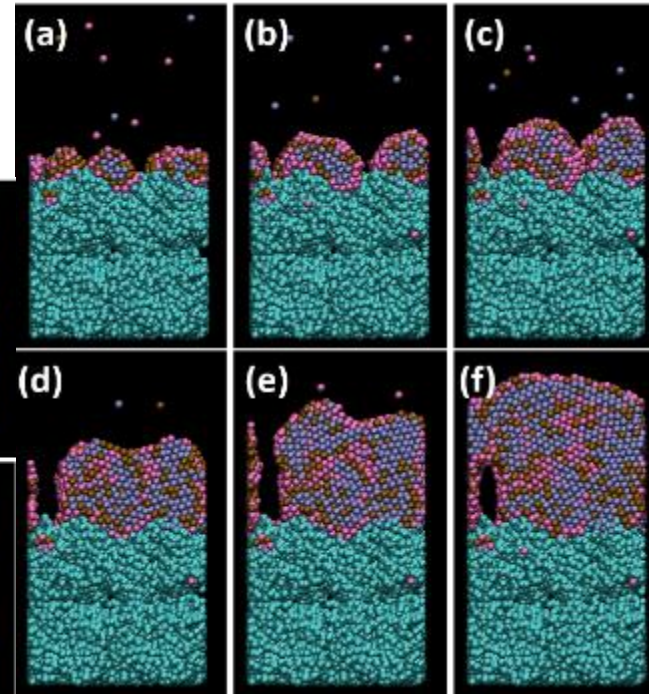
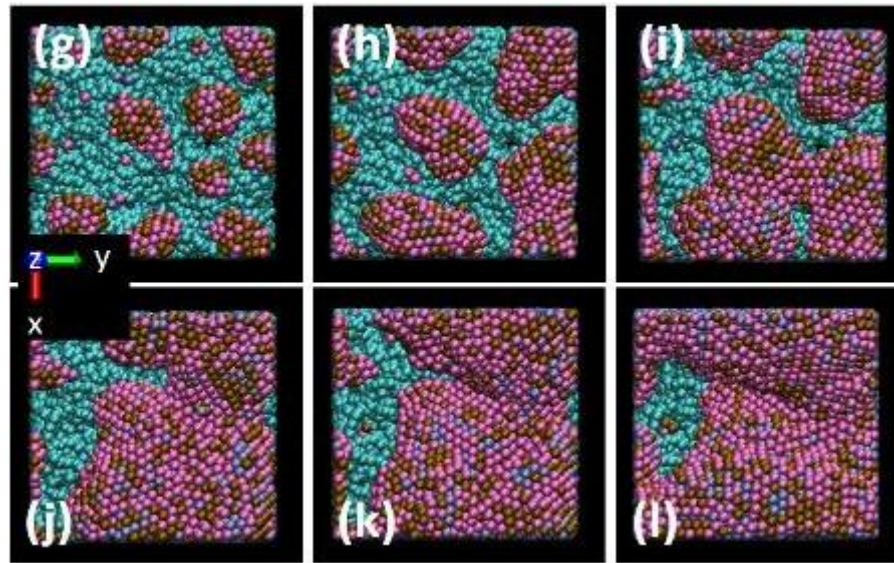
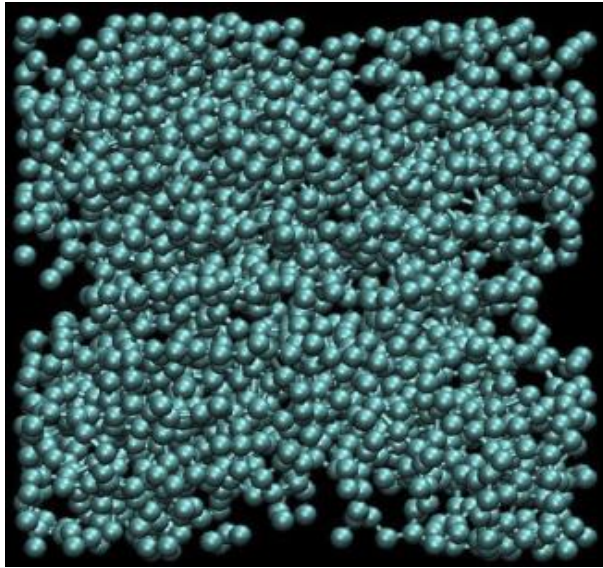
# Molecular Dynamics of plasma assisted nanocatalyst growth: Supported Pt<sub>2</sub>PdAu nanocatalyst growth on porous carbon

Potentials used in the system:

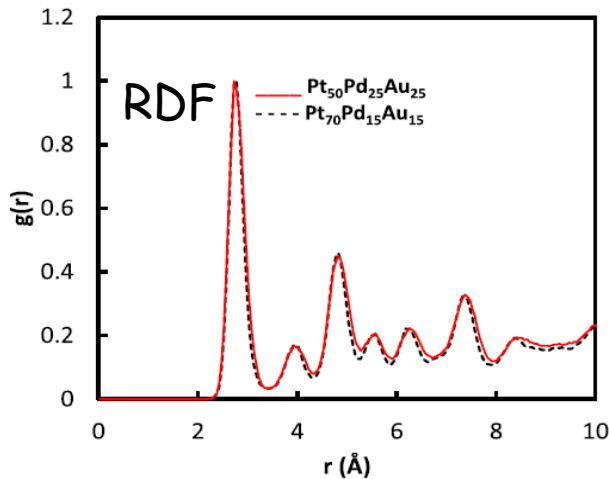
Pt-Pd-Au: EAM potentials

C – C: Tersoff potential -> thermostat

Metal – C: LJ potential (Steele)

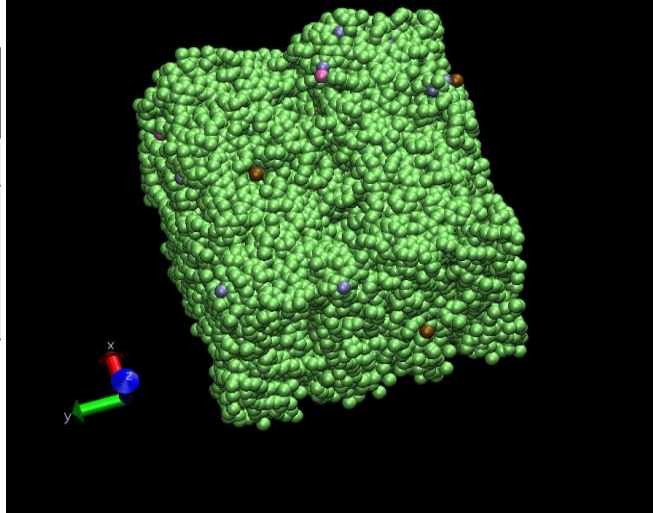


● Pt; ● Pd; ● Au



**Table 1 – EAM and average experimental surface energies of the low index faces of Pt, Pd, Au in  $\text{Jm}^{-2}$  [40].**

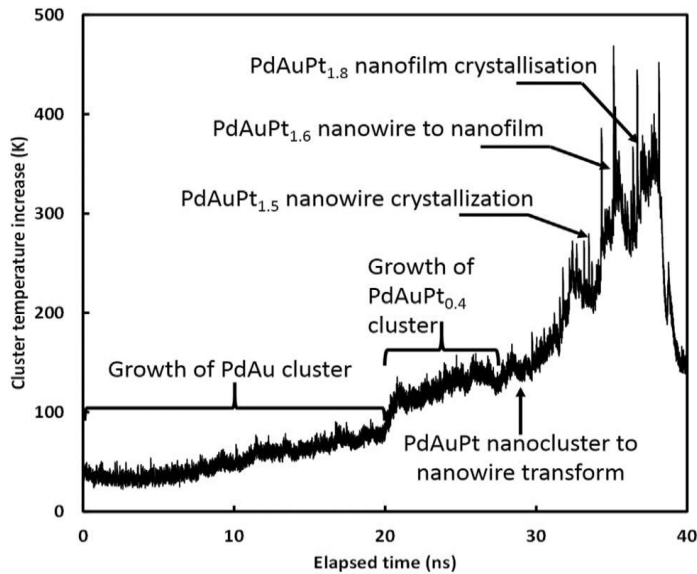
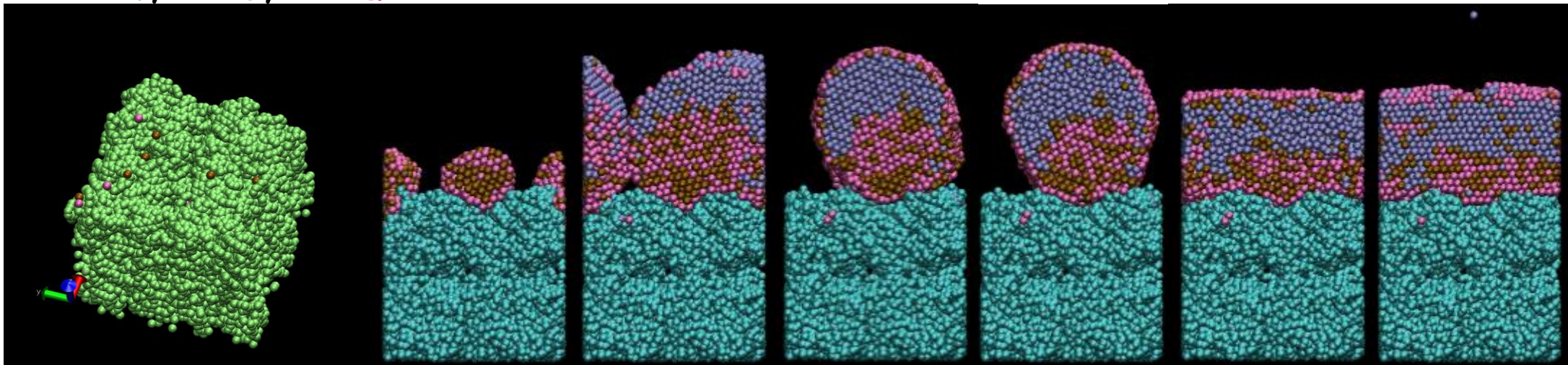
	Pt	Pd	Au
(111)	1.44	1.22	0.79
(100)	1.65	1.37	0.92
(110)	1.75	1.49	0.98
Experimental, face averaged	2.49	2.00	1.5



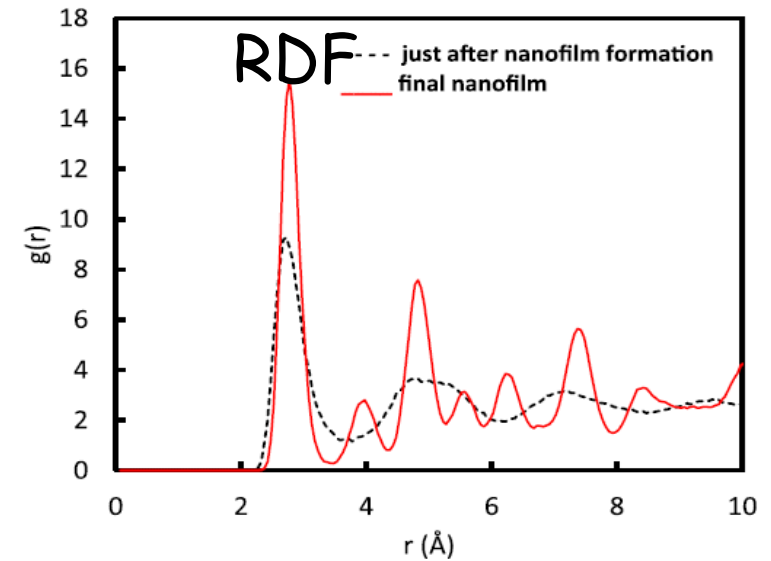


# Molecular Dynamics of plasma assisted nanocatalyst growth: Supported PdAu@Pt<sub>2</sub> core@shell nanocatalyst growth on porous carbon

● Pt; ● Pd; ● Au

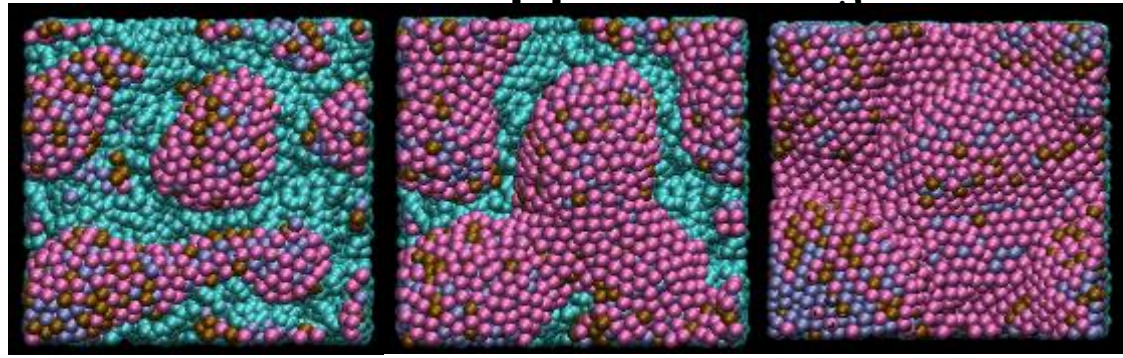


**Correlations between cluster temperature evolution and morphology transform in the course of deposition of core-shell PdAu@Pt<sub>2</sub> nanocatalyst**



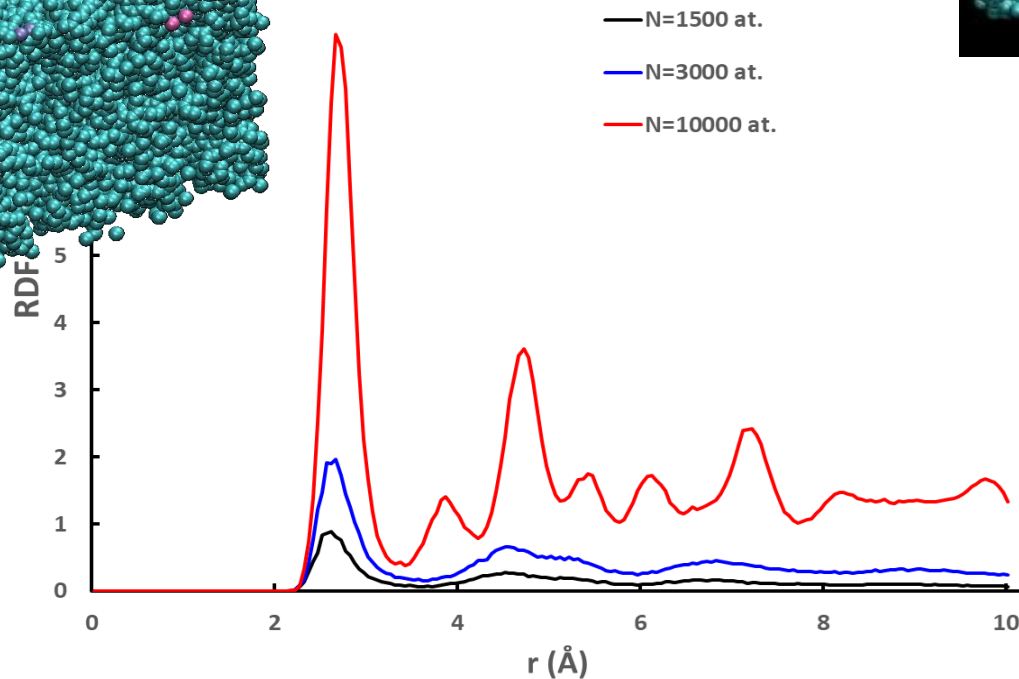
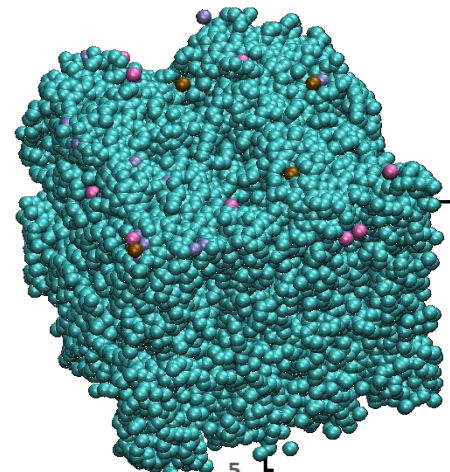
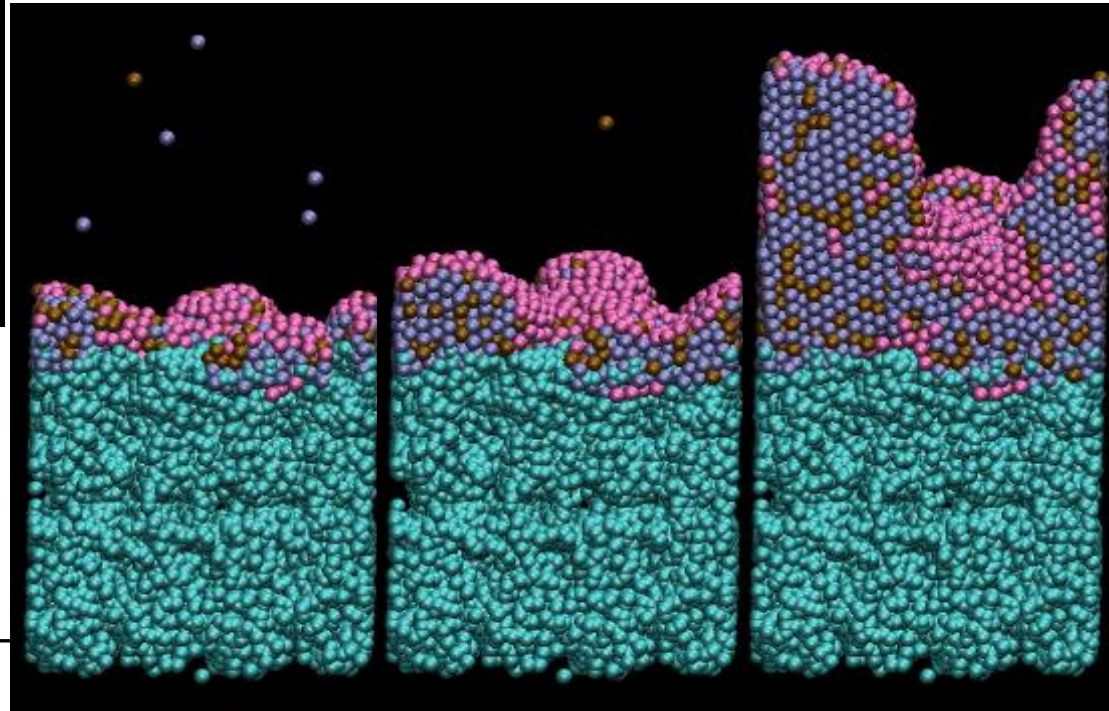
- L. Xie, P. Brault, C. Coutanceau, A. Caillard, J. Berndt, E. Neyts Appl. Cat. B, 62 (2015) 21 – 26
- P. Brault, C. Coutanceau, P. C. Jennings, T. Vegge, J. Berndt, A. Caillard, S. Baranton, S. Lankiang, International Journal of Hydrogen Energy 41 (2016) 22589-22597
- E. Neyts, P. Brault, Plasma Processes and Polymers 14 (2017) 1600145 (Review article)
- FP7 FCH-JU SMARTCat project #325327

# Molecular Dynamics of plasma assisted nanocatalyst growth: Supported Pt<sub>3</sub>NiAu nanocatalyst growth on porous carbon



● Pt; ● Ni; ● Au

→ Pt<sub>3</sub>Ni@Au



10000 at.

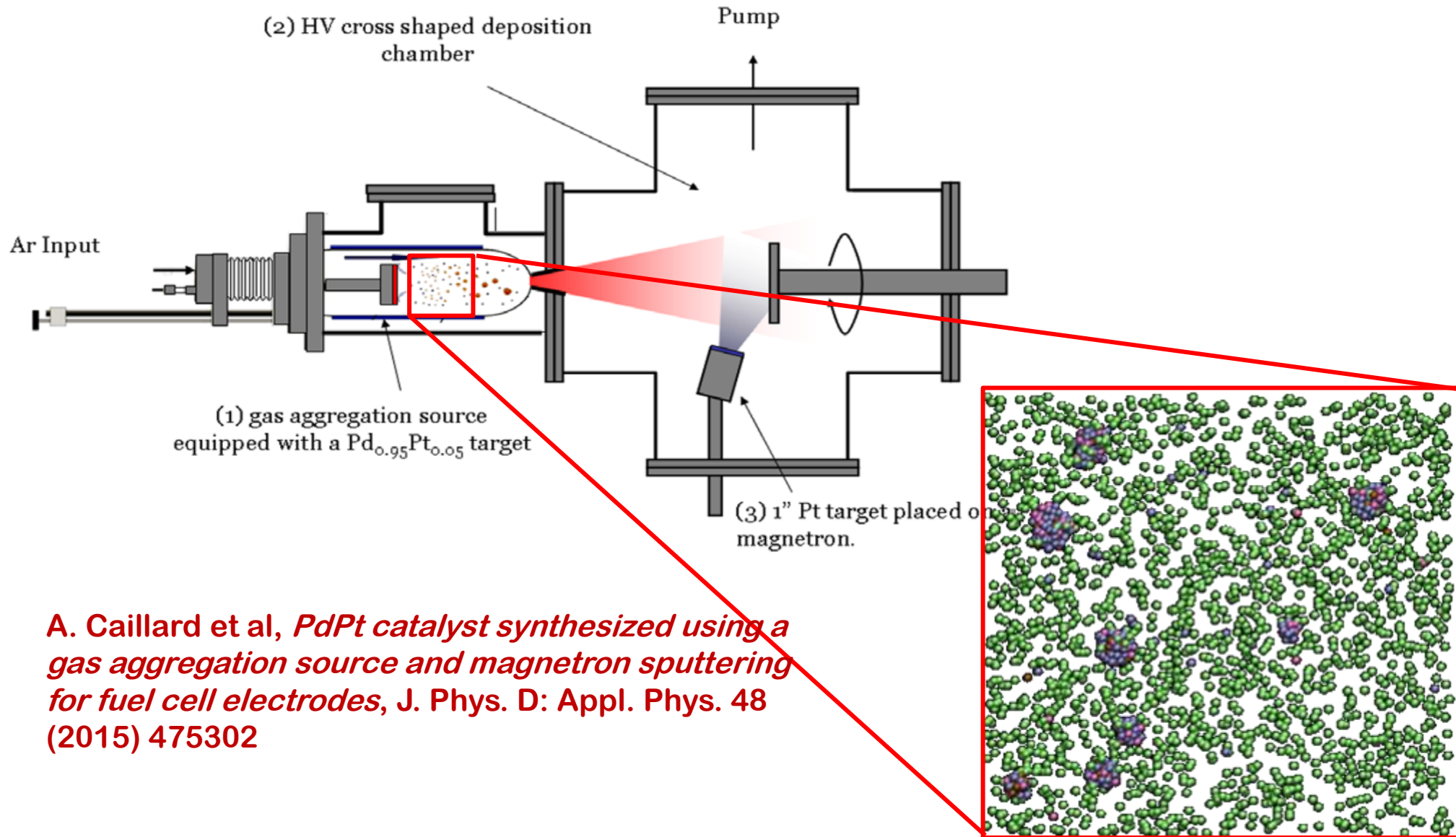
1st NN :  $d = \langle a(3\text{Pt}, 1\text{Ni})/\sqrt{2} \rangle$  (fcc)

2<sup>nd</sup> NN :  $a_0 = \langle a(3\text{Pt}, 1\text{Ni}) \rangle$

CN = 12 (3000 et 10000 at.)

# Molecular Dynamics of plasma assisted nanocatalyst growth: Free Pt<sub>3</sub>NiAu nanocatalyst growth in an Ar plasma

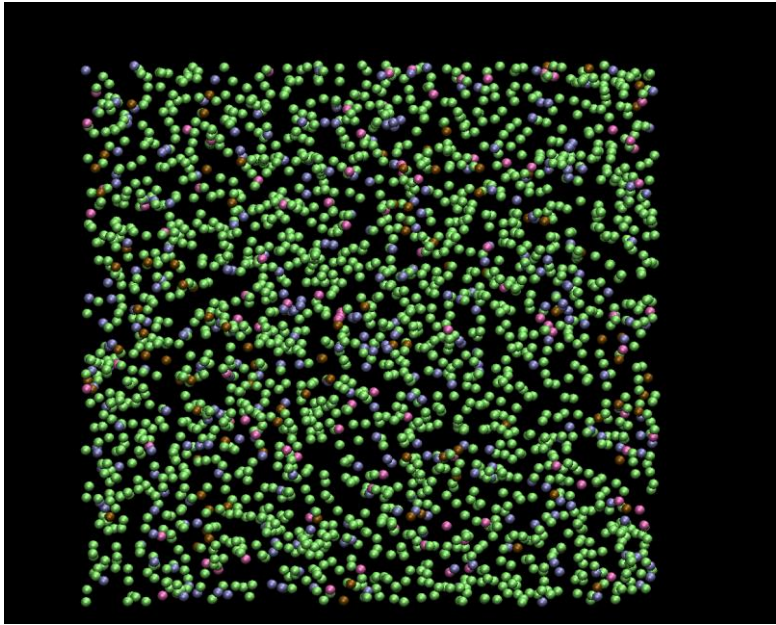
## Gas condensation nanocluster source



*A. Caillard et al, PdPt catalyst synthesized using a gas aggregation source and magnetron sputtering for fuel cell electrodes, J. Phys. D: Appl. Phys. 48 (2015) 475302*

# Molecular Dynamics of plasma assisted nanocatalyst growth: Free Pt<sub>3</sub>NiAu nanocatalyst growth in an Ar plasma

● Ar; ● Pt; ● Ni; ● Au



Temperature evolution of the vapor and of the metal vapor and then clusters display the cluster growth and coalescence : breaks in the plot (green vertical sticks)

Tricks :

NVE ensemble for Ar, Pt, Ni and Au

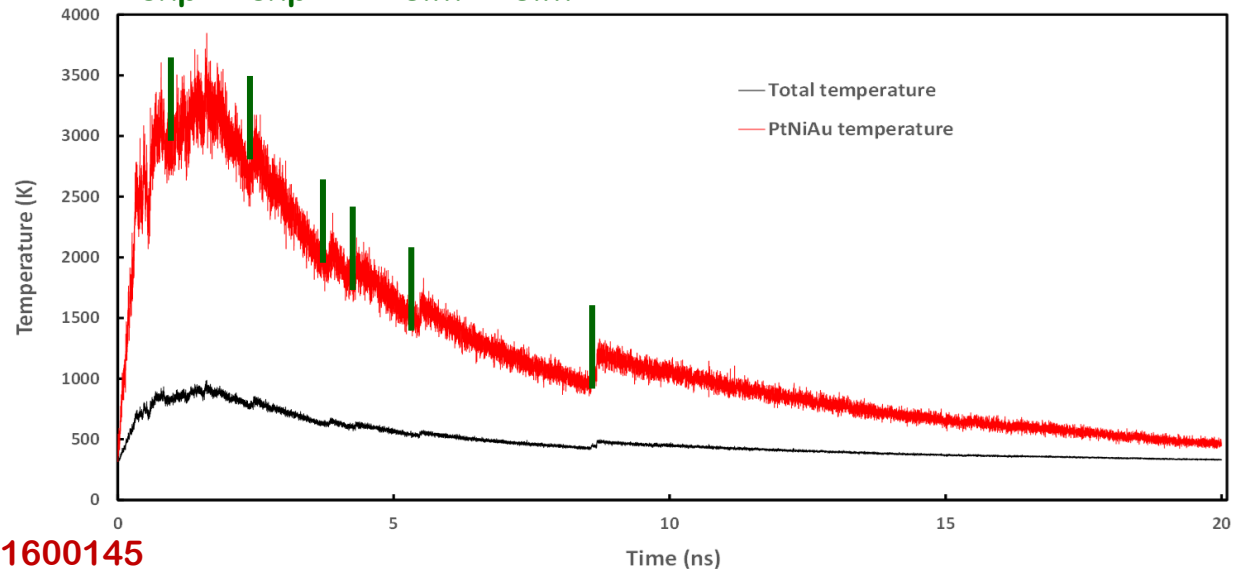
Ar surrounding gas is the thermostat

Ratio of  $N_{Ar}$  to  $N_{metal}$  estimated from experiments : depends from discharge current, Ar pressure, ...

=4 here:  $N_{Ar}=2000$ ;  $N_{Pt}=300$ ;  $N_{Ni}=100$ ;  $N_{Au}=100$

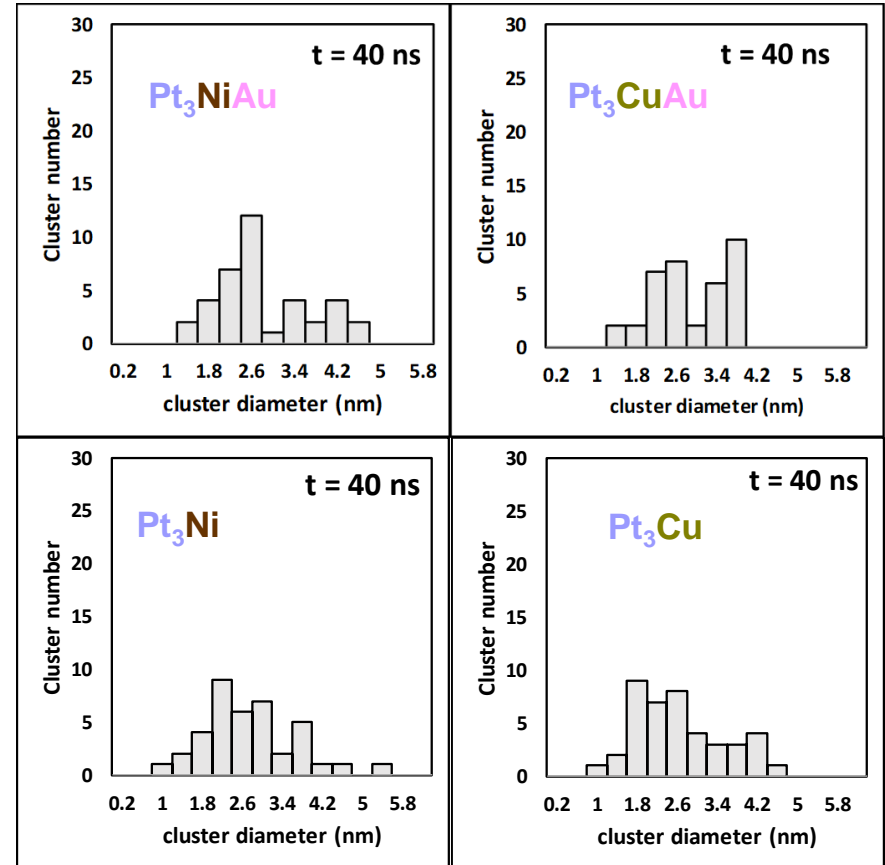
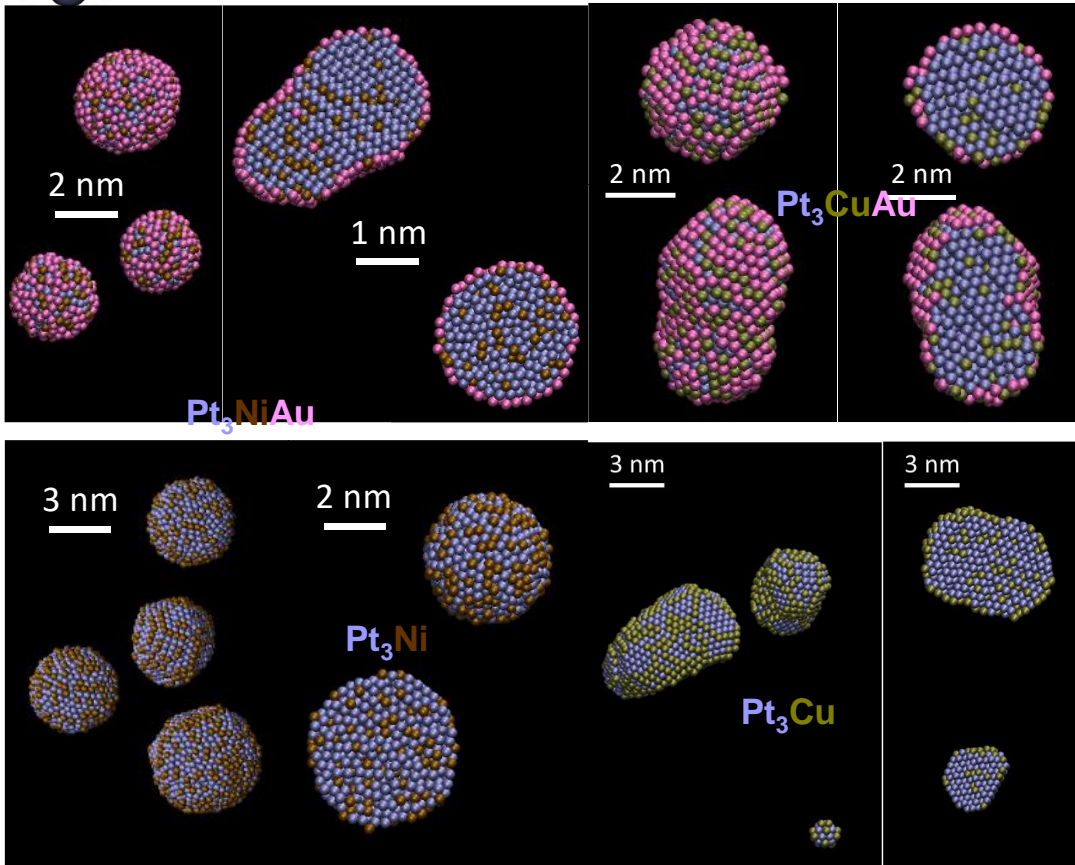
Significance : Collision number identical in experiments and in simulation

i.e.  $P_{exp} \cdot d_{exp} = P_{sim} \cdot d_{sim}$





# Free Pt<sub>3</sub>Me(Au) (Me = Ni, Cu) nanocatalyst growth



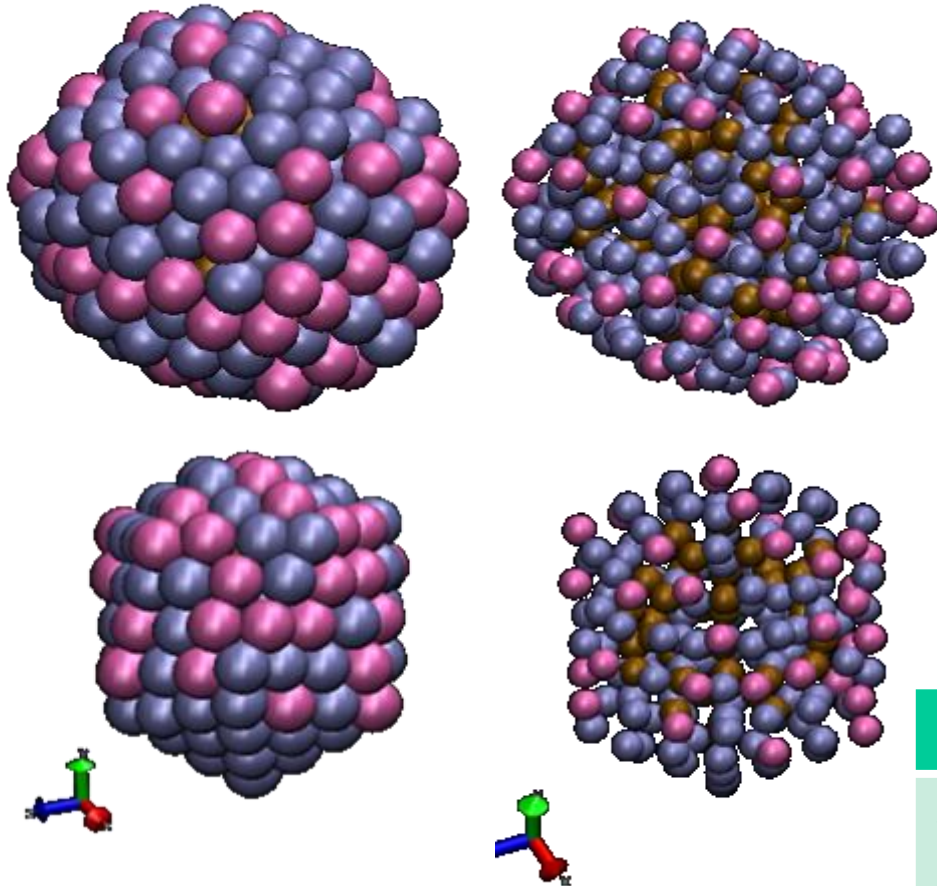
- Au segregation towards cluster surface
- CuAu surface alloy for Pt<sub>3</sub>CuAu → better efficiency for Oxygen Reduction Reaction
- Pt<sub>3</sub>Cu(Au) more well crystallized

P. Brault, et al, Pt<sub>3</sub>MeAu (Me = Ni, Cu) fuel cell nanocatalyst growth, shapes and efficiency: A molecular dynamics simulation approach, J. Phys. Chem. C 123 (2019) 29656 – 29664

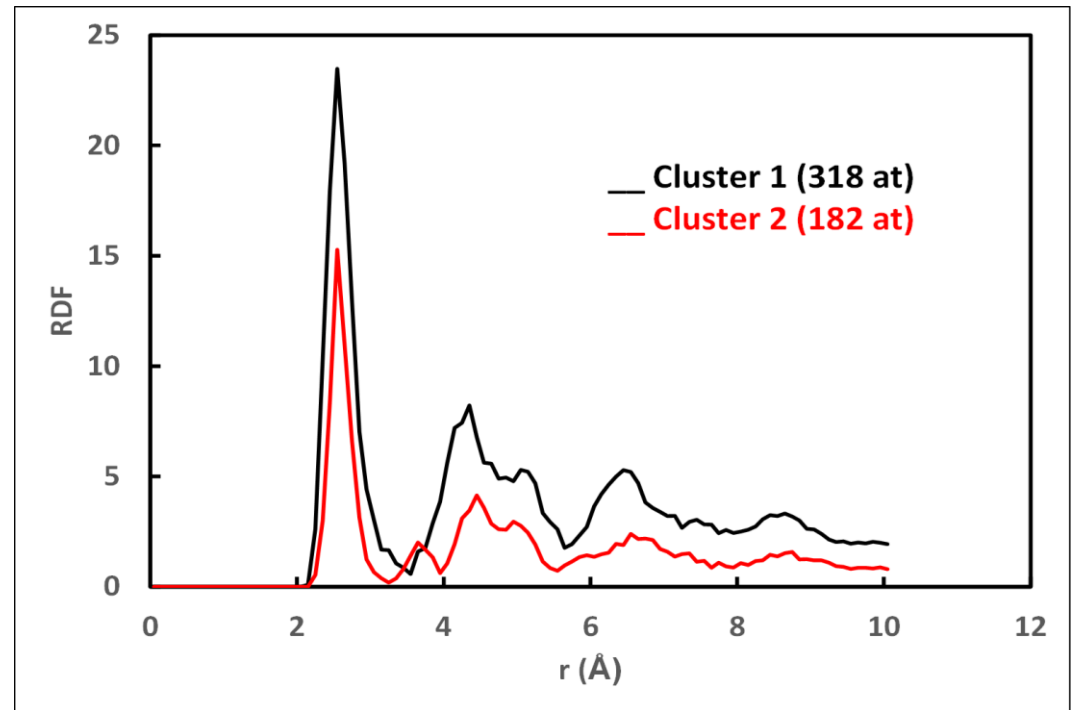
# Molecular Dynamics of plasma assisted nanocatalyst growth: Free Pt<sub>3</sub>NiAu nanocatalyst growth in an Ar plasma

● Pt; ● Ni; ● Au

Cluster 1 (318 at.) : cuboctahedron ?  
Pt<sub>189</sub>Ni<sub>62</sub>Au<sub>67</sub> ≈ Pt<sub>3</sub>NiAu



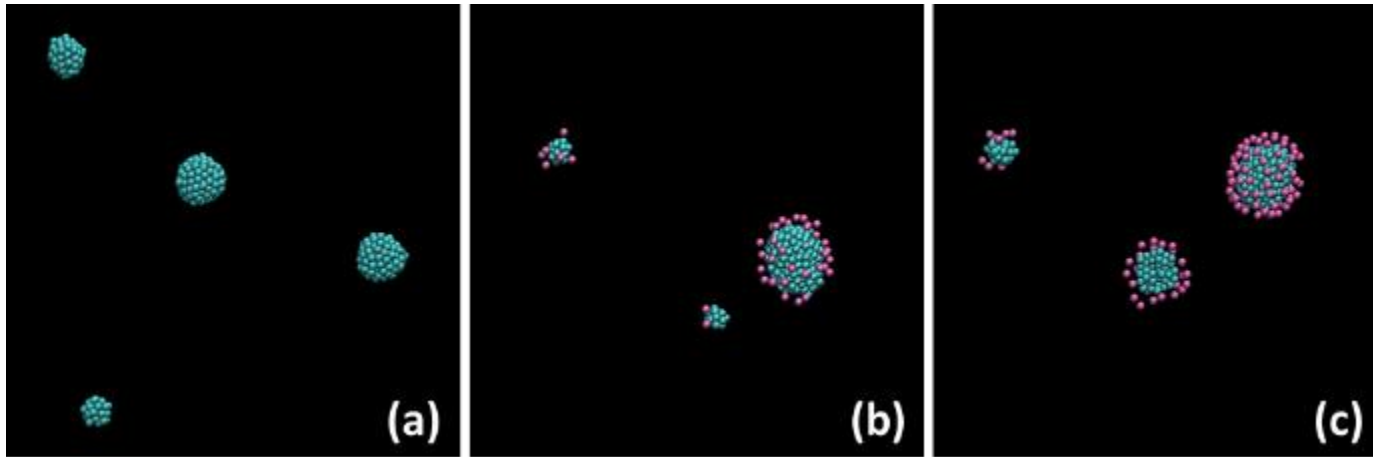
Cluster 2 (182 at.) : icosahedron ?  
Pt<sub>111</sub>Ni<sub>38</sub>Au<sub>33</sub>



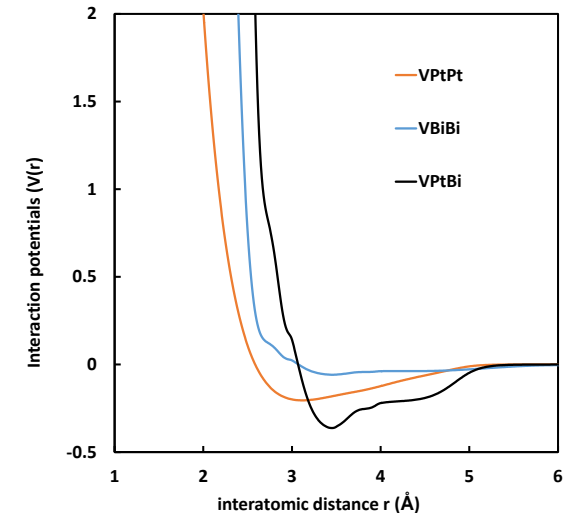
	1 <sup>st</sup> NN	2 <sup>nd</sup> NN	3 <sup>rd</sup> NN
Theoretical (fcc) 0.6Pt+0.2Ni+0.2Au	2.738 Å	3.872 Å	4.74 Å
Cluster 1	2.55 Å	(3.75 Å)	4.35 Å
Cluster 2	2.55 Å	3.65 Å	4.45 Å



# Pt<sub>x</sub>Bi<sub>y</sub> nanocatalyst growth



Snapshot of the final clusters at 20 ns. Argon atoms (4000) are not represented for clarity.  $n_{Pt} + n_{Bi} = 500$ . (a) Pt alone (b) Pt<sub>9</sub>Bi<sub>1</sub> (c) Pt<sub>8</sub>Bi<sub>2</sub>. Box size 16x16x16 nm<sup>3</sup>



Plots of the pair part of the EAM interaction potentials:

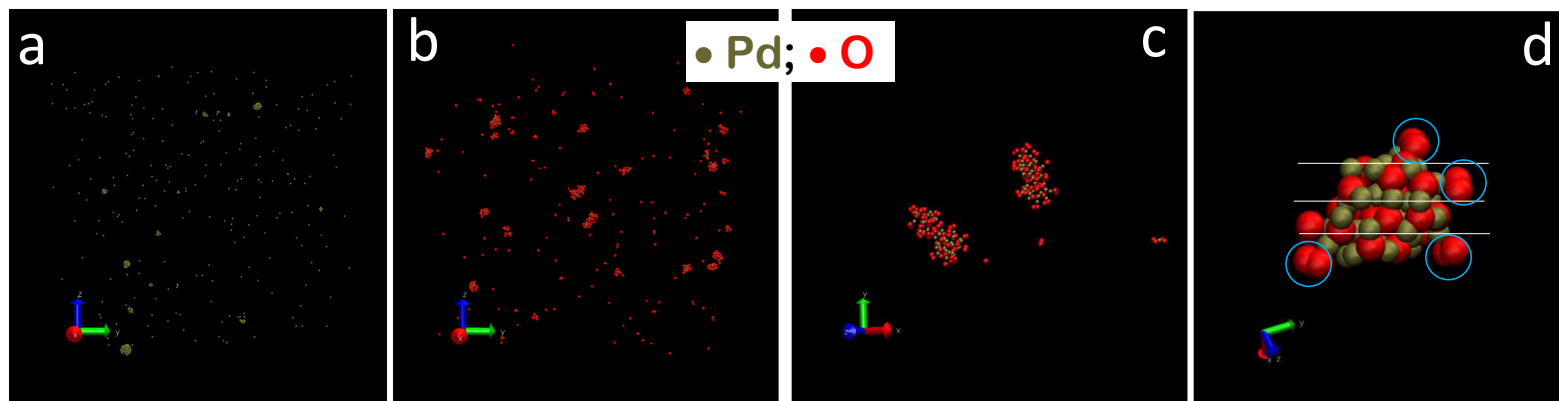
$$V_{PtPt}(r), V_{BiBi}(r), V_{PtBi}(r).$$

- Cluster atomic arrangements are typical of a crystalline structure of the Pt cores, with numbers of 1<sup>st</sup> nearest neighbors between 10 and 12 (i.e. consistent with fcc arrangement)
- Bi composition < 20% leads to cluster surfaces with both Pt and Bi, allowing catalytic activity enhancement.
- Pt/Bi atomic composition is not only globally preserved, but is also verified for each cluster

B.S.R. Kouamé et al, Insights on the unique electro-catalytic behavior of PtBi/C materials, *Electrochimica Acta* 329 (2020) 135161

# Molecular dynamics simulation of sputtering plasma catalysts growth: Reactive PdO nanocatalyst growth

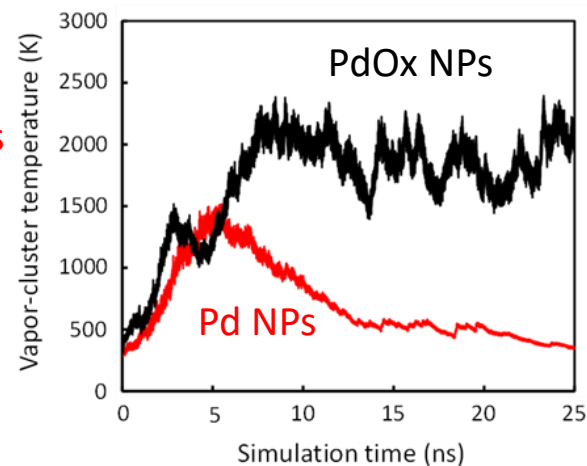
ReaxFF reactive variable charge potentials for Pd sputtering in Ar-O<sub>2</sub> gas mixture



Snapshot of (a-b) the overall Pd and PdO clusters at 25 ns simulation time (b-c) of the detailed PdO clusters.

First results: O addition -> no more free Pd, more PdO than Pd clusters

Ratio of  $N_{Ar}$  to  $N_{metal}$  estimated from experiments = 40 here;  
 $N_{Ar} = 20000$ ;  $N_{Pd} = 500$ ;  $N_{O} = 1000$ ; Box size : 40 x 40 x 40 nm<sup>3</sup>  
Integration time 0.25 fs → 1. 10<sup>8</sup> iterations



Potential ReaxFF : T. Senftle et al, J. Chem Phys 139 (2013) 044109

P. Brault et al, Molecular Dynamics simulations of initial Pd and PdO nanocluster growths in a magnetron gas aggregation source, Frontiers in Chemical Science and Engineering (2018) accepted.





# Hydrocarbon plasma and nanoparticles

$\mu$ wave plasma H<sub>2</sub>/10% CH<sub>4</sub>  
Initial conditions for MD simulations  
from 0D model (\*)

	1450 K	1650 K	1950K
H <sub>2</sub> (*)	1000	1000	1000
H	7	30	100
CH <sub>4</sub>	200	100	100
•CH <sub>3</sub>	2	5	7
C <sub>2</sub> H <sub>4</sub>	50	20	3
C <sub>2</sub> H <sub>2</sub>	400	500	600

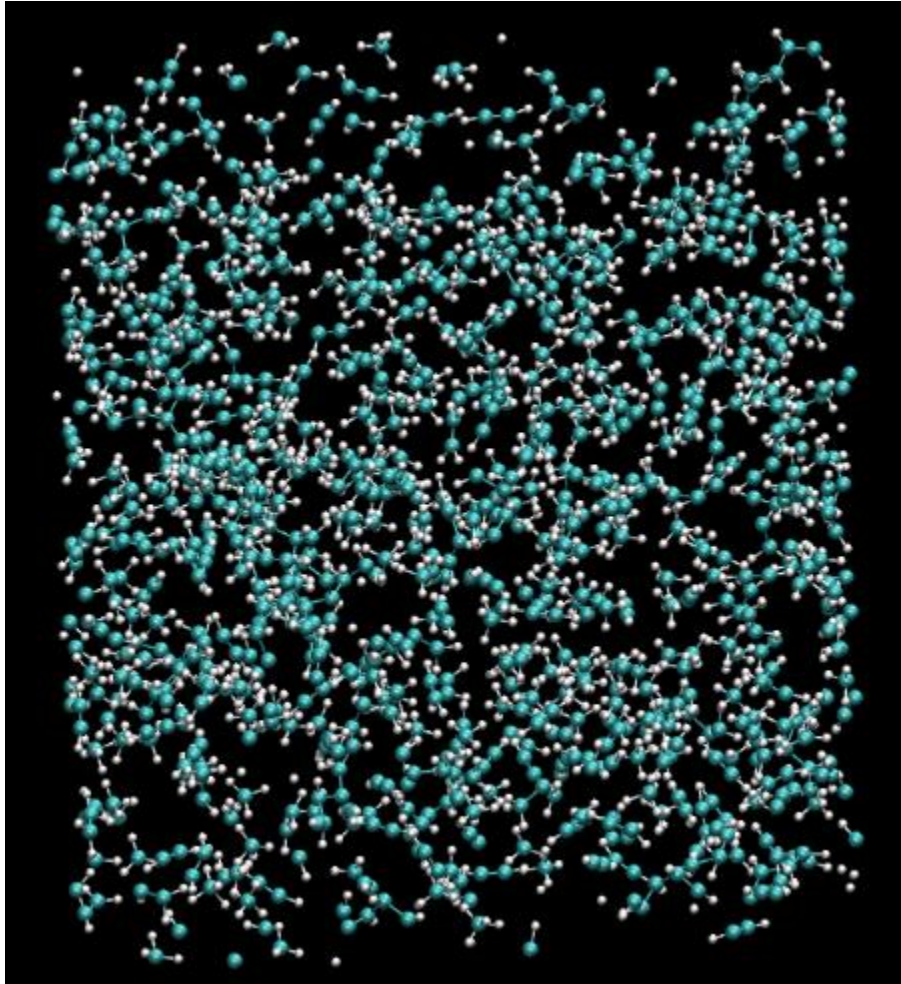
(\*) au lieu de 10000  
Suffisant pour thermostat

- Reactions can freely occur
- Bond formation energy is transported to walls by H<sub>2</sub> buffer gas, as in experiment (96% of molecules are H<sub>2</sub>). H atoms from H<sub>2</sub> are thermostated.



# Hydrocarbon plasma and nanoparticles

1450 K



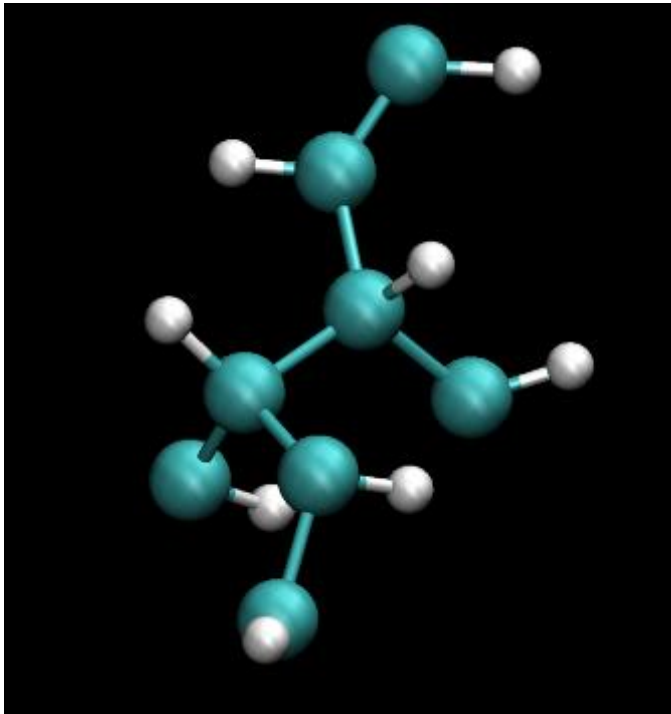
- ReaxFF potential
- NVT for  $H_2$  → thermostat
- NVE for other species
- $4 \times 4 \times 4 \text{ nm}^3$
- $dt = 0.25 \text{ fs}$ ;  $10^7$  timesteps
- 300h on 8 core Intel Xeon



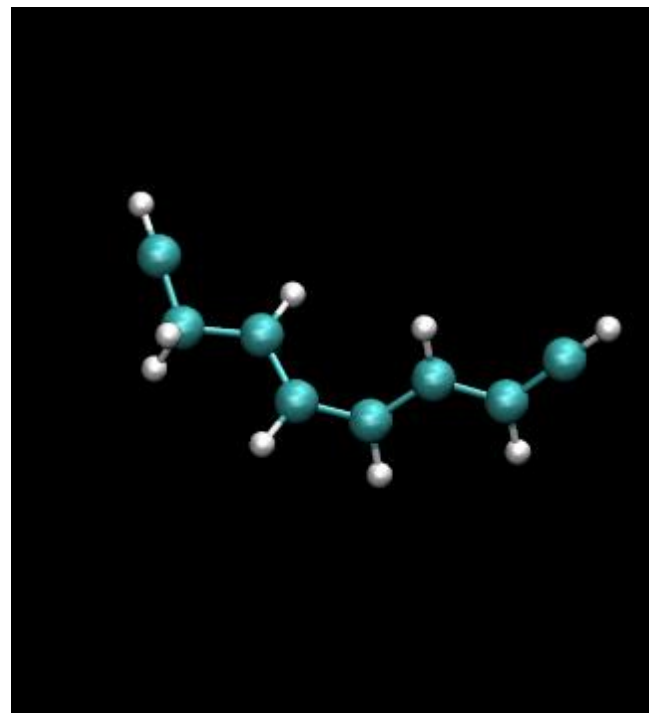
# Hydrocarbon plasma and nanoparticles

1450 K

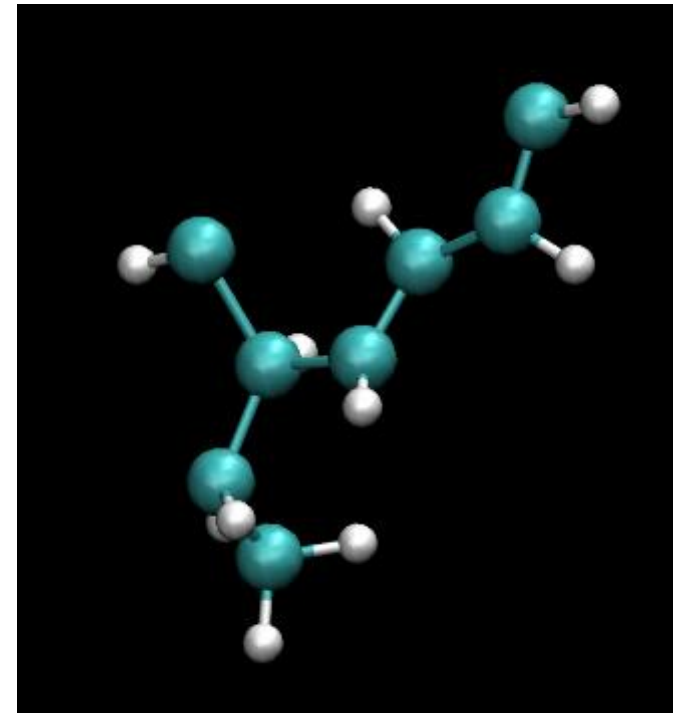
■ Negatively charged ions



#2603  
 $q = -0.45$



#2004  
 $q = -0.2$



#3088  
 $q = -0.25$